

Технические характеристики

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AGILENT ION PUMPS FEATURES AND BENEFITS

Ion Pump Evolution

- Since the late 1950's, when the ion pump was invented at Varian, now Agilent Technologies, many changes and technical improvements have taken place. Virtually all of the major innovations have come from us, from the first Diode Vaclon pump to the Triode, then to the StarCell series pumps, and the Vaclon *Plus*.



Vaclon Plus

- Vaclon *Plus* is a complete family of ion pumps, controllers, options, and accessories, designed to provide solutions to every application. Parameters such as operating pressure, the gas mixture to be pumped, the starting pressure, etc. can vary so dramatically that Varian, today Agilent, decided to develop dedicated ion pump solutions (including controllers and all other accessories) for different applications.
- The Vaclon *Plus* family includes Diode, Noble Diode, and StarCell pump versions that allow Agilent to provide the best technology for each field of application. The family is complemented by the new 4UHV Ion Pump controllers, that provide different power levels and interface capabilities.

Titanium Sublimation Combination Pumps (TSP)

- The titanium sublimation creates extra high getterable gas pumping speed while the ion pumping mechanisms handle the non-getterable gases such as argon and methane. The combination pump includes the cylindrical cryopanel and TSP source mounted to the extra port. Customized pump configurations are also available.



Wide Pumping Speed Range

- Miniature/Appendage pumps from 0.2 to 10 l/s
- Small/Medium pumps from 20 to 75 l/s
- Large size pumps from 150 to 2500 l/s
- Vaclon 150 "Slim Body" version available
- TSP/Combi pumps
- Custom solutions with special pumping speed, size, magnetic field



Vacuum Processing

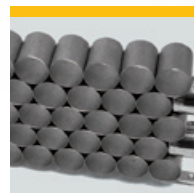
In order to ensure cleanliness, all pumps are:

- Factory processed at high temperature (450°) in ultra-high vacuum for a thorough outgassing of the body and all internal components
- Shipped under vacuum, and an RGA spectrum can be provided with each pump
- HE-Leak check



Application Specific Solutions

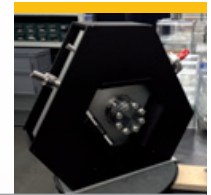
for SEM: a complete line of ion getter pumps dedicated to Electron Microscopy.



Element Cells and Insulators

- Cells' sizes and geometries are optimized in order to:
 - maximize the discharge intensity
 - maximize the pumping speed
- The special design of the ceramic insulators allows:
 - no buildup of sputtered conductive coating
 - longer pump life

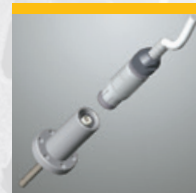
ION PUMPS



Custom Design

The pump body can be configured to meet optional requirements including:

- Cryopanel and TSP side or bottom mounted
- Integral heaters
- Additional roughing ports



Feedthroughs

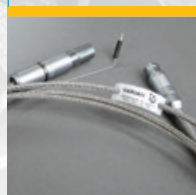
- Eliminate corrosion
- Implement the "High Voltage Cable Interlock"
- Provide an easy connection
- Prevent unintentional extraction
- Minimize overall dimensions



Pumping Elements

Three different types of pumping elements are available to cover all possible gas mixtures and optimize the application specific performances:

- Diode
- Noble Diode
- Our unique StarCell



Cables

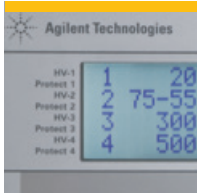
- Agilent cables have an "HV Safety Interlock" that prevents any chance of electrical shock
- If the cable is disconnected from the pump, the voltage is automatically cut off
- Available in different lengths
- Robust, flexible metal-shielded cable
- 10^7 Gy radiation tolerance



Heaters

- The pump can be supplied with heaters designed to perform the pump baking
- Minimize operational costs

THE NEW AGILENT 4UHV ION PUMP CONTROLLER FEATURES AND BENEFITS



Versatility

The 4UHV is available in different configurations, in order to independently power, control and monitor any combination of multiple pumps of different sizes, from one to four pumps, from 10 to 2500 l/s. For each number of pumps to be operated several options are available,
200 W for a single pump,
2 x 80 W or 2 x 200 W for two pumps,
2 x 80 + 200 W for three pumps,
4 x 80 W for four pumps.



Intelligence

To access the unit you can use analog or RS232/485 ports. The controller uses the same protocol as our other intelligent vacuum devices (Navigator turbo pump Controller and Inverter scroll & rotary vane pumps), giving you fast, convenient access to all elements of the vacuum system. Profibus and Ethernet communications available on request, please call Agilent for details.

More Choice and Flexibility

- The Vaclon *Plus* pump family is complemented by the new 4UHV Ion Pump controller, that provides different power levels and interface capabilities.
- The compact MiniVac controller and a dedicated TSP controller are also available.
- The new series of IPCU controller units completes Agilent's offer (see next pages).
- The existing range of ion pump controllers offers more choice and flexibility than ever before. With the latest in design features, they are simple and easy to operate; just select the right controller to fit your specific application.

4UHV - For Ultra High Vacuum

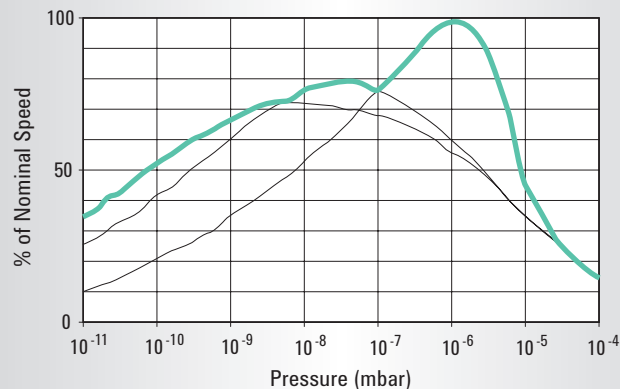
The new state-of-the-art Agilent 4UHV Ion Pump Controller operates up to four pumps simultaneously and independently. The 4UHV starts and controls ion pumps of any type (Diode, Noble Diode, StarCell) and size (from 10 to 2500 l/s). A large four-line LCD display allows simultaneous reading of individual pump voltage, current and pressure. The variable voltage feature ensures optimum pumping speed and pressure reading throughout the operating pressure range. Built-in set points, remote operation and RS232/485 computer interface are standard. Ethernet and Profibus are options.

Optimized Pumping Speed

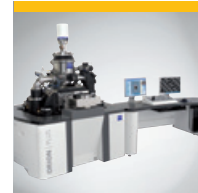
The 4UHV will select the right operating voltage to optimize the pumping speed of your ion pumps. By applying High Voltage in accordance with operating pressure, pumping speed performance is improved. This is because the energy with which the ion bombards the cathode is the nominal

applied HV, reduced by the space charge effect due to the electron cloud present in the ion pump cell. Since the space charge effect is pressure related, a variable HV is applied to maintain optimum bombardment energy, resulting in the best possible pumping performance at any pressure.

Pumping Speed vs Pressure at Different Voltages

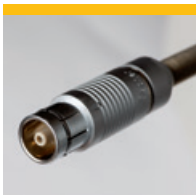


ION PUMPS



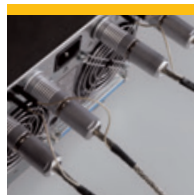
Low Noise

For SEM applications especially, the remaining AC component of the HV output was reduced to a minimum. It is much lower than in any other existing unit, eliminating the need for additional filters completely in many cases.



Safety

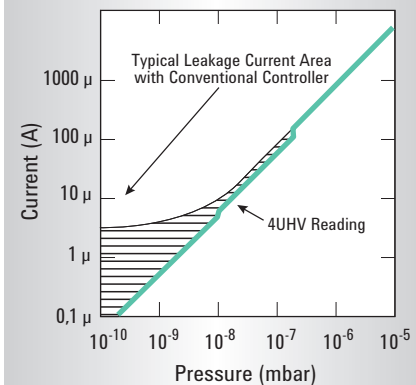
To protect you against high voltage the cable is equipped with an interlock system which immediately shuts down the high voltage when the plug is removed from the pump. The protect mode limits the current to protect the pump and the controller.



Pressure Reading

The 4UHV is preprogrammed to automatically convert current reading of any Vaclon Plus pump into pressure. Thanks to its ability to detect ion current as low as 10 nA, it allows pressure measurement in the 10^{-10} mbar range. To ensure reliable pressure reading down to the UHV region, the 4UHV optimizes the applied high voltage as a function of pressure. As a result, the leakage current of the ion pump is eliminated, thereby providing more accurate pressure readings.

Typical Current vs Pressure Curve



AGILENT SEM ION PUMPS FEATURES AND BENEFITS

The Agilent Advantage: Dedicated Solutions for SEM Applications

- Agilent is the only manufacturer to offer specially designed SEM ion pumps. These pumps are ideal for the high vacuum guns where stable vacuum and low leakage current is required to control and preserve the charged particle filament.
- The key to this superior performance is Agilent's patented anode design which uses contoured cells and simplified electrical elements. This insures stable current readings and lower particle generation.
- When combining the SEM ion pump on the gun with a StarCell ion pump on the lower column, Agilent ion pumps can offer a powerful combination optimised for modern E-beam columns.

SEM Ion Pumps are available on request; please ask Agilent for technical details.



Wide, Dedicated Range

- A complete range of SEM ion pumps from 10 to 75 l/s, tailored to your specific vacuum needs
- Small footprint for easier system integration



Dedicated Heaters

- Dedicated Heater for every pump size
- The new heaters are designed to perform a more effective pump baking
- Lower power and operational costs



Innovative SEM Anode Geometry

- Better current stability
- Lowest leakage current in the industry (< 10 nA)
- Double Shielded Ceramics
- Longer pump life
- Longer pressure stability
- Maximum uptime



Very Compact Design

- Improved design for:
- Lighter pump weight
 - Fast magnets replacement
 - Easy maintenance



IPCU3 / IPCU2 Power Supplies

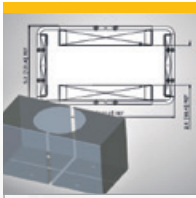
- Two versions: 3 or 2 supply channels
- Special low noise electronics for better SEM imaging
 - Battery backup (optional): up to 30 days 24/7 of battery life
 - Optional display and front panel

New 4UHV Controller

- Special low noise electronics for better SEM imaging



ION PUMPS



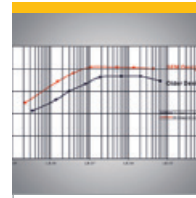
Dedicated Magnetic Stray Shields

- External magnetic shields for stray magnetic field reduction available individually on request



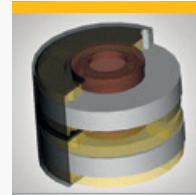
Agilent Feedthrough and Cables

- The HV Safety Interlock prevents any chance of electrical shock
- The voltage is automatically cut off as soon as the cable is disconnected from the pump
- Safer pump operation



Higher Pumping Speed

- Optimized magnetic circuit for max. performance in a very compact package
- Faster pump down



Available in Round Shape

Integrated ion pump/column allows:

- Optimum mass balancing
- Improved pumping conductance
- Compact and modular design
- Symmetric weight distribution for rugged column integration

Ion Pumps



RGA Guaranteed Ultimate Vacuum

- The pump is vacuum processed at 450 °C to outgas most of gases out of the pump body
- The pump is shipped under vacuum
- An RGA (Residual Gas Analysis) spectrum is available for each pump, to guarantee its performance and the cleanliness of the manufacturing process



Optical Baffle

Built-in Optical Baffle (optional) for:

- Minimized particle emission
- Minimum conductance reduction
- Total column protection
- Maximum e-gun life



Battery Power Supply

- Enables service without breaking vacuum
- Allows for column shipping under vacuum

TYPICAL APPLICATIONS FOR AGILENT VACION *PLUS* PUMPS



Courtesy: LBNL Advanced Light Source.



Courtesy PSI SLS.

Research and Development

Particle Accelerators & Synchrotron Light Sources

In these machines, electrically charged particles (electrons for the production of synchrotron light or ions for particle accelerators) are forced to follow a curved trajectory in a ring called a storage ring. Charged particles circulate for hours in the storage ring, at constant energy, in an ultra-high vacuum environment.

Before their injection into the storage ring, the particles first have to be accelerated inside an injection system composed of one or two accelerators (the Linac and the Booster). All along their path within the machine, the particles (electrons or ions) have to circulate inside a vacuum chamber. Otherwise, they would collide with the air molecules and would be absorbed very rapidly.

- **Linac**

The linac is a linear accelerator. The charged particles enter into a first RF cavity which accelerates them and at the same time groups them into bunches. They are then accelerated by a succession of RF cavities throughout the length of the linac. Vacuum within the linac can be created by Agilent Vaclon *Plus* pumps from 20 l/s to 70 l/s.

- **Booster**

Charged particles, which have already been accelerated in the linac, are accelerated even more strongly by the booster. The acceleration is produced by RF cavities through which the charged particles pass many times, gaining in energy at each pass. Once the level of maximum energy has been reached, the beam of particles is transferred from the booster to the storage ring. Vacuum in the booster is generally produced by small pumps. Small Agilent Vaclon *Plus* pumps fit this application perfectly.

- **Storage Ring**

Charged particles circulate inside the storage ring at constant energy. All along the ring there are curved sections as well as straight sections. The storage ring is placed inside a tunnel with very thick concrete walls in order to contain emitted radiation in case of beam loss. Ultra high vacuum is an absolute necessity in this part of the machine since the particles travel through the storage ring for hours. The less residual gas there is, the more focused the beam remains. Large Agilent Vaclon *Plus* pumps, in the 300 - 500 l/s range are used for this demanding application.

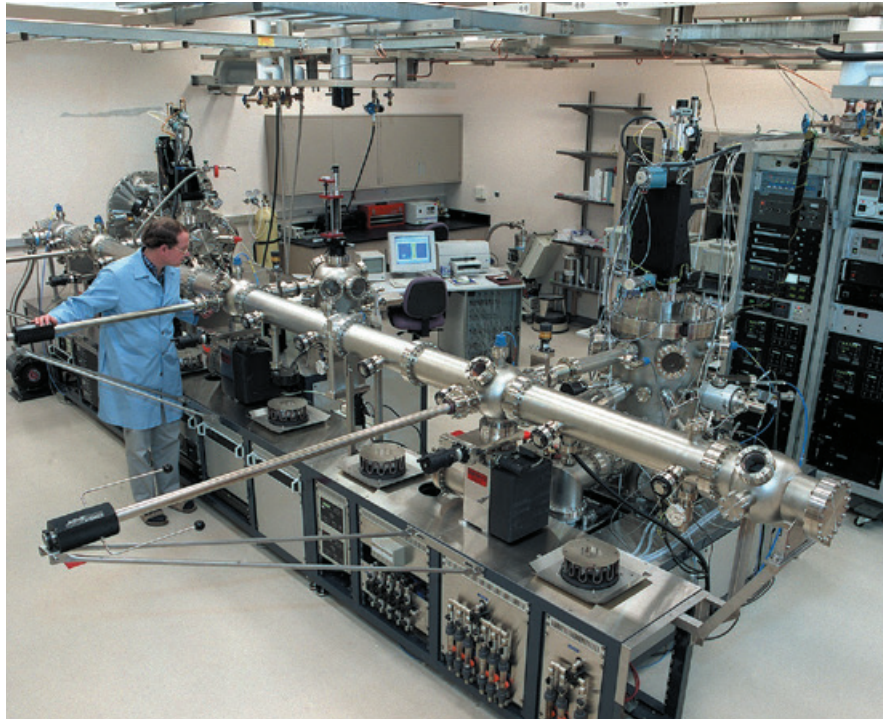
- **Front Ends**

The front end is the pipe work which transports the particles under a vacuum from the extraction zone up to the beamline outside of the tunnel of the ring. There you can find a beam shutter as well as devices allowing the isolation of the vacuum of the ring from that of the beamline, which is often of lower pressure. Agilent large pumps, as in for the storage ring, can be used in this part of the machine.

ION PUMPS



Courtesy of MedAustron.



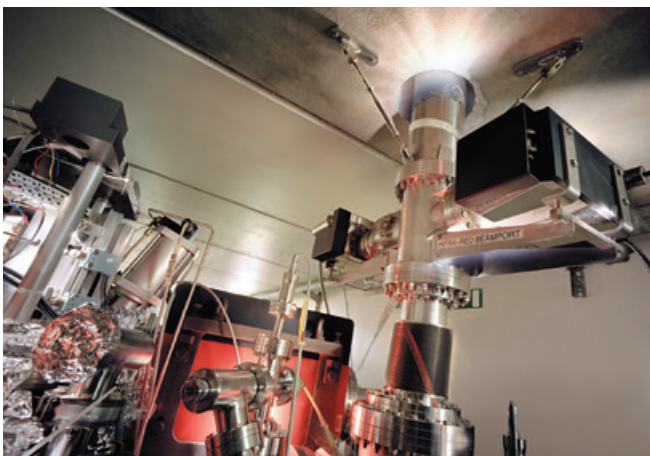
Courtesy Pacific Northwest National Laboratory.

- **Beam Lines**

The experimental hall, around the storage ring, houses the beamlines built tangentially to the ring. The beamlines are usually specialized in a field of research (such as biology, polymers, and magnetism) or an experimental method (such as diffraction, EXAFS, and imaging). Some of the longest beamlines are built outside the experimental hall. Generally, large pumps are used in this part, from 300 l/s to 500 l/s. They can be combined with TSP and cryopanel in order to pump even the lightest molecules.

- **Miscellaneous Projects**

Some fundamental research projects that use very sensitive equipment (necessitating ultra-high vacuum with no mechanical vibration) will find the solution in Agilent *Vaclon Plus* pumps. The new gravitational waves detectors (GWD) such as VIRGO in Italy and LIGO in the USA use Agilent pumps to produce and maintain the required vacuum.



Courtesy P. Ginter - ESRF Grenoble.



Courtesy P. Ginter - ESRF Grenoble.

AGILENT ION PUMPS TYPICAL APPLICATIONS

Mass Spectrometry

- Analytical systems that use focused charged particle beams (CPB) and certain types of mass spectrometers such as magnetic sector or Fournier Transfer often require ultra-high vacuum.
- These applications have very stringent performance requirements for sensitivity, resolution, sample throughput and measurement repeatability. These requirements are driven by the need to analyze ever-smaller samples, especially in semiconductor, manufacturing, and other high-tech applications.
- In general these applications require very clean vacuum pumping, and only Vaclon pumps can certify the required level of cleanliness because Agilent is the only ion pump manufacturer that bakes each pump in a vacuum furnace, and supply each pump with an RGA scan.
- Agilent offers a full range of pumps, from 0.2 l/s up to 2500 l/s, as well as combination and custom pumps so analytical system designers can meet all their vacuum requirements from one supplier.
- Over 50 years of ion pump experience makes Agilent uniquely qualified to supply customized solutions for special applications.

Nanotechnologies

- Agilent's line of high performance Vaclon ion pumps are well suited for the vacuum requirements of Transmission Electron Microscopes (TEM), Scanning Electron Microscopes (SEM), Focused Ion Beam (FIB) and Surface Analysis equipments.
- **Agilent is the only manufacturer to offer SEM application-specific ion pumps with unique anode design**
- The Diode SEM pump with its extremely low leakage current is ideal for the gun section of the column.
- The StarCell pump element with its unique design is the ideal solution for the high pressure operation of the columns. StarCell is also the best pump for noble gases or hydrogen.
- Agilent completes its offering to the microscope manufacture with a full line of controller/power supplies including the low cost power supplies and the full feature, multiple controllers.
- With the addition of Agilent complete line of oil-free, low vibration turbo pumps - ideal for sample chamber vacuum requirements – roughing pumps and vacuum gauges, Agilent can supply all the vacuum components required for electron microscopes.



Industrial Vacuum Processes

Different applications in industrial sectors such as telecommunication, defense, medical and others make use of Vaclon pumps to process and maintain essential components under vacuum. Most of the core equipment in these sectors requires the use of different electron devices including:

- **Microwave tubes and devices**
- **Power grid tubes**
- **X-ray imaging tubes and devices**
- **X-ray sources**

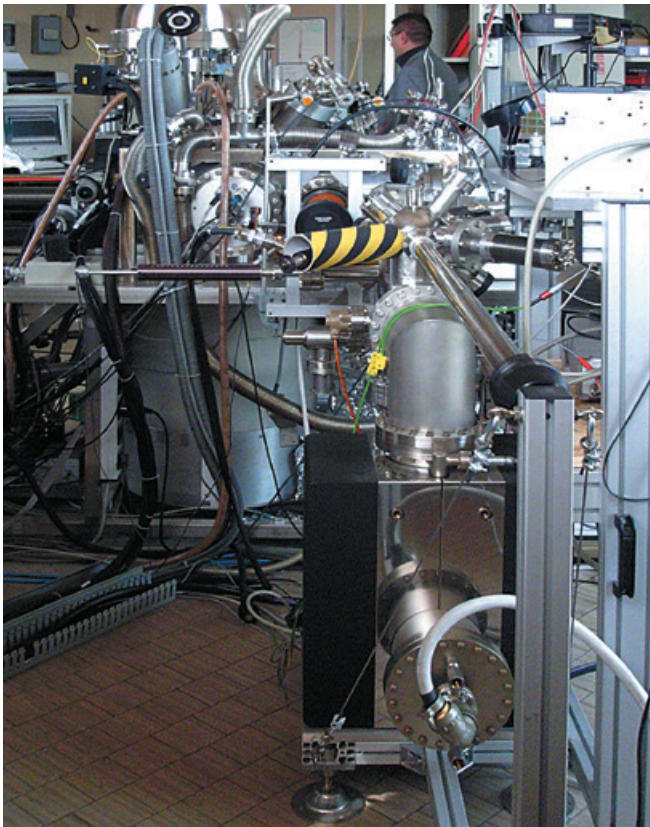
In the processing cycle of these types of electron devices, small ion pumps from 10 l/s to 50 l/s are being used. Special tube sizes or special applications may require even bigger ion pumps up to 300-500 l/s. Vaclon pumps are often being used in combination with Turbo Molecular Pumps, backing pumps and other components out of the wide range of Agilent products.

After processing, frequently these electron devices are being equipped with so-called appendage ion pumps in the range of 0.2 l/s to 10 l/s for the purpose of maintaining the electron tube under vacuum for its operational lifetime.

The first ion pump was invented in the late 1950's, for the production of high-quality vacuum tubes used in radar technology. From this point on, Vaclon pumps set the pace in



ION PUMPS



Courtesy University of Modena.

the industrial field for a wide range of applications using vacuum processed electron devices used worldwide in:

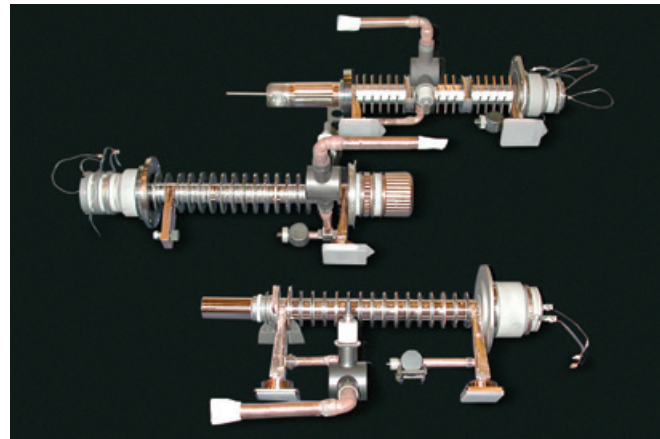
- **Space**

Electron devices are essential to various space programs, from satellite services and earth observation satellites to space probes. Microwave tubes and devices are vital tools, which link people and satellites in order to enable global communications. Spaceborne tubes are the power generators for the transponders carried on satellites. They retransmit TV or telecommunication signals back to the ground. The electron tubes used for this application are Travelling Wave Tubes. In these tubes, amplification is produced under vacuum by the interaction between a beam of electrons and the Radio-Frequency (RF) wave.

- **Telecommunications**

Microwave tubes, devices like Traveling Wave Tubes (TWTs) and Klystrons (powerful radio vacuum tubes) are widely used in civil and military telecommunication networks and equipment used for:

- Satellite and terrestrial communication
- High data-rate transmissions for High Speed Internet and Wireless Cable
- Broadband high speed data
- Point-to-point and point-to-multipoint microwave links.



Courtesy CPI.

- **Broadcast**

Radio and TV broadcasters and transmitter manufacturers use electron devices in their equipment to enable high power transmission or digital broadcasting. Power grid tubes or microwave tubes are being used in AM radio, FM radio, VHF TV, UHF TV or digital TV transmitters and amplifiers.

- **Medical**

Radiological equipment manufacturers use electron devices for critical components in the radiological chain, such as X-ray image intensifiers and radiological imaging units for diagnostics, as well as medical linear accelerators for radiation therapy. Typical fields of application include:

- Medical Imaging (X-ray image tubes and devices)
- Radiation Therapy (high power Klystrons, LINAC)
- Magnetic Resonance Imaging.

- **Defense**

Microwave tubes and devices are key components in equipment and systems used for different defense applications:

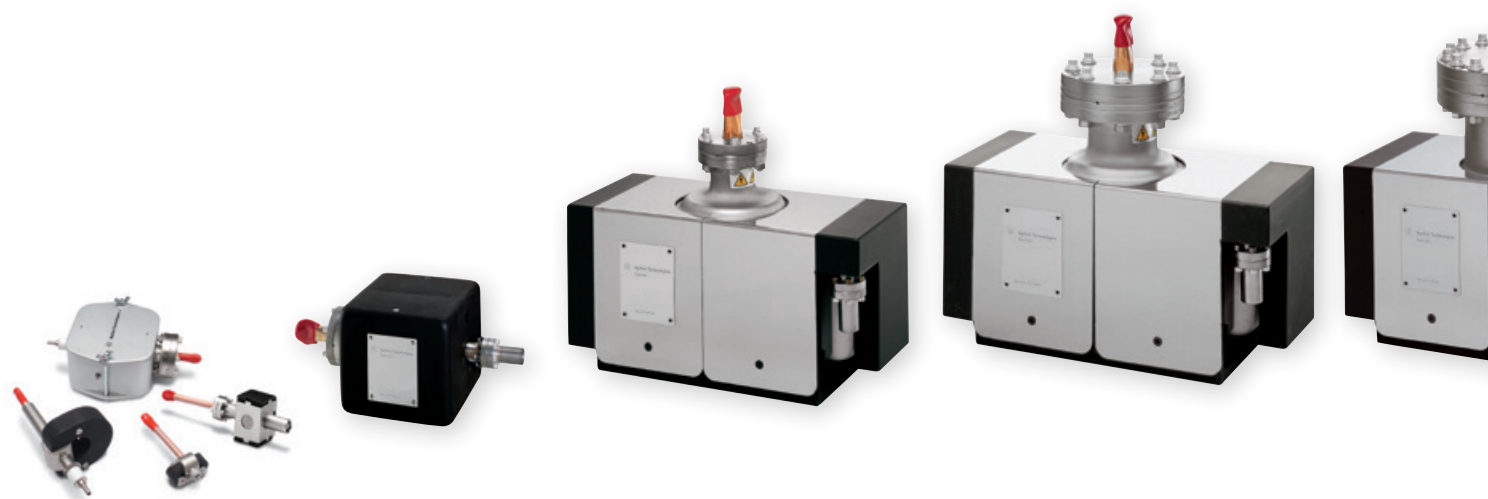
- Radar (ground based or airborne)
- Electronic Countermeasures (ECM)
- Smart Weapons & Electronic Warfare
- Missile guidance & Missile seekers

- **Industrial and Others**

Several industrial processes make use of RF & Microwave tubes. Some examples are heat treating, Plastic welding, Food processing, Textile manufacturing, Film curing & drying. Other applications make use of X-ray tubes for non-destructive testing methods.

AGILENT ION PUMP MODELS

	Miniature Pump	2 l/s Pump	10 l/s Pump	Vaclon Plus 20		
Inlet flange				2 ¼" OD CFF (NW 35)		
Element type	Diode	Diode	Diode	Star Cell	Noble Diode	Diode
Pumping speed (l/s) (saturated pump at 1 ⁻⁶ mbar) Nitrogen	0.2	2	10	20	22	27
Operating life (hours) (at 1 ⁻⁶ mbar)	N/A	8,000	40,000	80,000	50,000	50,000
Maximum starting pressure (mbar)	1 x 10 ⁻⁴	1 x 10 ⁻⁴	≤ 1 x 10 ⁻⁴	<10 ⁻²	<10 ⁻³	<10 ⁻³
Maximum baking temperature (°C)	400 (without magnet) 150 (with magnet)	400 (without magnet) 150 (with magnet)	350	350	350	350
Weight kg (lbs)	Net 0.3 (0.66) Shipping 0.6 (1.33)	Net 0.3 (0.66) Shipping 0.6 (1.33)	Without magnet 4 (9)	Net 7 (15) Shipping 11 (24)		
SEM version available on request	–	–	+	+		



ION PUMPS

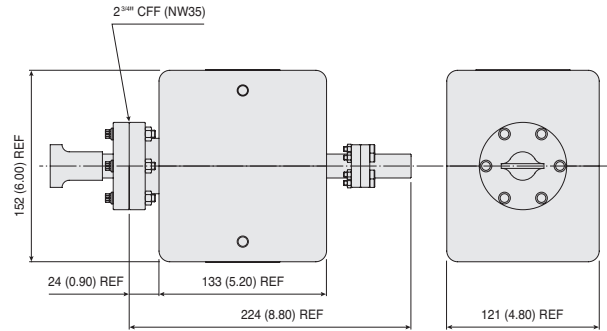
	Vaclon Plus 40			Vaclon Plus 55			Vaclon Plus 75			Vaclon Plus 150*			Vaclon Plus 300			Vaclon Plus 500		
	2 ¾" OD CFF (NW 35)			4 ½" OD CFF (NW 63)			6" OD CFF (NW 100)			6" OD CFF (NW 100)			8" OD CFF (NW 150)			8" OD CFF (NW 150)		
	Star Cell	Noble Diode	Diode	Star Cell	Noble Diode	Diode	Star Cell	Noble Diode	Diode	Star Cell	Noble Diode	Diode	Star Cell	Noble Diode	Diode	Star Cell	Noble Diode	Diode
	34	36	40	50	53	55	65	68	75	125	135	150	240	260	300	410	440	500
0	80,000	50,000	50,000	80,000	50,000	50,000	80,000	50,000	50,000	80,000	50,000	50,000	80,000	50,000	50,000	80,000	50,000	50,000
3	<10 ⁻²	<10 ⁻³	<10 ⁻³	<10 ⁻²	<10 ⁻³	<10 ⁻³	<10 ⁻²	<10 ⁻³	<10 ⁻³	<10 ⁻²	<10 ⁻³	<10 ⁻³	<10 ⁻²	<10 ⁻³	<10 ⁻³	<10 ⁻²	<10 ⁻³	<10 ⁻³
	350	350	350	350	350	350	350	350	350	350	350	350	350	350	350	350	350	350
	Net 17 (37) Shipping 21 (46)			Net 18 (39) Shipping 22 (48)			Net 19 (42) Shipping 23 (51)			Net 43 (94) Shipping 53 (110)			Net 69 (149) Shipping 84 (185)			Net 120 (264) Shipping 135 (297)		
	+			+			+			-			-			-		

*150 "Slim Body" available



AGILENT ION PUMP MODELS

▶ Agilent Vaclon Plus 20



Dimensions: millimeters (inches)

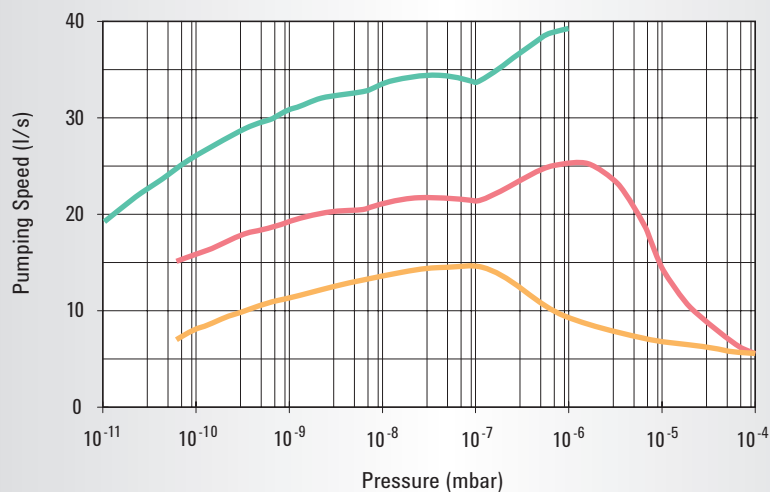
Technical Specifications

	StarCell	Noble Diode	Diode
Nominal pumping speed for Nitrogen (*) (l/s)	20	22	27
Operating life at 1×10^{-6} mbar (hours)	80,000	50,000	50,000
Maximum starting pressure (mbar)	$\leq 5 \times 10^{-2}$	$\leq 1 \times 10^{-3}$	$\leq 1 \times 10^{-3}$
Ultimate pressure	Below 10^{-11}		
Inlet flange	2 3/4" CFF (NW 35) AISI 304 ESR SST		
Maximum baking temperature (°C)	350		
Weight, kg (lbs) (with ferrite magnet)	Net 7 (15), Shipping 11 (24)		

(*) Tested according to ISO/DIS 3556-1-1992

SEM version available on request
 Customized design available on request

Vaclon Plus 20 - Pumping Speed vs Pressure



— Nitrogen unsaturated Diode — Nitrogen saturated Diode — Argon saturated StarCell

Ordering Information

Description	Part Number
Pumps	
Diode with Ferrite magnets	9191115
Diode without magnets	9191114
StarCell with Ferrite magnets	9191145
StarCell with Sm-Co magnets	9191146
StarCell without magnets	9191144
<i>Noble Diode versions available on request</i>	
4UHV Controller	
200 W neg	9299010
200 W pos	9299011
2 x 80 W neg	9299200
2 x 80 W pos	9299201
2 x 200 W neg	9299020
2 x 200 W pos	9299021
1 x 200 W pos & 1 x 200 W neg	9299022
4 x 80 W neg	9299400
4 x 80 W pos	9299401
2 x 80 W pos & 2 x 80 W neg	9299402
2 x 80 W neg & 1 x 200 W neg	9299210
2 x 80 W pos & 1 x 200 W pos	9299211
2 x 80 W pos & 1 x 200 W neg	9299212
2 x 80 W neg & 1 x 200 W pos	9299213

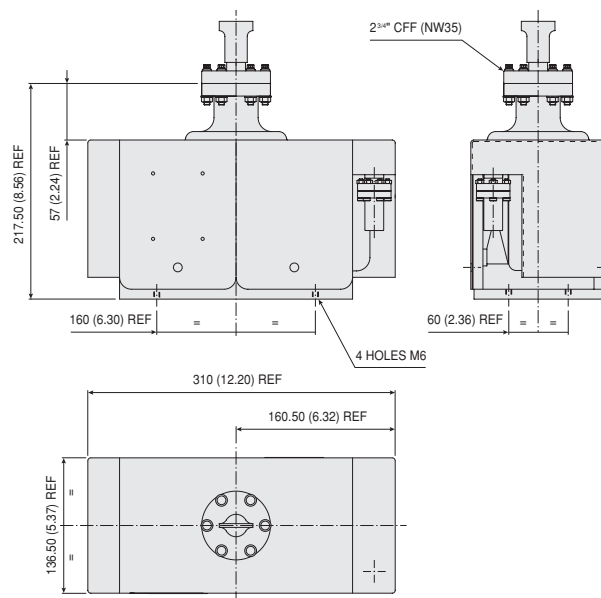
Description	Part Number
HV Cables	
HV Bakeable cable, radiation resistant, 4 m (13 ft.) long, with interlock	9290705
HV Bakeable cable, radiation resistant, 7 m (23 ft.) long, with interlock	9290707
HV Bakeable cable, radiation resistant, 10 m (33 ft.) long, with interlock	9290708
HV Bakeable cable, radiation resistant, 20 m (66 ft.) long, with interlock	9290709
Replacement Parts	
HV Feedthrough with interlock	9595125
Vaclon Plus 20 Diode Ferrite magnet assembly	9191001
Vaclon Plus 20 Noble Diode Ferrite magnet assembly	9191002
Vaclon Plus 20 StarCell Ferrite magnet assembly	9191004
Heaters* (Input Power 140 W) 120 V	9191110
Heaters* (Input Power 140 W) 220 V	9191111

* To order heaters for replacement or upgrading of existing pumps, please contact your local Agilent Vacuum Technologies representative.

Diode, Noble Diode	positive
StarCell, Triode	negative
(see page 42)	

AGILENT ION PUMP MODELS

▶ Agilent Vaclon Plus 40



Dimensions: millimeters (inches)

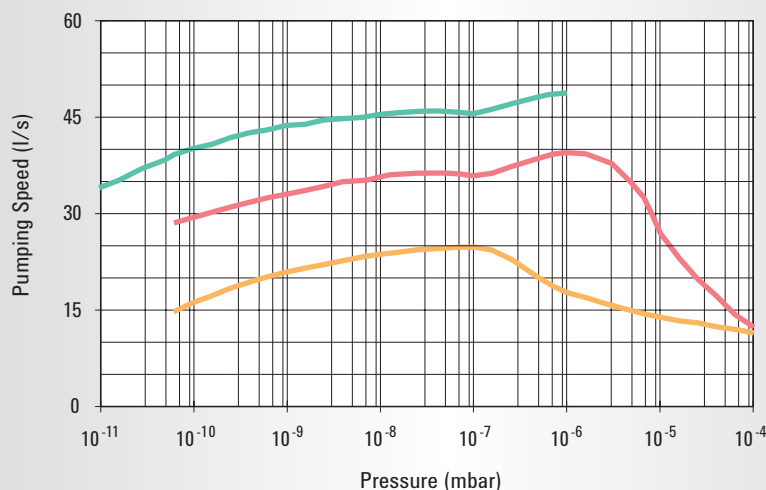
Technical Specifications

	StarCell	Noble Diode	Diode
Nominal pumping speed for Nitrogen (*) (l/s)	34	36	40
Operating life at 1×10^{-6} mbar (hours)	80,000	50,000	50,000
Maximum starting pressure (mbar)	$\leq 5 \times 10^{-2}$	$\leq 1 \times 10^{-3}$	$\leq 1 \times 10^{-3}$
Ultimate pressure	Below 10^{-11}		
Inlet flange	2 3/4" CFF (NW 35) AISI 304 ESR SST		
Maximum baking temperature (°C)	350		
Weight, kg (lbs)	17 (37)		

(*) Tested according to ISO/DIS 3556-1-1992

SEM version available on request
 Customized design available on request

Vaclon Plus 40 - Pumping Speed vs Pressure



— Nitrogen unsaturated Diode — Nitrogen saturated Diode — Argon saturated StarCell

Ordering Information

Description	Part Number
Pumps	
Diode	9191210
Diode with additional 2 3/4" CFF port	9191213
Diode without magnets	9191214
StarCell	9191240
StarCell with additional 2 3/4" CFF port	9191243
StarCell without magnets	9191244

Noble Diode versions available on request

4UHV Controller	
200 W neg	9299010
200 W pos	9299011
2 x 80 W neg	9299200
2 x 80 W pos	9299201
2 x 200 W neg	9299020
2 x 200 W pos	9299021
1 x 200 W pos & 1 x 200 W neg	9299022
4 x 80 W neg	9299400
4 x 80 W pos	9299401
2 x 80 W pos & 2 x 80 W neg	9299402
2 x 80 W neg & 1 x 200 W neg	9299210
2 x 80 W pos & 1 x 200 W pos	9299211
2 x 80 W pos & 1 x 200 W neg	9299212
2 x 80 W neg & 1 x 200 W pos	9299213

Description	Part Number
HV Cables	
HV Bakeable cable, radiation resistant, 4 m (13 ft.) long, with interlock	9290705
HV Bakeable cable, radiation resistant, 7 m (23 ft.) long, with interlock	9290707
HV Bakeable cable, radiation resistant, 10 m (33 ft.) long, with interlock	9290708
HV Bakeable cable, radiation resistant, 20 m (66 ft.) long, with interlock	9290709

Replacement Parts	
HV Feedthrough with interlock	9595125
Heaters*/** (Input Power 250 W) 120 V	9190071
Heaters*/** (Input Power 250 W) 220 V	9190070

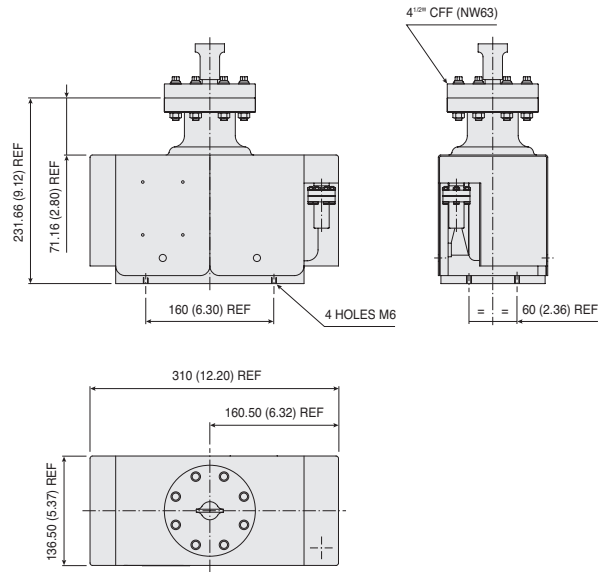
* To order heaters for replacement or upgrading of existing pumps, please contact your local Agilent Vacuum Technologies representative.

** cCSAus marked version available on request.

Diode, Noble Diode	positive
StarCell, Triode	negative
(see page 42)	

AGILENT ION PUMP MODELS

▶ Agilent Vaclon Plus 55



Dimensions: millimeters (inches)

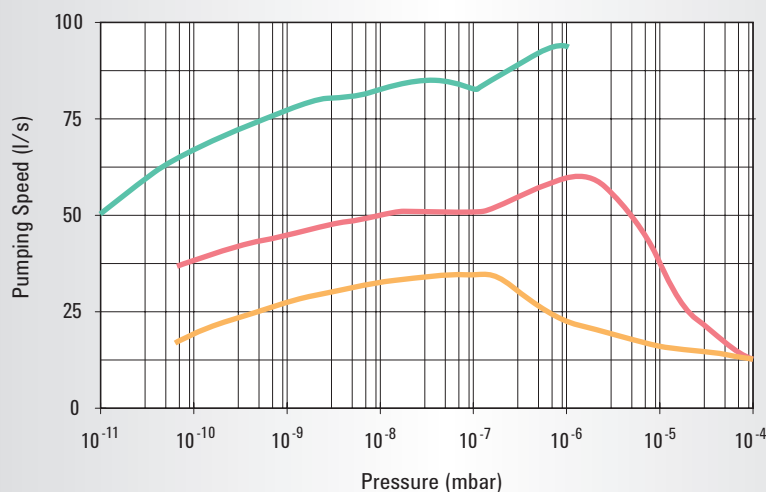
Technical Specifications

	StarCell	Noble Diode	Diode
Nominal pumping speed for Nitrogen (*) (l/s)	50	53	55
Operating life at 1×10^{-6} mbar (hours)	80,000	50,000	50,000
Maximum starting pressure (mbar)	$\leq 5 \times 10^{-2}$	$\leq 1 \times 10^{-3}$	$\leq 1 \times 10^{-3}$
Ultimate pressure	Below 10^{-11}		
Inlet flange	4 3/4" CFF (NW 63) AISI 304 ESR SST		
Maximum baking temperature (°C)	350		
Weight, kg (lbs)	18 (39)		

(*) Tested according to ISO/DIS 3556-1-1992

SEM version available on request
 Customized design available on request

Vaclon Plus 55 - Pumping Speed vs Pressure



— Nitrogen unsaturated Diode — Nitrogen saturated Diode — Argon saturated StarCell

Ordering Information

Description	Part Number
Pumps	
Diode	9191310
Diode with additional 2 3/4" CFF port	9191313
Diode without magnets	9191314
StarCell	9191340
StarCell with additional 2 3/4" CFF port	9191343
StarCell without magnets	9191344
<i>Noble Diode versions available on request</i>	
4UHV Controller	
200 W neg	9299010
200 W pos	9299011
2 x 80 W neg	9299200
2 x 80 W pos	9299201
2 x 200 W neg	9299020
2 x 200 W pos	9299021
1 x 200 W pos & 1 x 200 W neg	9299022
4 x 80 W neg	9299400
4 x 80 W pos	9299401
2 x 80 W pos & 2 x 80 W neg	9299402
2 x 80 W neg & 1 x 200 W neg	9299210
2 x 80 W pos & 1 x 200 W pos	9299211
2 x 80 W pos & 1 x 200 W neg	9299212
2 x 80 W neg & 1 x 200 W pos	9299213

Description	Part Number
HV Cables	
HV Bakeable cable, radiation resistant, 4 m (13 ft.) long, with interlock	9290705
HV Bakeable cable, radiation resistant, 7 m (23 ft.) long, with interlock	9290707
HV Bakeable cable, radiation resistant, 10 m (33 ft.) long, with interlock	9290708
HV Bakeable cable, radiation resistant, 20 m (66 ft.) long, with interlock	9290709

Replacement Parts		
HV Feedthrough with interlock		9595125
Heaters*/** (Input Power 250 W)	120 V	9190071
Heaters*/** (Input Power 250 W)	220 V	9190070

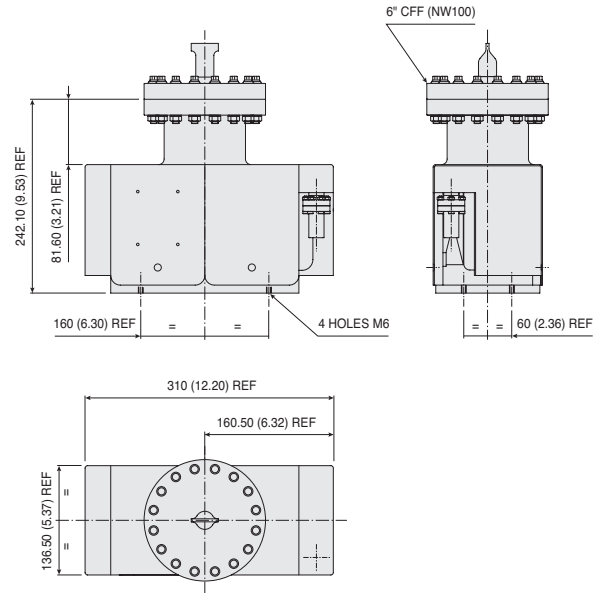
* To order heaters for replacement or upgrading of existing pumps, please contact your local Agilent Vacuum Technologies representative.

** cCSAus marked version available on request.

Diode, Noble Diode	positive
StarCell, Triode	negative
(see page 42)	

AGILENT ION PUMP MODELS

▶ Agilent Vaclon Plus 75



Dimensions: millimeters (inches)

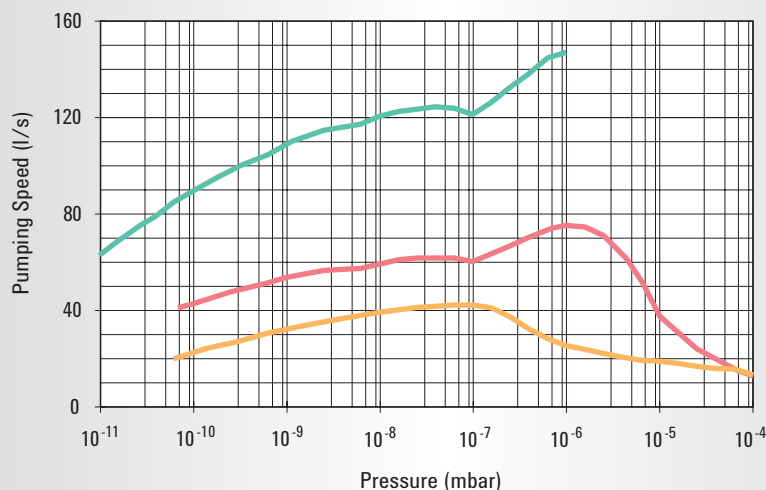
Technical Specifications

	StarCell	Noble Diode	Diode
Nominal pumping speed for Nitrogen (*) (l/s)	65	68	75
Operating life at 1×10^{-6} mbar (hours)	80,000	50,000	50,000
Maximum starting pressure (mbar)	$\leq 5 \times 10^{-2}$	$\leq 1 \times 10^{-3}$	$\leq 1 \times 10^{-3}$
Ultimate pressure	Below 10^{-11}		
Inlet flange	6" CFF (NW 100) AISI 304 ESR SST		
Maximum baking temperature (°C)	350		
Weight, kg (lbs)	19 (42)		

(*) Tested according to ISO/DIS 3556-1-1992

SEM version available on request
 Customized design available on request

Vaclon Plus 75 - Pumping Speed vs Pressure



— Nitrogen unsaturated Diode — Nitrogen saturated Diode — Argon saturated StarCell

Ordering Information

Description	Part Number
Pumps	
Diode	9191410
Diode with additional 2 3/4" CFF port	9191413
Diode without magnets	9191414
StarCell	9191440
StarCell with additional 2 3/4" CFF port	9191443
StarCell without magnets	9191444

Noble Diode versions available on request

4UHV Controller	
200 W neg	9299010
200 W pos	9299011
2 x 80 W neg	9299200
2 x 80 W pos	9299201
2 x 200 W neg	9299020
2 x 200 W pos	9299021
1 x 200 W pos & 1 x 200 W neg	9299022
4 x 80 W neg	9299400
4 x 80 W pos	9299401
2 x 80 W pos & 2 x 80 W neg	9299402
2 x 80 W neg & 1 x 200 W neg	9299210
2 x 80 W pos & 1 x 200 W pos	9299211
2 x 80 W pos & 1 x 200 W neg	9299212
2 x 80 W neg & 1 x 200 W pos	9299213

Description	Part Number
HV Cables	
HV Bakeable cable, radiation resistant, 4 m (13 ft.) long, with interlock	9290705
HV Bakeable cable, radiation resistant, 7 m (23 ft.) long, with interlock	9290707
HV Bakeable cable, radiation resistant, 10 m (33 ft.) long, with interlock	9290708
HV Bakeable cable, radiation resistant, 20 m (66 ft.) long, with interlock	9290709

Replacement Parts	
HV Feedthrough with interlock	9595125
Heaters*/** (Input Power 250 W) 120 V	9190071
Heaters*/** (Input Power 250 W) 220 V	9190070

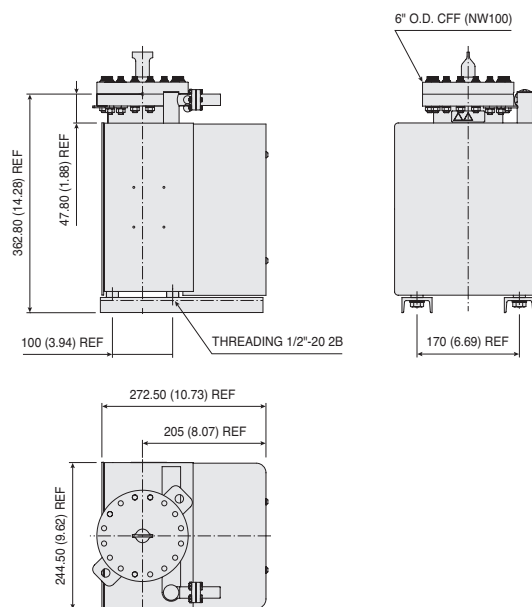
* To order heaters for replacement or upgrading of existing pumps, please contact your local Agilent Vacuum Technologies representative.

** cCSAus marked version available on request.

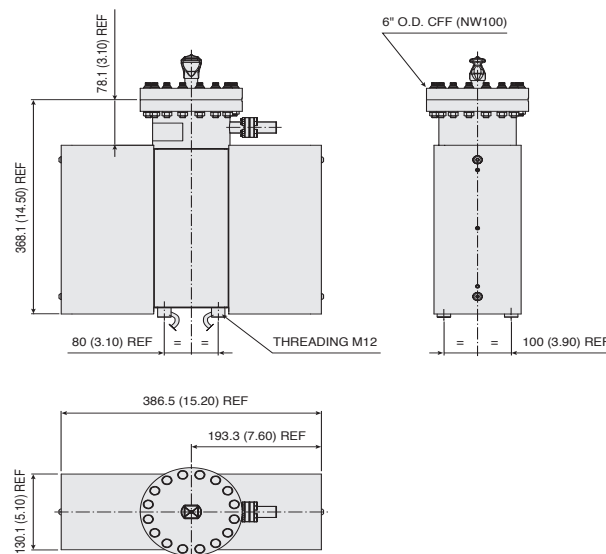
Diode, Noble Diode	positive
StarCell, Triode	negative
(see page 42)	

AGILENT ION PUMP MODELS

▶ Agilent Vaclon Plus 150



Vaclon Plus 150 I/s SLIM BODY version available



Technical Specifications

Dimensions: millimeters (inches)

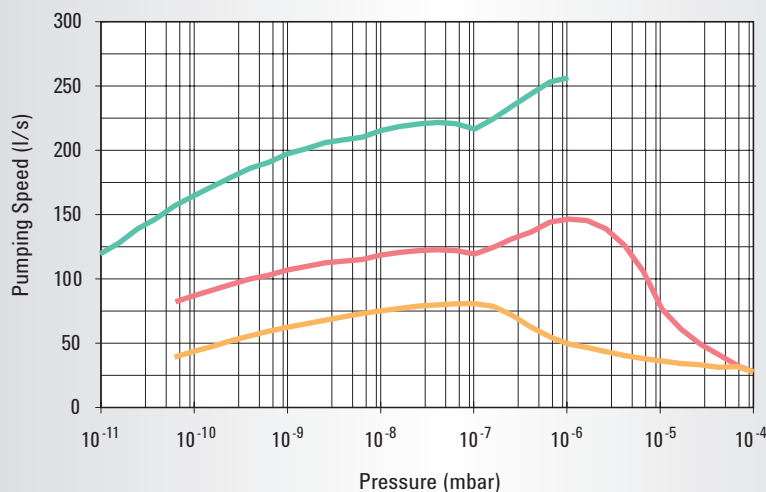
	StarCell	Noble Diode	Diode
Nominal pumping speed for Nitrogen (*) (l/s)	125	135	150
Operating life at 1×10^{-6} mbar (hours)	80,000	50,000	50,000
Maximum starting pressure (mbar)	$\leq 5 \times 10^{-2}$	$\leq 1 \times 10^{-3}$	$\leq 1 \times 10^{-3}$
Ultimate pressure	Below 10^{-11}		
Inlet flange	6" CFF (NW 100) AISI 304 ESR		
Maximum baking temperature (°C)	350		
Weight, kg (lbs)	43 (94)		

(*) Tested according to ISO/DIS 3556-1-1992

Customized design available on request

ION PUMPS

Vaclon Plus 150 - Pumping Speed vs Pressure



— Nitrogen unsaturated Diode — Nitrogen saturated Diode — Argon saturated StarCell

Ordering Information

Description	Part Number
Pumps	
Diode	9191510
Diode with heaters installed 120 V	9191511
Diode with heaters installed 220 V	9191512
Diode double-ended	9191550
Diode double-ended with heaters installed 120 V	9191551
Diode double-ended with heaters installed 220 V	9191552
StarCell	9191540
StarCell with heaters installed 120 V	9191541
StarCell with heaters installed 220 V	9191542
StarCell double-ended	9191580
StarCell double-ended with heaters installed 120 V	9191581
StarCell double-ended with heaters installed 220 V	9191582
Diode "slim body"	9191510M004
Diode "slim body" with heaters installed 120 V	9191511M003
Diode "slim body" with heaters installed 220 V	9191512M008
StarCell "slim body"	9191540M012
StarCell "slim body" with heaters installed 120 V	9191541M003
StarCell "slim body" with heaters installed 220 V	9191542M010

Noble Diode versions available on request

4UHV Controller

200 W neg	9299010
200 W pos	9299011
2 x 80 W neg	9299200
2 x 80 W pos	9299201
2 x 200 W neg	9299020
2 x 200 W pos	9299021
1 x 200 W pos & 1 x 200 W neg	9299022
4 x 80 W neg	9299400
4 x 80 W pos	9299401

Description	Part Number
4UHV Controller (cont'd)	
2 x 80 W pos & 2 x 80 W neg	9299402
2 x 80 W neg & 1 x 200 W neg	9299210
2 x 80 W pos & 1 x 200 W pos	9299211
2 x 80 W pos & 1 x 200 W neg	9299212
2 x 80 W neg & 1 x 200 W pos	9299213

HV Cables

HV Bakeable cable, radiation resistant, 4 m (13 ft.) long, with interlock	9290705
HV Bakeable cable, radiation resistant, 7 m (23 ft.) long, with interlock	9290707
HV Bakeable cable, radiation resistant, 10 m (33 ft.) long, with interlock	9290708
HV Bakeable cable, radiation resistant, 20 m (66 ft.) long, with interlock	9290709

Replacement Parts

HV Feedthrough with interlock	9595125
Pumping element* Diode	9199040
Pumping element* Noble Diode	9199045
Pumping element* StarCell	9199030
Heaters** (Input Power 480 W) 120 V	9190073
Heaters** (Input Power 480 W) 220 V	9190072

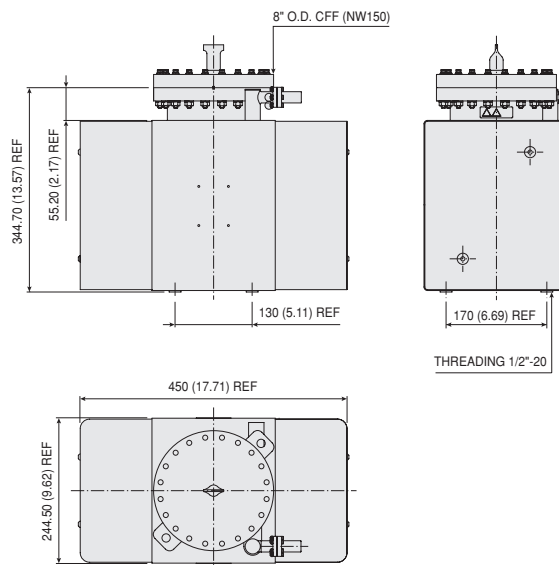
* Quantity required: 2.

** To order heaters for replacement or upgrading of existing pumps, please contact your local Agilent Vacuum Technologies representative.

Diode, Noble Diode	positive
StarCell, Triode	negative
(see page 42)	

AGILENT ION PUMP MODELS

▶ Agilent Vaclon Plus 300



Dimensions: millimeters (inches)

Technical Specifications

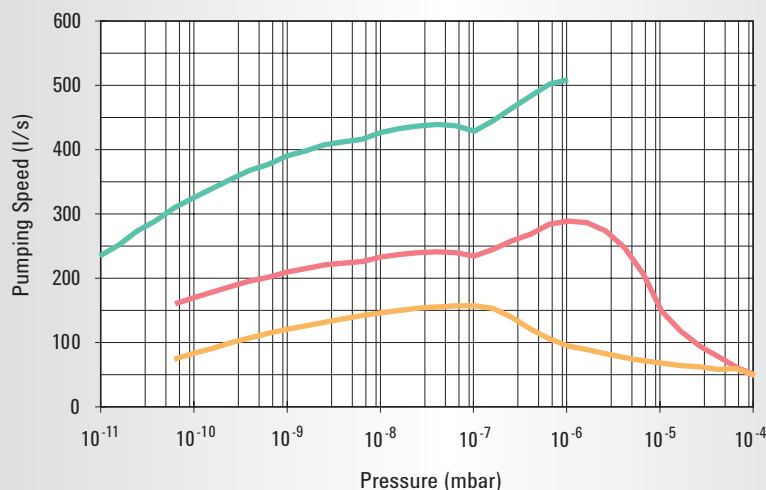
	StarCell	Noble Diode	Diode
Nominal pumping speed for Nitrogen (*) (l/s)	240	260	300
Operating life at 1×10^{-6} mbar (hours)	80,000	50,000	50,000
Maximum starting pressure (mbar)	$\leq 5 \times 10^{-2}$	$\leq 1 \times 10^{-3}$	$\leq 1 \times 10^{-3}$
Ultimate pressure		Below 10^{-11}	
Inlet flange		8" CFF (NW 150) AISI 304 ESR	
Maximum baking temperature (°C)		350	
Weight, kg (lbs)		69 (149)	

(*) Tested according to ISO/DIS 3556-1-1992

Customized design available on request

ION PUMPS

Vaclon Plus 300 - Pumping Speed vs Pressure



— Nitrogen unsaturated Diode — Nitrogen saturated Diode — Argon saturated StarCell

Ordering Information

Description	Part Number
Pumps	
Diode	9191610
Diode with heaters installed	120 V 9191611
Diode with heaters installed	220 V 9191612
Diode double-ended	9191650
Diode double-ended with heaters installed	120 V 9191651
Diode double-ended with heaters installed	220 V 9191652
StarCell	9191640
StarCell with heaters installed	120 V 9191641
StarCell with heaters installed	220 V 9191642
StarCell double-ended	9191680
StarCell double-ended with heaters installed	120 V 9191681
StarCell double-ended with heaters installed	220 V 9191682
<i>Noble Diode versions available on request</i>	
4UHV Controller	
200 W neg	9299010
200 W pos	9299011
2 x 80 W neg	9299200
2 x 80 W pos	9299201
2 x 200 W neg	9299020
2 x 200 W pos	9299021
1 x 200 W pos & 1 x 200 W neg	9299022
4 x 80 W neg	9299400
4 x 80 W pos	9299401
2 x 80 W pos & 2 x 80 W neg	9299402

Description	Part Number
4UHV Controller (cont'd)	
2 x 80 W neg & 1 x 200 W neg	9299210
2 x 80 W pos & 1 x 200 W pos	9299211
2 x 80 W pos & 1 x 200 W neg	9299212
2 x 80 W neg & 1 x 200 W pos	9299213
HV Cables	
HV Bakeable cable, radiation resistant, 4 m (13 ft.) long, with interlock	9290705
HV Bakeable cable, radiation resistant, 7 m (23 ft.) long, with interlock	9290707
HV Bakeable cable, radiation resistant, 10 m (33 ft.) long, with interlock	9290708
HV Bakeable cable, radiation resistant, 20 m (66 ft.) long, with interlock	9290709
Replacement Parts	
HV Feedthrough with interlock	9595125
Pumping element* Diode	9199040
Pumping element* Noble Diode	9199045
Pumping element* StarCell	9199030
Heaters** (Input Power 580 W)	120 V 9190075
Heaters** (Input Power 580 W)	220 V 9190074

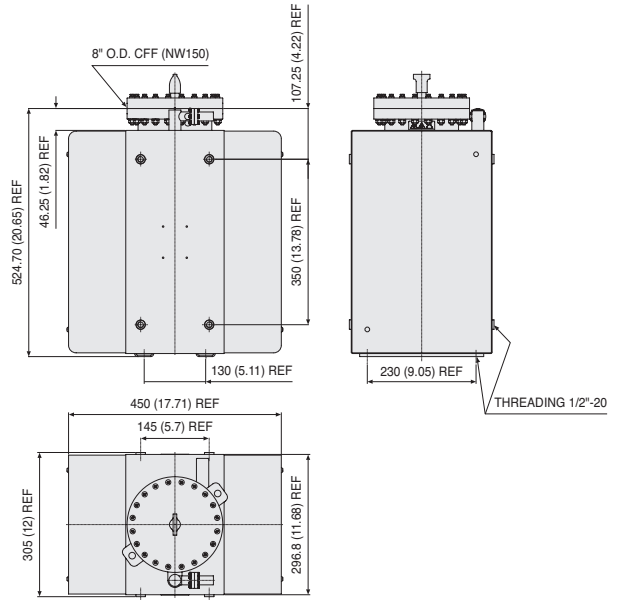
* Quantity required: 4.

** To order heaters for replacement or upgrading of existing pumps, please contact your local Agilent Vacuum Technologies representative.

Diode, Noble Diode	positive
StarCell, Triode	negative
(see page 42)	

AGILENT ION PUMP MODELS

▶ Agilent Vaclon Plus 500



Dimensions: millimeters (inches)

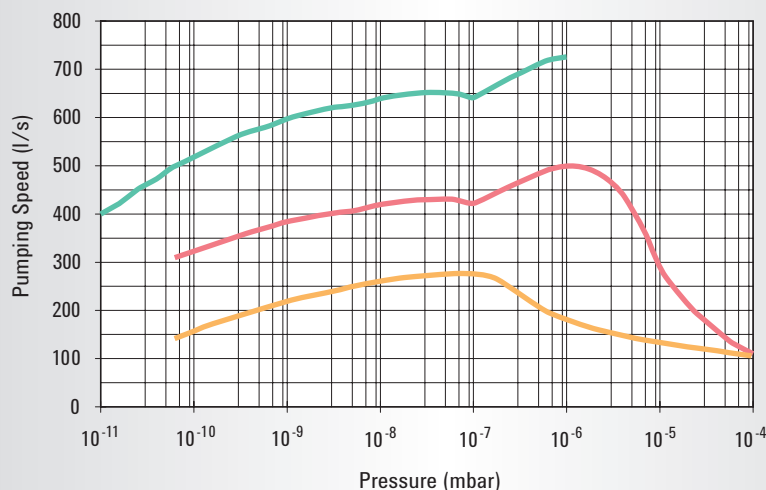
Technical Specifications

	StarCell	Noble Diode	Diode
Nominal pumping speed for Nitrogen (*) (l/s)	410	440	500
Operating life at 1×10^{-6} mbar (hours)	80,000	50,000	50,000
Maximum starting pressure (mbar)	$\leq 5 \times 10^{-2}$	$\leq 1 \times 10^{-3}$	1×10^{-3}
Ultimate pressure		Below 10^{-11}	
Inlet flange		8" CFF (NW 150) AISI 304 ESR	
Maximum baking temperature (°C)		350	
Weight, kg (lbs)		120 (264)	

(*) Tested according to ISO/DIS 3556-1-1992

Customized design available on request

Vaclon Plus 500 - Pumping Speed vs Pressure



— Nitrogen unsaturated Diode — Nitrogen saturated Diode — Argon saturated StarCell

Ordering Information

Description	Part Number
Pumps	
Diode	9191710
Diode with heaters installed	120 V 9191711
Diode with heaters installed	220 V 9191712
Diode double-ended	9191750
Diode double-ended with heaters installed	120 V 9191751
Diode double-ended with heaters installed	220 V 9191752
StarCell	9191740
StarCell with heaters installed	120 V 9191741
StarCell with heaters installed	220 V 9191742
StarCell double-ended	9191780
StarCell double-ended with heaters installed	120 V 9191781
StarCell double-ended with heaters installed	220 V 9191782
<i>Noble Diode versions available on request</i>	
4UHV Controller	
200 W neg	9299010
200 W pos	9299011
2 x 80 W neg	9299200
2 x 80 W pos	9299201
2 x 200 W neg	9299020
2 x 200 W pos	9299021
1 x 200 W pos & 1 x 200 W neg	9299022
4 x 80 W neg	9299400
4 x 80 W pos	9299401
2 x 80 W pos & 2 x 80 W neg	9299402

Description	Part Number
4UHV Controller (cont'd)	
2 x 80 W neg & 1 x 200 W neg	9299210
2 x 80 W pos & 1 x 200 W pos	9299211
2 x 80 W pos & 1 x 200 W neg	9299212
2 x 80 W neg & 1 x 200 W pos	9299213
HV Cables	
HV Bakeable cable, radiation resistant, 4 m (13 ft.) long, with interlock	9290705
HV Bakeable cable, radiation resistant, 7 m (23 ft.) long, with interlock	9290707
HV Bakeable cable, radiation resistant, 10 m (33 ft.) long, with interlock	9290708
HV Bakeable cable, radiation resistant, 20 m (66 ft.) long, with interlock	9290709
Replacement Parts	
HV Feedthrough with interlock	9595125
Pumping element* Diode	9199040
Pumping element* Noble Diode	9199045
Pumping element* StarCell	9199030
Heaters** (Input Power 780 W)	120 V 9190077
Heaters** (Input Power 780 W)	220 V 9190076

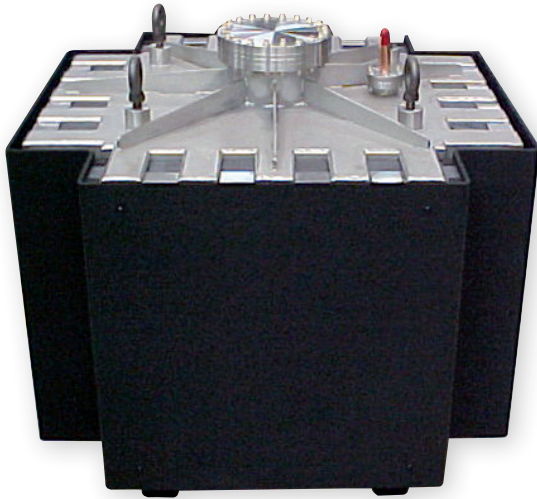
* Quantity required: 8.

** To order heaters for replacement or upgrading of existing pumps, please contact your local Agilent Vacuum Technologies representative.

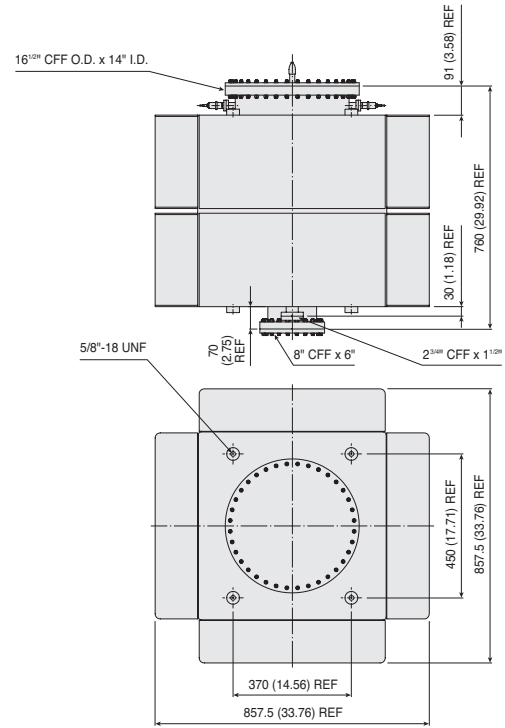
Diode, Noble Diode	positive
StarCell, Triode	negative
(see page 42)	

AGILENT ION PUMP MODELS

▶ Agilent Vaclon Plus Large Size Pumps

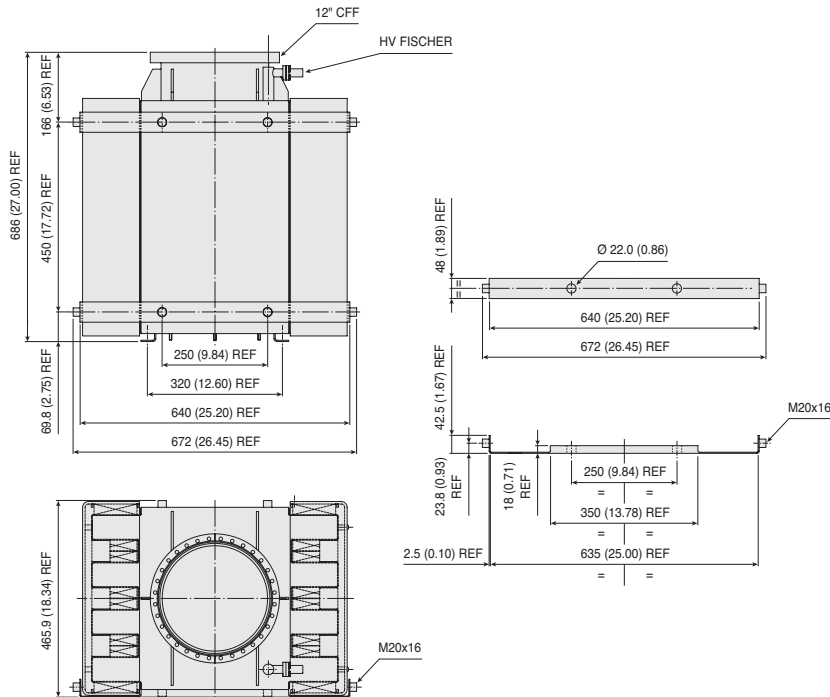


Agilent Vaclon Plus 2500 I/s



Larger Ion Pumps up to 2500 I/s, in StarCell and Diode versions, are available on request. Please contact Agilent for technical specifications and ordering information.

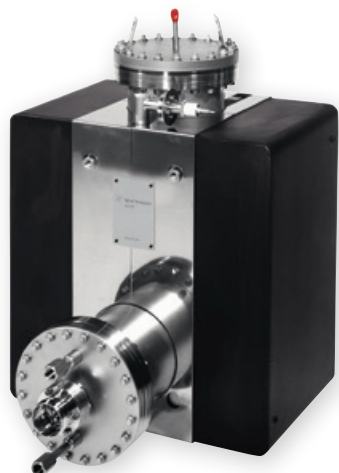
Agilent Vaclon Plus 960 I/s



Dimensions: millimeters (inches)

ION PUMPS

► Agilent Vaclon *Plus* Combination Pumps



Titanium Sublimation Combination Pumps

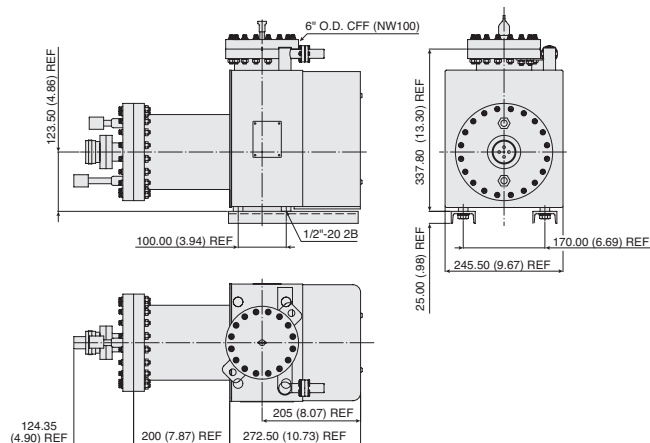
- Ion-Sublimation combination pumps have been a popular choice for many years for creating ultra high vacuum environments. The titanium sublimation creates extra high getterable gas pumping speed while the ion pumping mechanisms handle the non-getterable gases such as argon and methane.
- This combination pump is a Vaclon *Plus* 150, 300, or 500 with an extra side or bottom-mounted 8" ConFlat port. The combination pump includes the cylindrical cryopanel and TSP source mounted to the extra port. Getterable gases enter the end of the cylindrical cryopanel and are pumped by being combined with the freshly-deposited titanium there. Liquid nitrogen cooling the cryopanel increases the efficiency of the getting process and adds greatly to the water pumping speed.
- The Agilent Vaclon *Plus* series combination pumps allow addition of a cryopanel from the bottom of the pump or from the side. This can be a significant advantage in situations where height restrictions are present. Customized pump configurations are also available.

Technical Specifications

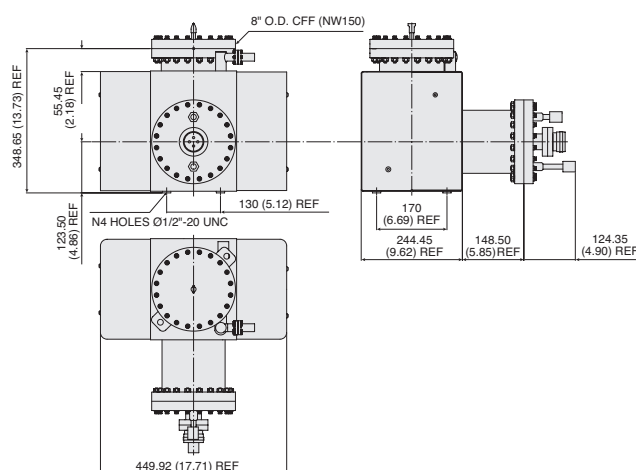
Nominal net pumping speed at 20 °C (l/s) with StarCell elements (water cooled cryopanel)

Vaclon <i>Plus</i> 150	N ₂ – 610 H ₂ – 1,380
Vaclon <i>Plus</i> 300	N ₂ – 720 H ₂ – 1,580
Vaclon <i>Plus</i> 500	N ₂ – 880 H ₂ – 1,930

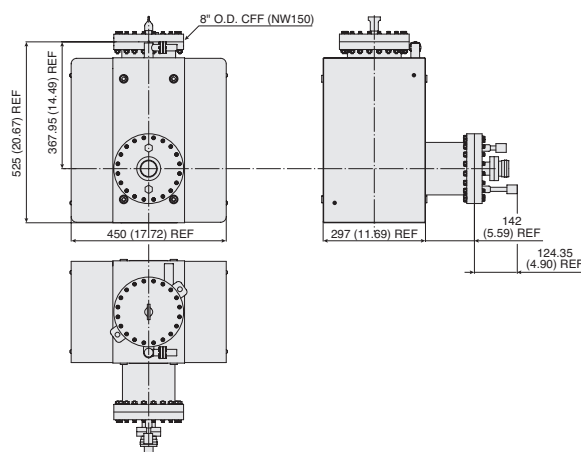
Vaclon *Plus* 150 Combination Pump (side-mounted TSP)



Vaclon *Plus* 300 Combination Pump (side-mounted TSP)



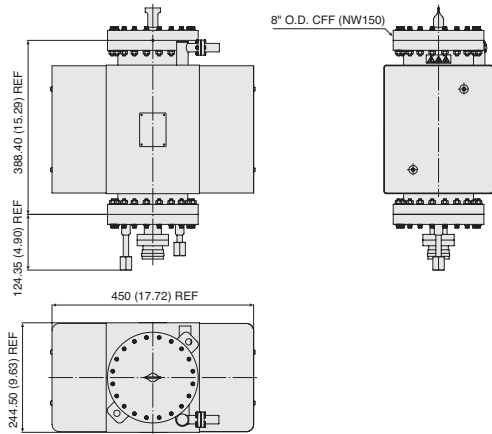
Vaclon *Plus* 500 Combination Pump (side-mounted TSP)



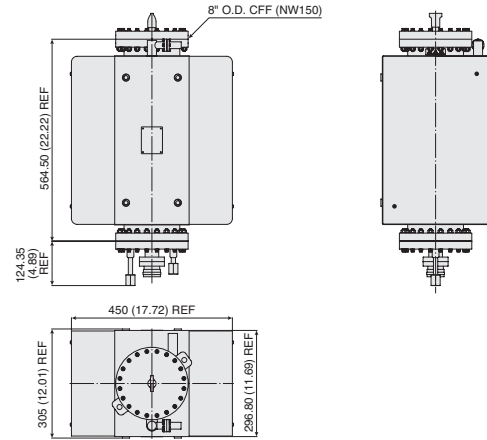
AGILENT ION PUMP MODELS

▶ Agilent Vaclon Plus Combination Pumps

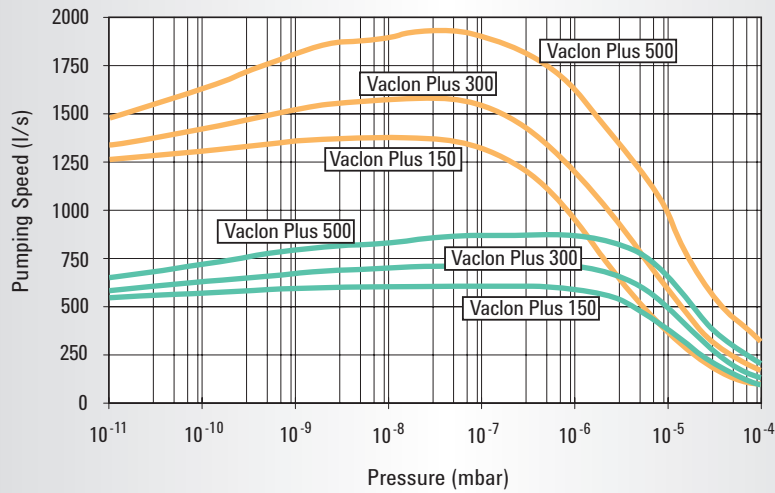
Vaclon Plus 300 Combination Pump (bottom-mounted TSP)



Vaclon Plus 500 Combination Pump (bottom-mounted TSP)



Combination Pumps Pumping Speed



— Nitrogen StarCell

— Hydrogen StarCell

ION PUMPS

Ordering Information

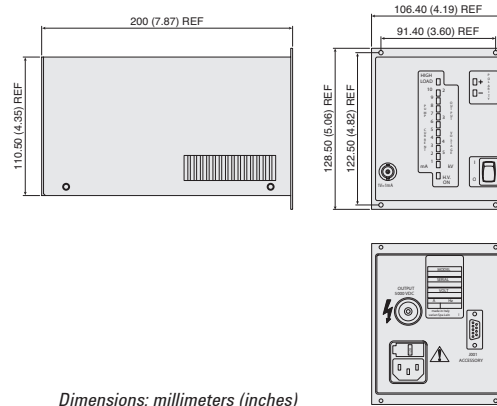
The Vaclon *Plus* 500, 300, and 150 pumps can be supplied with the sublimation cryopanel factory-installed and TSP cartridge included. Cables and controllers are to be ordered separately. For basic pump part number, see pages 22-27.

Description	Part Number	
Vaclon <i>Plus</i> 500, 300, or 150 combination pump		
Vaclon <i>Plus</i> 150 Diode, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	120V	9192510
Vaclon <i>Plus</i> 150 Diode, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	220V	9192511
Vaclon <i>Plus</i> 150 Noble Diode, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	120V	9192520
Vaclon <i>Plus</i> 150 Noble Diode, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	220V	9192521
Vaclon <i>Plus</i> 150 Starcell, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	120V	9192540
Vaclon <i>Plus</i> 150 Starcell, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	220V	9192541
Vaclon <i>Plus</i> 300 Diode, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	120V	9192610
Vaclon <i>Plus</i> 300 Diode, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	220V	9192611
Vaclon <i>Plus</i> 300 Noble Diode, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	120V	9192620
Vaclon <i>Plus</i> 300 Noble Diode, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	220V	9192621
Vaclon <i>Plus</i> 300 Starcell, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	120V	9192640
Vaclon <i>Plus</i> 300 Starcell, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	220V	9192641
Vaclon <i>Plus</i> 300 Diode, with Bottom-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	120V	9192612
Vaclon <i>Plus</i> 300 Diode, with Bottom-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	220V	9192613
Vaclon <i>Plus</i> 300 Noble Diode, with Bottom-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	120V	9192622
Vaclon <i>Plus</i> 300 Noble Diode, with Bottom-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	220V	9192623
Vaclon <i>Plus</i> 300 Starcell, with Bottom-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	120V	9192642
Vaclon <i>Plus</i> 300 Starcell, with Bottom-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	220V	9192643
Vaclon <i>Plus</i> 500 Diode, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	120V	9192710
Vaclon <i>Plus</i> 500 Diode, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	220V	9192711
Vaclon <i>Plus</i> 500 Noble Diode, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	120V	9192720
Vaclon <i>Plus</i> 500 Noble Diode, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	220V	9192721
Vaclon <i>Plus</i> 500 Starcell, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	120V	9192740
Vaclon <i>Plus</i> 500 Starcell, with Side-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	220V	9192741
Vaclon <i>Plus</i> 500 Diode, with Bottom-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	120V	9192712
Vaclon <i>Plus</i> 500 Diode, with Bottom-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	220V	9192713
Vaclon <i>Plus</i> 500 Noble Diode, with Bottom-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	120V	9192722
Vaclon <i>Plus</i> 500 Noble Diode, with Bottom-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	220V	9192723
Vaclon <i>Plus</i> 500 Starcell, with Bottom-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	120V	9192742
Vaclon <i>Plus</i> 500 Starcell, with Bottom-Mounted Cryopanel, with TSP Cartridge and with Installed Heater	220V	9192743

Description		Weight kg (lbs)	Part Number
Replacement Parts and Accessories			
TSP Filament Cartridge on 2 3/4" CFF		2.7 (6.0)	9160050
Replacement filaments, package of 12 each		0.4 (2.0)	9160051
Titanium Sublimation Pump Control Unit (Order cables separately)	120V	17.7 (39.0)	9290022
Titanium Sublimation Pump Control Unit (Order cables separately)	220V	17.7 (39.0)	9290023
TSP Cartridge cable, 3.5 m (12 ft.)		9.1 (20.0)	9240730
Sublimation Cryopanel on 8" CFF		10.5 (23.0)	9190180

AGILENT ION PUMP CONTROLLERS

▶ Agilent Mini Vac Controller



The MiniVac Ion Pump Controller is designed to economically operate any Vaclon Plus type and size: Diode, Noble Diode, and StarCell, from Miniature to 500 l/s pumps. The MiniVac is very compact and light, can be operated in local or remote mode, and is suitable for high radiation environments.

Medium pumps (Vaclon Plus 20 to 75) can be operated at any pressure below 1×10^{-5} mbar (continuous operation).

Large pumps (Vaclon Plus 150 to 500) can be operated at any pressure below 2×10^{-6} mbar (continuous operation).

The MiniVac is designed to withstand continuous operation at short circuit conditions, without damaging the ion pump or itself. A 24 V battery-operable version is available for portable applications.

Technical Specifications

Input

90 to 130 VAC or 180 to 240 VAC or 24 VDC

Output

Voltage: ± 5000 VDC (open load) (factory pre-set is negative)

Current: 15 mA (short circuit)

Maximum Power: 21 W (3 kV at 7 mA)

Front Panel

HV ON, HIGH LOAD, and POLARITY LEDs

LED bargraph linear scale for current and voltage indication

Recorder Output 0 to +10 VDC linear proportional to current (10 V = 10 mA)

Safety Marks

CE

Conformity to Norms

Safety: EN61010-1

EMI/EMC: EN61000-4-2, EN61000-4-3, EN61000-4-4

Rear Panel

Nine pin "D" type connector with following available signals and commands Recorder outputs:

- 0 to +5 VDC, linear proportional to HV (1 V = 1 kV)
- 0 to +10 VDC, linear proportional to current (10 V = 10 mA)
- 0 to +10 VDC, linear proportional to current (10 V = 1 mA)

HV ON confirm signal: Contact rating – 1 A at 250 VAC; 0.2 A at 30 VDC

Remote HV ON/OFF (interlock) command

HV connector: Fischer type 105 or King type, 10 kV

ION PUMPS

Ordering Information

Description		Weight kg (lbs)	Part Number
MiniVac Controller			
With any Vaclon Plus pump	MiniVac, FISCHER HV connector, US plug, 120 V preset	2.3 (5.0)	9290191
	MiniVac, FISCHER HV connector, European plug, 220 V preset	2.3 (5.0)	9290290
	MiniVac, FISCHER HV connector, 24 VDC	2.3 (5.0)	9290196
With small Vaclon pumps (2 and 10 l/s)	MiniVac, KING HV connector, US plug, 120 V preset	2.3 (5.0)	9290190
	MiniVac, KING HV connector, European plug, 220 V preset	2.3 (5.0)	9290291
	MiniVac, KING HV connector, 24 VDC	2.3 (5.0)	9290197
Accessories and Cables			
	19" Rack adapter	4.5 (10.0)	9699191
With any Vaclon Plus pump	HV bakeable cable, radiation resistant, 4 m (13 ft.) long, with Interlock	0.9 (2.0)	9290705
	HV bakeable cable, radiation resistant, 7 m (23 ft.) long, with Interlock	1.6 (3.5)	9290707
	HV bakeable cable, radiation resistant, 10 m (33 ft.) long, with Interlock	2.2 (5.0)	9290708
	HV bakeable cable, radiation resistant, 20 m (66 ft.) long, with Interlock	4.4 (10.0)	9290709
With small Vaclon pumps (2 and 10 l/s)	HV bakeable cable, radiation resistant, 4 m (13 ft.) long, with Interlock for 2 l/s pump	0.9 (2.0)	9290706
	HV cable, 3 m (10 ft.) long, for 8 l/s Vaclon pumps	0.9 (2.0)	9240741

Diode, Noble Diode	positive
StarCell, Triode (see page 42)	negative

AGILENT ION PUMP CONTROLLERS

▶ Agilent 4UHV Ion Pump Controller



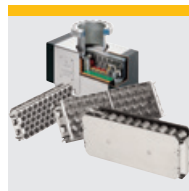
How much power do I need for my ion pumps?

Power requirement depends on the pump size and starting pressure; the larger the pump and higher the starting pressure, the higher the power consumption. The largest standard Ion Pump configuration, 500 l/s, can be easily started with 200W up to 10^{-5} mbar, while a medium size pump (75 l/s) needs less than 80 W to be started at the same pressure, and 80 W are sufficient to operate a 500 l/s in the typical Ion Pump operating range (below 2×10^{-6} mbar).



Why was the higher power rating necessary in the past?

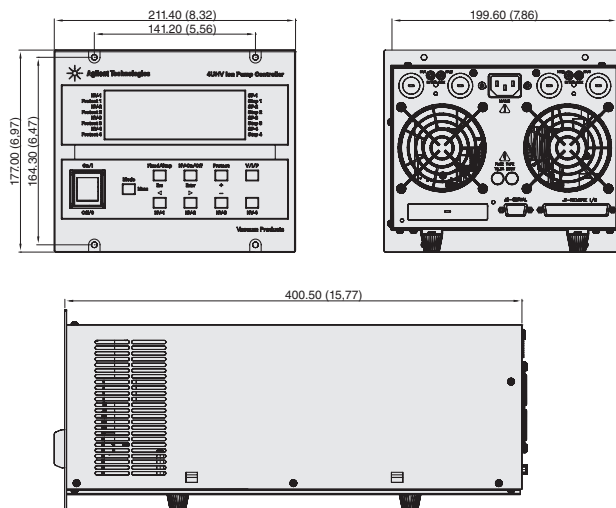
In the past ion pumps were started with the aid of sorption pumps, able to reach 10^{-4} mbar only. As a consequence, much larger and more powerful Ion pumps controller were needed. The resulting life of Ion Pumps started at such high pressures was much shorter (1 minute of operation at 10^{-4} mbar is equivalent to 2 months at 10^{-9} mbar). Today's oil-free turbo pumps, backed by oil-free primary pumps, achieve lower pressures, thereby reducing the starting pressure of the ion pump. This reduces the maximum power requirement of the ion pump controller and extends the lifetime of the ion pump.



Negative or positive?

The requirement of negative or positive potential depends on the pumping element installed in the ion pump. Diode style elements (Diode & Noble Diode) need positive voltages, while Triode style elements (old style Triode & StarCell) need negative voltages for operation.

ION PUMPS



Dimensions: millimeters (inches)

Technical Specifications

Input voltage	100 - 240 Vac (+/-10%)
Input frequency	50/60 Hz
Dimensions	400.5 x 211.4 x 177.0 mm (l x w x h)
Display	4 rows with 20 characters
Available configurations	1 x 200 W, 2 x 80 W, 2 x 200 W, 4 x 80 W, 2 x 80 W + 1 x 200 W
Minimum configuration	One HV card with 200W or 2x80W
Output voltage (Open Circuit)	3.5 and 7 kV
Output current (Short Circuit)	40 mA for 80 W channel, 100 mA for 200 W channel

Ordering Information

Description	Part Number
4UHV Controller	
200 W neg	9299010
200 W pos	9299011
2 x 80 W neg	9299200
2 x 80 W pos	9299201
2 x 200 W neg	9299020
2 x 200 W pos	9299021
1 x 200 W pos & 1 x 200 W neg	9299022
4 x 80 W neg	9299400
4 x 80 W pos	9299401
2 x 80 W pos & 2 x 80 W neg	9299402
2 x 80 W neg & 1 x 200 W neg	9299210
2 x 80 W pos & 1 x 200 W pos	9299211
2 x 80 W pos & 1 x 200 W neg	9299212
2 x 80 W neg & 1 x 200 W pos	9299213

Ethernet and Profibus communication available

- Add 729 to PN for ETHERNET configuration (i.e. 7299400 4x80W Neg with Ethernet)
- Add 829 to PN for PROFIBUS configuration (i.e. 8299400 4UHV 4x80W Neg with Profibus)

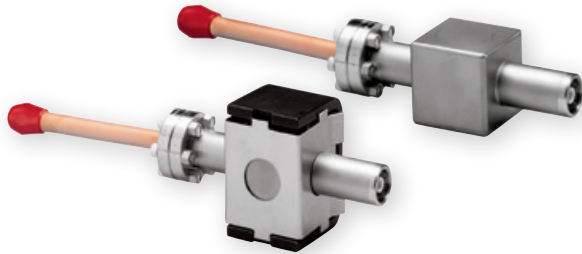
Modes of operation	Local / Serial / Remote
Front panel readings	Voltage, Pressure, Current, Status
Safety marks	CE, C_CSA_US
Current measurement range	10 nA to 100 mA
Input signals	On/off; Protect; Step Mode;
Output signals	Analog Out; NC Set-point; NO Set-point
HV connector	Fischer Type 105
Output Power Maximum	400 W
Communications	RS232/485 standard Profibus or Ethernet optional

Description	Part Number
Accessories and Cables *	
HV Bakeable cable, radiation resistant, 4 m (13 ft.) long, with interlock	9290705
HV Bakeable cable, radiation resistant, 7 m (23 ft.) long, with interlock	9290707
HV Bakeable cable, radiation resistant, 10 m (33 ft.) long, with interlock	9290708
HV Bakeable cable, radiation resistant, 20 m (66 ft.) long, with interlock	9290709
Rack adapter 19"	9290064
Mains cable NEMA Plug, 3 m (10 ft.) long	9699958
Mains cable European Plug, 3 m (10 ft.) long	9699957

(*) The unit does not include the power cable, please order the cable separately.

AGILENT ION PUMP MODELS

▶ Agilent Miniature and Small Vaclon Pumps and Controllers



Agilent offers a wide variety of small size ion pumps designed especially for electron device and detector applications. The Miniature Vaclon pump is a diode configuration and provides approximately 0.4 l/s of nitrogen pumping speed. The 2 l/s model is a modified diode configuration to enhance starting at low pressure. The 10 l/s pump is a noble gas optimized diode configuration with high efficiency for residual gases such as hydrogen. The pumping speed for noble gases is about 20% of the nominal speed.

Pumps that are processed are baked to 400 °C and pinched

off under vacuum, which allows the vacuum integrity to be verified by the user just before use. Non-processed pumps are tested for no vacuum leaks and minimum leakage current.

Modified and Customized Versions

Modified versions of standard pumps can be provided when different inlet tube lengths, angles, and diameters are required. These pumps can also be customized with different high voltage feedthroughs, body geometries, and pumping cell arrangements. Special testing procedures can be quoted for customers who have specific requirements in this area.

Ordering Information

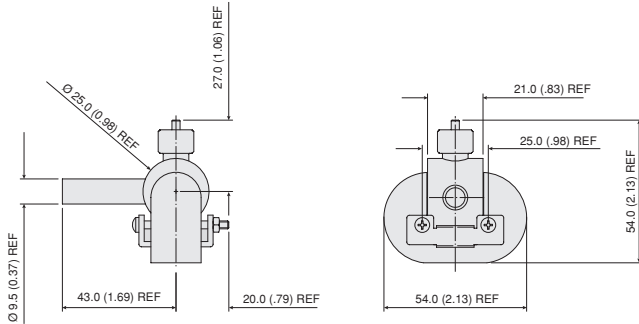
See pages 32-33 for controllers, cables, and accessories.

Description	Weight kg (lbs)	Part Number
Miniature Pump		
With 3/8" OD 180° stainless steel tube	0.5 (1.0)	9130038
With 3/8" OD 90° stainless steel tube	0.5 (1.0)	9130041
With 3/8" OD 180° copper tube, vacuum processed	0.5 (1.0)	9130049
With 3/8" OD 90° copper tube, vacuum processed	0.5 (1.0)	9130050
Magnet for Miniature pump	0.5 (1.0)	9130042
HV cable, 2.4 m (8 ft.) long, for Mini Vaclon pumps	0.9 (2.0)	9240122
2 l/s Pump		
With 3/4" OD 180° stainless steel tube	0.9 (2.0)	9190521
With 3/4" OD 180° copper tube, vacuum processed	0.9 (2.0)	9190522
With 3/4" OD 180° stainless steel tube, vacuum processed	0.9 (2.0)	9190523
With 3/4" OD 90° stainless steel tube, tee style	0.9 (2.0)	9190524
With 1 1/3" CFF 180° vacuum processed	0.9 (2.0)	9190520
Magnet for 2 l/s pump	0.9 (2.0)	9190038
HV bakeable cable, radiation resistant, 4 m (13 ft.) long with interlock for 2 l/s pump	0.9 (2.0)	9290706
10 l/s Pump		
10 l/s Vaclon pump, processed, with 2 3/4" CFF	3.6 (8.0)	9195005
Magnet assembly for 10 l/s Vaclon pump	5.0 (11.0)	9110030
HV cable, 3 m (10 ft.) long, for 10 l/s Vaclon pumps	0.9 (2.0)	9240741

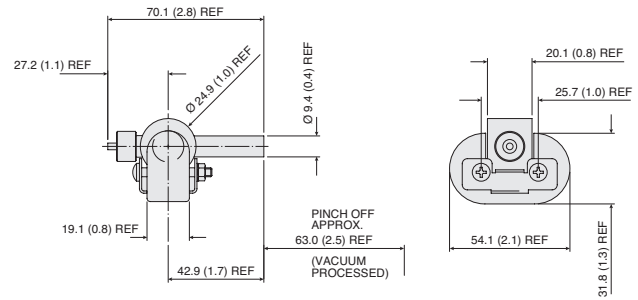
Magnets must be ordered separately.

ION PUMPS

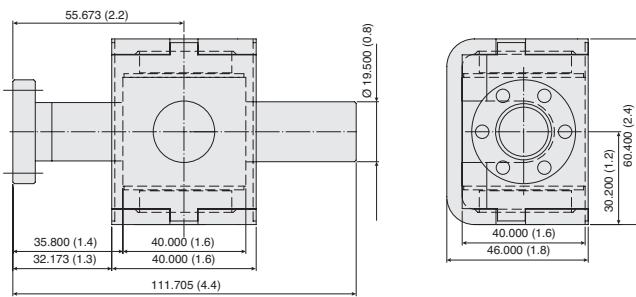
Miniature Pump (90 deg. config.)



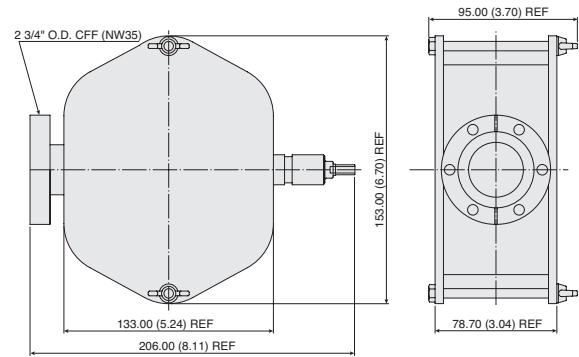
Miniature Pump (180 deg. config.)



2 l/s Pump



10 l/s Pump

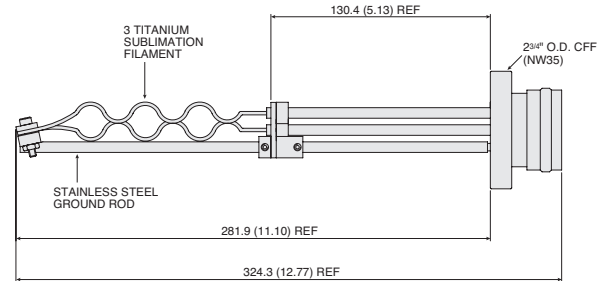


Dimensions: millimeters (inches)

The Miniature and 2 l/s pumps are available with copper or stainless steel inlet tubes in 90- or 180-degree configurations, relative to the high voltage feedthrough.

AGILENT TITANIUM SUBLIMATION PUMPS AND CONTROLLERS

TSP Cartridge



Dimensions: millimeters (inches)

Titanium sublimation pumps (TSPs) are typically used as an effective way to pump getterable gases such as hydrogen and nitrogen in UHV systems. TSPs are often combined with ion pumping, since the ion pump is effective with non-getterable UHV gases such as argon and methane. The TSP can be added to the inside of the ion pump, or as a separate pumping unit. If the TSP is used in conjunction with a liquid nitrogen-cooled cryopanel, extra high water pumping speed will be achieved. Agilent offers two different types of titanium sublimation pumps: filament and titanium ball sources. Filament-type TSP sources are most popular with UHV systems since they can be turned off between sublimations and thus do not add thermally-induced outgassing. The ball-type sources contain larger amounts of titanium which means longer life when operated under conditions that use more titanium, such as higher operating pressures. However, the ball sources require standby power between sublimations to prevent cracks from forming in the titanium ball.

The factors affecting titanium sublimation pumping efficiency include sublimation rate, frequency, surface area, and temperature. Sublimation pumping speed is generally a constant value below 10^{-7} mbar.

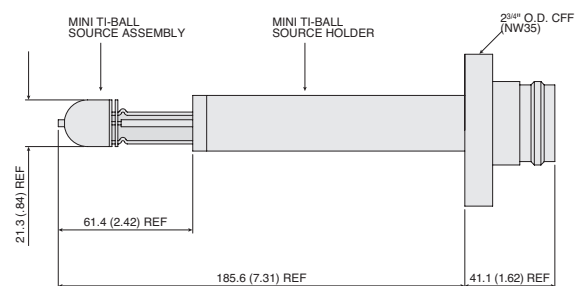
TSP Cartridge Filament Source

The popular TSP cartridge is provided on a 2 3/4" OD ConFlat flange and contains three titanium-molybdenum filaments, each with 1.1 grams of usable titanium. The cartridge assembly is bakeable to 400 °C. Maximum sublimation is achieved at 300 watts of source power.

Technical Specifications

Usable titanium (per filament)	1.1 grams
Total usable	3.3 grams
Operating range	10^{-4} to 10^{-12} mbar

Mini Ti-Ball



Dimensions: millimeters (inches)

Mini Ti-Ball Source

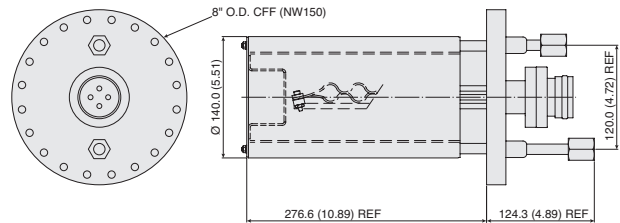
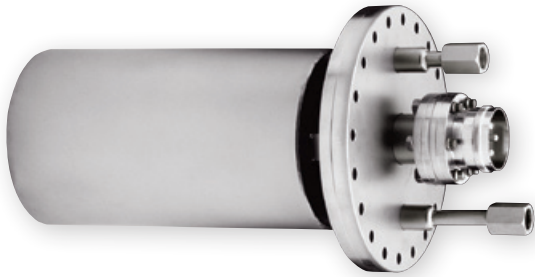
The Mini Ti-Ball source provides 15.2 grams of usable titanium and is mounted on a 2 3/4" OD ConFlat flange. Maximum sublimation is achieved at 300 watts of source power, while the Standby power requirement is 100 watts.

Technical Specifications

Usable titanium	15.2 grams
Operating range	10^{-4} to 10^{-12} mbar

ION PUMPS

► Agilent TSP Cryopanel



Dimensions: millimeters (inches)

TSP Cryopanel

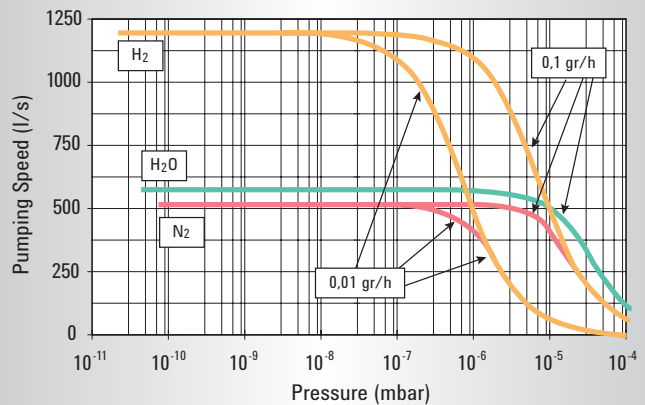
Designed for use with the TSP cartridge source*, this sublimation cryopanel is mounted to an 8" OD ConFlat flange. It can operate with water cooling, liquid nitrogen, or uncooled if used at UHV. This cryopanel can be mounted to double-ended or side-ported ion pumps and can also be used independently in any 8" (NW 150) CFF port with 11 inch depth/clearance.

The Cryopanel does not include the cartridge.

Technical Specifications

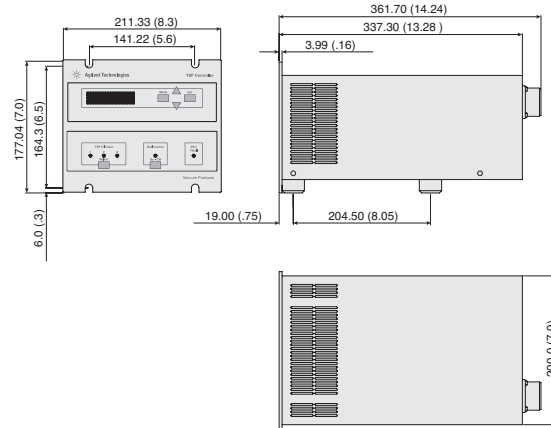
	N ₂	H ₂	H ₂ O
Pumping speed at 20 °C			
water-cooled (l/s)	515	1200	575
Inner pumping surface (cm²)	826		
Main flange	8" CF (NW150)		
Reservoir volume (liters)	1.8		
Cooling connection	3/8" G		
Titanium source flange	2 3/4" CF		

Pumping Speed vs Pressure at different evaporation rates



AGILENT TITANIUM SUBLIMATION PUMPS AND CONTROLLERS

▶ Agilent TSP Controller



Dimensions: millimeters (inches)

- Pump cable lengths up to 50 m
- Compact design ½ standard rack
- Selectable for automatic or manual operation
- Remote control (standard) via RS232/485

- To operate Agilent TSP filament cartridge or Agilent Mini Ti-Ball
- Safety Marks: CE, cCSAus

Technical Specifications

Input	100, 120, 220, 240 Vac ±10% 1-phase
Voltage (selectable at the rear of the case)	<ul style="list-style-type: none"> • 90 to 110 Vac - 1 phase (use setting 100 Vac) • 110 to 130 Vac - 1 phase (use setting 120 Vac) • 190 to 230 Vac - 1 phase (use setting 220 Vac) • 230 to 265 Vac - 1 phase (use setting 240 Vac)
Input frequency	47 to 63 Hz
Power consumption	1400 VA (maximum, see note)
Output current	30 to 50 A
Temperature	0 to + 45 °C
Humidity	90 % maximum non condensing humidity
Storage temperature	-20 °C to +70 °C
In compliance with norms	EN 61010-1 EN 61326-1 - Class A (industrial application)

Protection category	IP 20
Internal use only	
Installation category	II
Pollution degree	2
Power cable	3 meters long • 3 wires Ø AWG14, NEMA plug (only for model 929-0032) • 3 wires Ø 0.75 mm ² European plug (only for model 929-0033)
Weight	12 kg (26.5 lbs)

NOTE • When the controller is powered by means of a transformer, the transformer power must be at least 3000 VA to avoid a distortion of the power waveform.

Ordering Information

Titanium Sublimation Pumps	Part Number
TSP Filament Cartridge on a 2 ¾" CFF	9160050
Replacement filaments, package of 12 each	9160051
Mini Ti-Ball Source with Holder on a 2 ¾" CFF	9160009
Replacement Mini Ti-Ball Source	9160008
Titanium Sublimation Cryopanel	Part Number
Sublimation Cryopanel on an 8" CFF	9190180
Controllers	Part Number
Sublimation Controller set for 220 Vac	9290033
Sublimation Controller set for 110 Vac	9290032

Accessories	Part Number
Cable for TSP pump (3.5 mt)	9240730
Cable for TSP pump (7 mt)	9240730M002
Cable for TSP pump (10 mt)	9240730M001
Cable for TSP pump (30 mt)	9240730M017
Cable for TSP pump (40 mt)	9240730M015
Cable for TSP pump (50 mt)	9240730M013
Cable for Mini Ti-Ball pump	9240752
Rack adapters	9290064

Historical Notes

Ion pumping is used to remove gases from systems in order to create ultra-high vacuum environments. The earliest evidence of ion pumping was reported by J. Plucker (1858 - Germany) who found that it took ever-increasing voltages to maintain a current in a gas discharge tube.

This, he rightly concluded, is due to a reduction of pressure in the tube by some mechanism involving the cathode.

Later, as an offshoot of his work on electrical discharge in gases, F. Penning (1937 - Holland) developed a cold cathode ionization gauge for measuring pressures in the range of 10^{-3} to 10^{-5} Torr. Due to the sputtering effect of the high voltage, ions were both buried in and "gettered" by the cathode material. (Gettering is the chemical combination of active gases with a suitably reactive substance).

The result of this pumping action was a noticeable pressure reduction. The Penning cell has been used as a commercially available vacuum gauge ever since, but it was not until the late 1950's that its pumping characteristics were exploited, resulting in the invention of the ion pump. This was done in order to improve the life and performance of microwave tubes by continuous pumping with "appendage" ion pumps.

The invention of the sputter ion pump ushered in the era of ultrahigh vacuum, just in time to make a large contribution to the space age.

The availability of vacuum systems that could routinely achieve pressures in the low 10^{-11} Torr range enhanced R&D efforts. Space hardware and space-compatible materials were tested by simulating many of the conditions they would encounter. Today, ion pumps are used in both research and industrial applications wherever a pristine, oil-free, vibration-free, cost-effective environment is required.

Operation

Vacuum pumps in general operate on the basis of maintaining a lower gas density within themselves than exists in the environment they are pumping. This results in a net gas migration into the pump due to the random motion of the molecules under molecular flow conditions. Once in the pumps, few escape and they are either displaced or captured, depending on the type of pump.

Rather than being a displacement pump that actually moves molecules of gas through it to the atmosphere, the ion pump instead captures and stores them. As a result, at some point in time the pump must be reconditioned or replaced. This is generally required only after many years of use.

The generic name Sputter Ion Pump (or Ion Getter Pump) comes from the fact that some of the gas molecules undergo ionization and cause sputtering of the gettering agent. This material chemically reacts with the active gases to form stable compounds that are deposited on the internal walls of the pump. The getter, usually titanium, is provided by a plate

or electrode of that material, which is in turn sputtered and eroded by gas ions formed under the influence of the high voltage. These electrical potentials are usually in the range of 3,000 to 7,000 Vdc.

Most ionization devices operate in the same way. Gas molecules are bombarded by high energy electrons when a collision occurs. A molecule may lose one or more of its own electrons and thereby is left as a positively charged ion. Under the influence of a strong electric field, the ion is accelerated into the titanium cathode. The force of this collision is sufficient to cause atoms to be ejected from the cathode and "sputtered" onto the adjacent walls of the pump. Freshly sputtered titanium is extremely reactive and will chemically react with active gases. The resulting compounds accumulate on surfaces of the pump elements and pump walls.

Active gases are those such as oxygen, nitrogen, CO, CO₂, and water, as opposed to the noble gases like helium, neon, argon, krypton, and xenon, which are nonreactive. The latter are pumped by "ion burial" (ion burial is the "plastering over" of inert gas atoms by the sputtered getter atoms).

The simplest form of ion pump is the Penning cell, which was originally conceived as a cold cathode vacuum gauge. It consists of a central anode wire which is at positive high voltage. In an ion pump the anode can either be a short section of metal tubing or a square, box-like structure, open at each end like a unit of an egg crate. Opposite each open end is a plate of titanium that is connected to the ground to form the cathode structure. An external permanent magnetic circuit generates a magnetic field, usually ranging from 800 to 2,000 G, parallel to the anode cell axis. A cell configured in this way is said to be a diode pump (Figure 1). It is then packaged in a suitable enclosure and the assembly becomes a pump.

To make a higher speed pump, it is now simply a matter of making a package containing more cells with a larger cathode (Figure 2).

The function of the anode cell structure is to contain a "cloud" of high energy electrons which are constrained by the magnetic field.

This field causes the electrons to move in oscillating spiral paths (Figure 3) that increase their chances of striking gas molecules and thereby create positive ions. These ions are accelerated away from the positive anode voltage and collide into the titanium cathode plates (Figure 3). This results in the removal of titanium atoms by "sputtering".

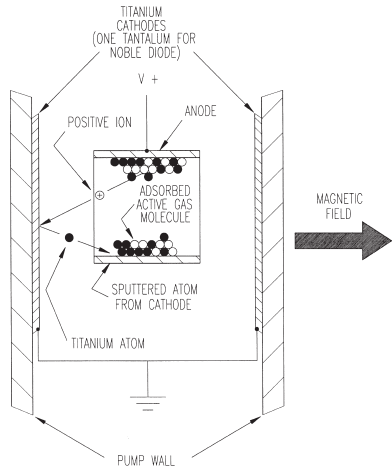
The sputtered titanium is deposited on the internal surfaces of the pump where it reacts with absorbed active gases to form stable compounds.

In summary, the pumping efficiency depends on the electron "cloud" density (which determines the number of ions produced) and on the sputtering yield (which determines the quantity of active getter material produced).

The electron cloud density mainly depends on the Penning

AGILENT ION PUMP TECHNICAL NOTES

Figure 1



Ion pump cutaway



Figure 2

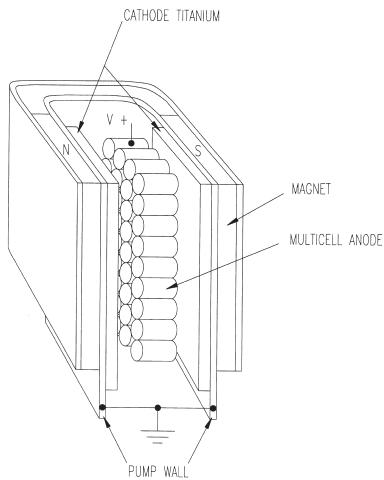


Figure 4

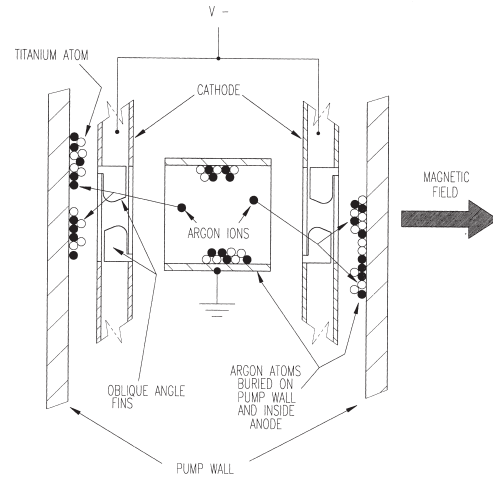


Figure 3

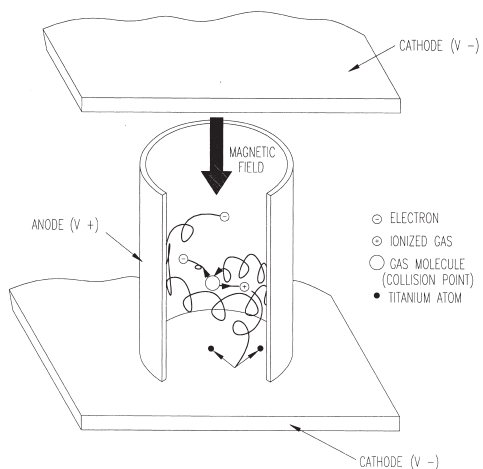
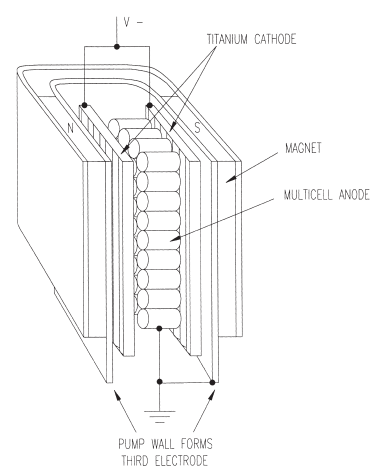


Figure 5



ION PUMPS

cell geometry and on the electric and magnetic field strengths. By adjusting these parameters, the pump performance can be modified according to the application. In particular, using an “intelligent” high voltage power supply, the right voltage can be automatically selected as the pressure changes.

The sputtering efficiency depends on the cathode geometry and material and on the gas species. Thus the cathode configuration can also be optimized for the gas used in the application.

Agilent offers three different cathode configurations that will satisfy a wide variety of applications involving different gases and operative pressures.

It should be noted that a few types of gases do not need to be ionized in order to be pumped. Hydrogen, for instance, forms a solid solution directly with the titanium cathode plates as well as the sputtered film.

It is the function of the ions to maintain a fresh supply of “gettering” material. In this regard, the ion pump is self-regulating; it only sputters as much getter material as is needed at that particular pressure.

In this way, at low pressures cathode plates are not wasted and electric power is conserved.

Some of the noble gas atoms are pumped as a result of being ionized.

In this case, they are implanted (at least temporarily) in the cathodes by the force of the accelerating voltage. Others are pumped by burial in the sputtered titanium film (Figure 4). Generally, pumping noble gases does not pose a problem because they are present in such small quantities. When it is necessary to deal with considerable amounts of noble gases, a pump of the triode configuration should be used (Figure 5). In the triode pump, the cathode is at negative potential and built with slits that permit grazing incidence sputtering. Thus, they tend not to be implanted to any appreciable extent and the un-sputtering of previously buried noble gases is largely eliminated. Instead, the gases either react with or are buried by the sputtered film on the walls of the pump body and on the anode.

Selecting Vaclon Plus Pumps

Ion pumps are commonly used to create Ultra High Vacuum (UHV), due to their cleanliness, ability to pump different gases, and maintenance- and vibration-free operation. Long operating life and ability to read pressure are other important features of ion pumps.

The Vaclon Plus family has been designed to enhance all of these characteristics, and thus offers the most advanced and valuable solution to any ion pumping requirement.

Cleanliness

To reach very low pressures (i.e. 10^{-11} mbar) in any system, both the chamber and pump outgassing must be minimized.

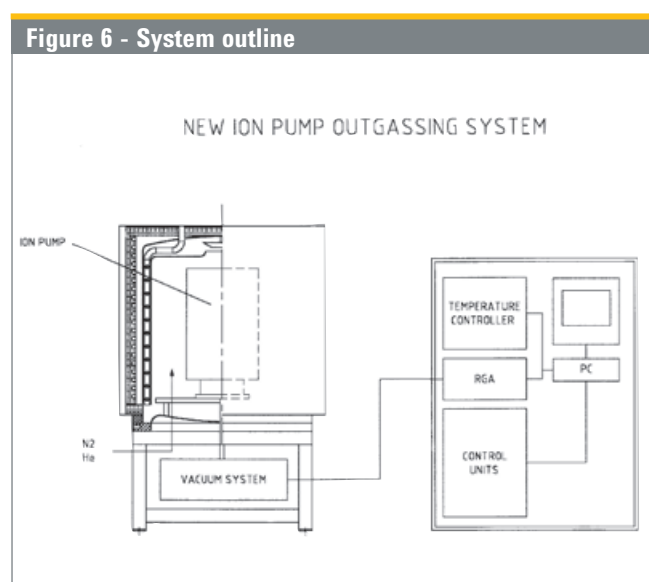
If not cleaned properly, the ion pump itself can be a source of gas at UHV.

In order to ensure cleanliness, Vaclon Plus Pumps are factory processed at high temperature in ultraclean vacuum for a thorough outgassing of the body and all internal components. The cleanliness of the ion pump element at high temperature ($450\text{ }^{\circ}\text{C}$) in ultraclean is even more critical, due to the continuous cathode bombardment. Any gas trapped on the surface or in the bulk of the cathode will eventually be released.

Ion Pump Outgassing System

The ion pump outgassing system is a thermal process of the pump, completely computer controlled and able to provide an automatic final test of the achieved pump specifications.

The bake-out of the pump is done in a nitrogen-controlled atmosphere to protect the external pump body from oxidation. See Figure 6 for System outline.



The system is based on the principle of thermal outgassing the ion pump internal surfaces through the control of their intrinsic outgassing. Therefore pressure, not time, is the driving factor of the overall process.

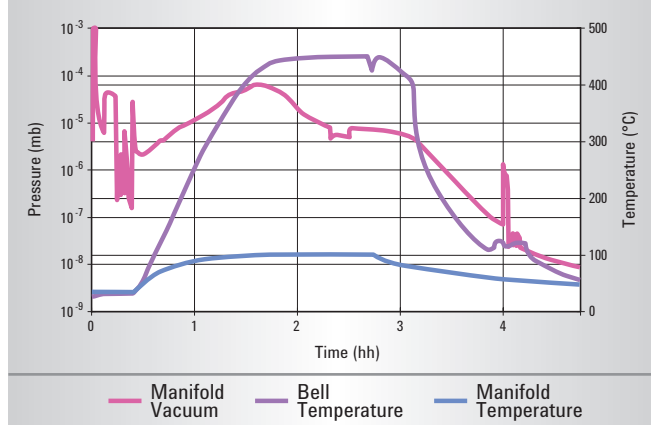
The bake-out time depends on the internal cleaning of the pump components and all the pumps will have, in this way, the same final outgassing rate and base pressure.

Figure 7 shows the working principle. The green curve represents the temperature and the yellow one the pressure read by the gauge located on the vacuum control system placed on the bottom of the outgassing station (see Fig. 6). The temperature is maintained at the set point level until the pressure does not change any more, which means the outgassing of the pump for the defined bake-out temperature is completed.

At the end of the thermal process, once room temperature is achieved, an RGA is performed.

AGILENT ION PUMP TECHNICAL NOTES

Figure 7 - Thermal process working principle

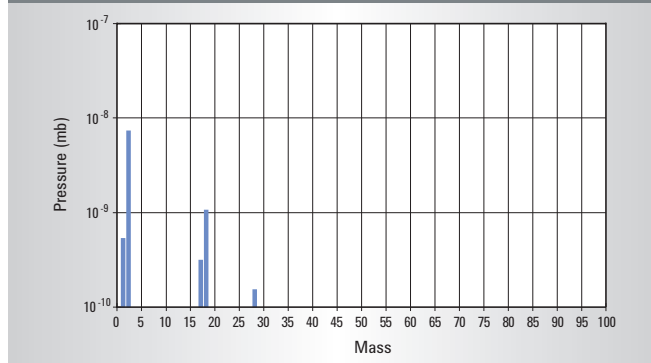


The gas analyser, placed on the vacuum system, provides the spectrum of the different gases degassed by the pump. If H₂ and the other peaks normally present in a well-baked vacuum system exceed the acceptance levels, the pump is baked again. Otherwise, it is pinched off and its base pressure monitored. The base pressure is evaluated through the ion current reading.

The current decrease is computer monitored, and the pump is ready to be shipped only after the base current is reached.

Figure 8 shows the result of the residual gas analysis performed at the end of the bake-out.

Figure 8 - Residual gas analysis



Pumping of Different Gases

In general, all ion pumps can pump all gases to some degree. To obtain the best performance and base pressure, different types of ion pumps have been developed with optimized performance in different pressure ranges and with different gases.

Agilent's Vaclon *Plus* is a complete product family that offers the choice among three different elements: Diode, Noble Diode and StarCell.

Whatever the application, there is a Vaclon *Plus* pump designed for it.

Long Operating Life

All Vaclon *Plus* pumps have rated lives in excess of many thousand of hours at a pressure of 1×10^{-6} mbar (50,000 hours for the Diode pump, and 80,000 hours for the StarCell).

With many ion pumps, maintenance may be required well before the rated life, due to metallization of insulators or pumping element distortion.

All Vaclon *Plus* elements are designed to minimize cathode distortion (even after repetitive bake-outs and starting at high pressure), and the insulators are protected from sputtered titanium by using a double re-entrant design and a cap shield.

Pressure Reading

The ability to read pressures using an ion pump is due to the direct proportionality between pump current and operating pressure.

The reliability of pressure readings at very low pressure is limited by leakage current, and the leakage current from field emission is heavily dependent on the voltage applied to the pump.

The Dual controller, designed for use with any Vaclon *Plus* pump, provides the unique ability to adjust the voltage in accordance with the operating pressure. By doing this, the leakage current is minimized at low pressure, providing a reliable pressure reading down to the 10^{-10} mbar range.

Custom Design and Flexibility

All ion pumps can be mounted in any position, and do not need any isolation valve from the system in case of venting or power failure.

Vaclon *Plus* pumps are the most compact ion pumps in each speed range. The pumps can be configured with additional flanges and can accommodate other pumping systems (like TSP = Titanium Sublimation Pump), allowing the best use of available space.

Agilent Feedthrough

The whole Ion Pump line is provided with an innovative feedthrough.

The improved feedthrough of the ion pump line is a major breakthrough. The greatest advantages of the ion pumps are listed here below:

• Corrosion Free

The design of the feedthrough will reduce drastically the corrosion that may occur when the pump is used in humid environments.

Our tests and experience have demonstrated that the corrosion starts and increases with the presence of humidity between feedthrough and connector. The high voltage during the pump operation ionizes the entrapped water vapor; the ions react with the brazing alloy and corrode it. The design of the feedthrough aims to solve these issues:

- On one hand the design structure of the feedthrough presents a negligible quantity of air.

– On the other hand, the brazing is done on the vacuum side so that the brazing alloy surface exposed to air is minimal.

- **High Voltage Cable Interlock**

The feedthrough has been designed for the “HV cable safety interlock” implementation. This feature avoids any electrical shock since the voltage is automatically cut off as soon as the cable is disconnected from the pump.

Our Ion Pump control unit (Dual) and the HV cable are already able to support this safety feature when connected to an ion pump with the feedthrough.

- **Easy Connection**

The connection of the cable connector to the feedthrough requires simply inserting and pushing the connector. No use of retention screws is required.

- **Safety against Unintentional Extraction**

When the HV cable connector is inserted into the new patented feedthrough, it is firmly and mechanically secured to it. A latch on the cable prevents disconnection.

- **Compactness**

The feedthrough design allows a significant gain of space for the customer.

The Vaclon *Plus* Family

Diode Vaclon *Plus*

The diode version of the Vaclon *Plus* pump has the highest pumping speed among all ion pumps for oxygen (O_2), nitrogen (N_2), carbon dioxide (CO_2), carbon monoxide (CO), and any other getterable gas. It provides the highest pumping speed and capacity for hydrogen (H_2) as well.

Its simple mechanical structure allows a reliable current/pressure reading down to very low pressures, as well as absolutely vibration-free operation. Its geometric and electrical configuration allows it to be used in the vicinity of electron detectors or similar devices.

Diode Vaclon *Plus* pumps are therefore widely and successfully used in general purpose UHV systems, for evacuating electron devices and in the most sensitive electron microscopes. However, diodes are not suggested for applications where noble gases such as argon (Ar), helium (He) and methane (CH_4) are to be pumped.

Noble Diode Vaclon *Plus*

The Noble Diode Vaclon *Plus* element is a version of the diode element, in which a tantalum cathode is substituted in place of a titanium cathode. This substitution allows a higher pumping speed and stability for pumping noble gases (mainly argon and helium).

The element is otherwise equivalent to the Diode Vaclon *Plus*. Noble Diode Vaclon *Plus* pumps are used in any application where pumping of noble gases is an important characteristic.

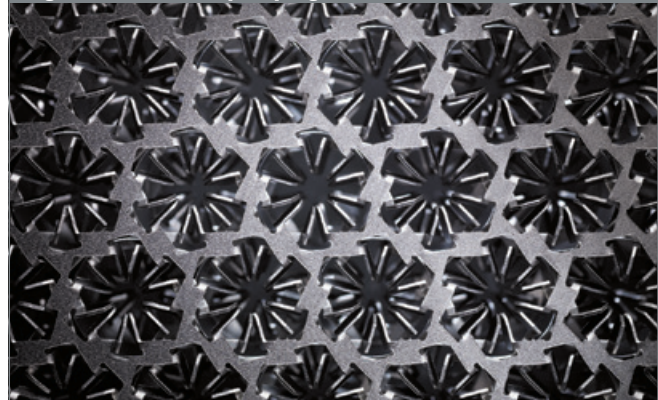
As with the diode configuration, the Noble Diode retains a consistent pumping speed for all gases at very low pressures. However, pumping speed for H_2 and getterable gases is lower than for the corresponding Diode. The Noble Diode Vaclon *Plus* is typically used in UHV applications where a mixture of gas is to be pumped and where the pressure is quite constant (i.e., no sudden gas burst or systematic high pressure cycling). Its characteristics of consistent speed for almost any gas even at very low pressures make it ideal whenever the ion pump alone is used to obtain UHV pressures. This is often the situation in particle accelerators or synchrotron rings, as well as in surface analysis applications.

Other Vaclon *Plus* versions are suggested whenever the application requires cycling to higher pressures, pumping of large amounts of H_2 , or when the ion pump is combined with other UHV pumps such as Titanium Sublimation Pumps or Non-Evaporable Getters.

StarCell Vaclon *Plus*

The StarCell Vaclon *Plus* element is the latest variation of the Triode configuration. Its design makes this ion pump the only one that can handle a high amount of noble gases (better than Noble Diode) and hydrogen (comparable to the Diode). Furthermore, this pump provides the highest speed and capacity for methane, argon, and helium. Its high total capacity for all the different gases, together with its very good speed performance at relatively higher pressures, makes the StarCell Vaclon *Plus* ideal for applications requiring constant operation at 10^{-8} mbar or above. This typically includes Electron Microscopes and Mass Spectrometers.

Figure 9 - StarCell pumping element



Its high pumping speed for argon, helium, and methane (the highest of any ion pump at any pressure) has made StarCell the standard for any application where the ion pump is used in combination with TSP or NEG pumps, where its pumping performance is enhanced. The lowest attainable pressure has been obtained with combinations of StarCell Vaclon *Plus* and TSP/NEG pumps, thanks to the optimized characteristics of these combinations. Most existing particle accelerators

AGILENT ION PUMP TECHNICAL NOTES

and synchrotron sources, beam lines, transfer lines, and similar devices have used and are successfully using these combinations to obtain the maximum speed for all the gas species.

For more specific information regarding the pumping speeds for different element configurations relevant to different gases, refer to the various curves published in the Vaclon *Plus* Pumping Speed section. The aim of this section is to help you choose the best Vaclon *Plus* configuration. Whatever the application, there is a Vaclon *Plus* version suited for it.

Do not hesitate to contact your local Agilent representative if you need more assistance in making the right choice.

For Vaclon Plus and NEG integrated pumps, please ask Agilent for a special quotation.

Vaclon *Plus* Pumping Speed

The most common parameter used to express the capability of a pump to remove molecules from a given volume is pumping speed. It is usually measured in liters per second and expresses the volume of gas (at a given pressure) removed per time unit.

In an ion pump, the net pumping effect results from the sum of different phenomena:

- The pumping action of the getter film produced by the sputtering of cathode material by ion bombardment.
- The pumping action due to the ion implantation and diffusion into the cathode.
- Gas burial on the anodes and pump walls.
- The gas re-emission from the cathode due to cathode heating and erosion.

When an ion pump is new or has been regenerated, for example by baking, the surface layer of the cathode is clean and the gas re-emission from it is negligible. In this condition, the ion pump is called “unsaturated” and the pumping effect is due both to the gettering effect as well as to ion implantation and diffusion. As the number of gas molecules implanted into the cathode increases, the re-emission of them due to the ion bombardment increases.

As a consequence, the net pumping speed decreases until an equilibrium condition between ion implantation and gas re-emission is reached. In this condition, the ion pump is “saturated” and the net pumping speed, due only to the gettering action of the material sputtered from the cathode, is about half the pumping speed of the unsaturated pump.

Since the saturation effect depends on the quantity of gas molecules implanted into the cathode, the time required to saturate an ion pump is inversely proportional to the pressure at which the pump is operated. Thus, the lower the pressure, the longer the time before the pump saturation occurs (Figure 10).

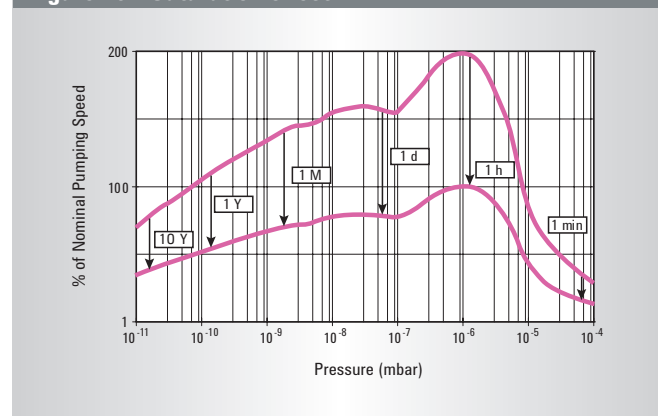
In an ion pumped UHV system with a proper bakeout procedure (and consequent pump regeneration), a pressure in the 10^{-11} mbar range is possible. At this pressure, the ion pump will work at the higher (unsaturated) pumping speed values for a few years before it is saturated.

When pump saturation is reached, the pumping speed is constant and no longer depends on the quantity of pumped gas. The values of the pumping speed curve after saturation are the lowest obtainable at any given pressure.

Generally, the ion pump works in an intermediate condition between the unsaturated and saturated extremes. The “nominal” pumping speed is defined as the maximum point on the pumping speed curve for a saturated pump; the reference gas is usually nitrogen.

The nominal pumping speed thus defines only a part of the characteristics of an ion pump. A more comprehensive description of an ion pump performance is given by the complete pumping speed vs pressure curve. By using these plots and keeping in mind the application, the best pump can be chosen.

Figure 10 - Saturation effect



Active Gases (N_2 , O_2 , CO , CO_2 ,...)

A characteristic of these gases is their ability to easily react with most metals forming stable compounds. In an ion pump, these active gas molecules react with the fresh titanium film produced by the sputtering of the cathode material. These active gas molecules do not diffuse deeply in the cathode.

The saturation effect, due to the re-emission of these molecules trapped on the cathode surface, is very strong.

Diode and Noble Diode elements show a higher pumping speed at low pressure while StarCell elements perform better at higher pressure, because the Penning discharge is better confined inside the element (Figures 11, 12).

ION PUMPS

Figure 11 - Nitrogen pumping speed before saturation

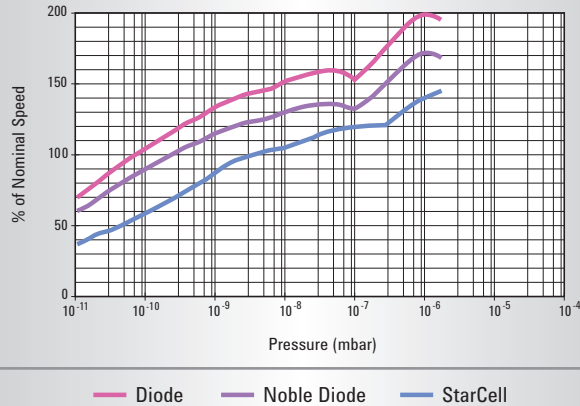


Figure 13 - Hydrogen pumping speed

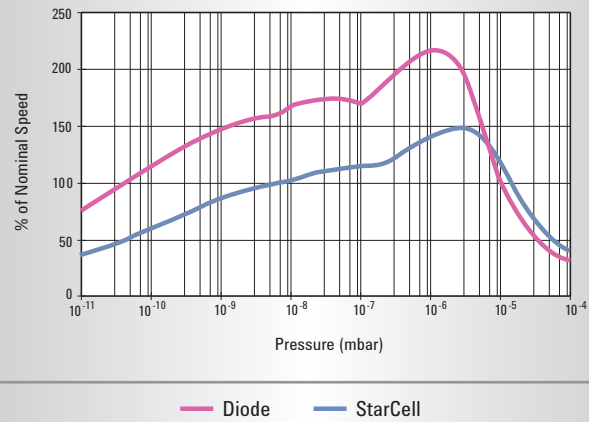
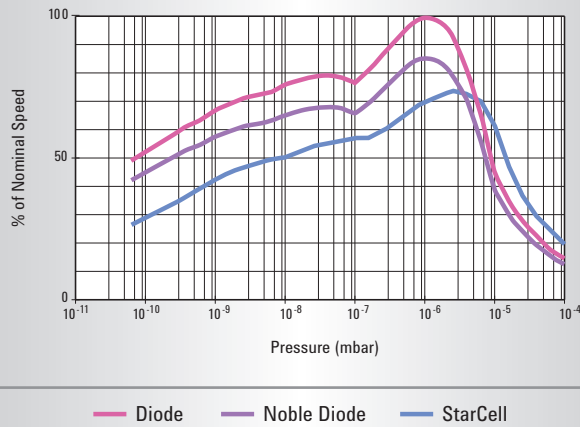


Figure 12 - Nitrogen pumping speed after saturation



Noble Gases (He, Ne, Ar,...)

The main characteristic of noble gases is that they do not react with any other element. Therefore, the film produced by the sputtering of cathode material does not provide getter pumping for helium and argon. Moreover, since these gases do not tend to diffuse into the cathode, the pumping effect due to the ion implantation is not permanent.

Nevertheless, all the ion pump elements have some capacity to remove these gases.

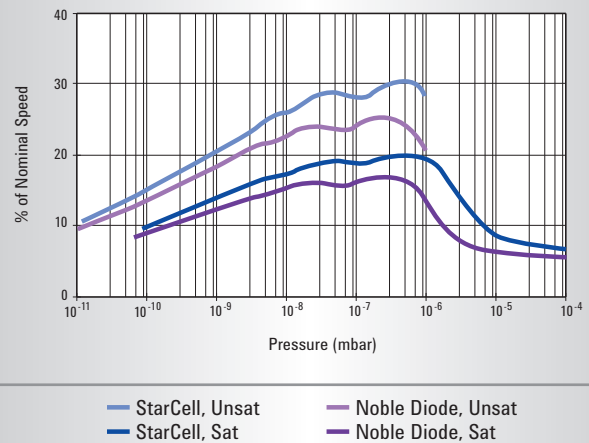
Hydrogen

Hydrogen is an active gas but, due to its very small mass, the sputtering rate is very low. In spite of this fact, the pumping speed for H₂ is very high because it quickly diffuses into the cathode with negligible re-emission. When pumping H₂, the ion pump always works in the unsaturated condition. As a result, the nominal speed for H₂ is about twice the corresponding value for nitrogen.

Furthermore, if some traces of heavier gases are present, the increased sputtering rate produces an even higher hydrogen pumping speed.

The Diode element shows a higher pumping speed than the Noble Diode since the H₂ solubility in the tantalum cathode is lower than in a titanium cathode. StarCell elements combine good performance at higher pressures with enhanced capacity for H₂.

Figure 14 - Argon and Helium pumping speed

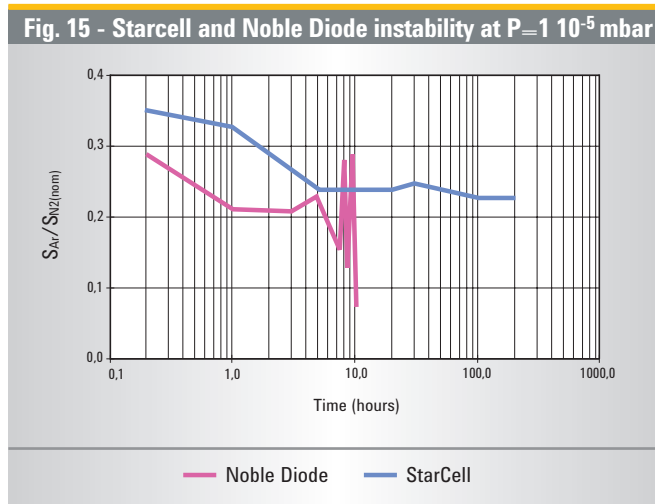


Noble gases are pumped by being buried by titanium. Noble gas ions can be neutralized and scattered from the cathode without losing their energy. These neutral atoms maintain enough energy to implant or stick on the anode and on the pump walls where they will be buried by sputtered titanium and thus permanently pumped.

AGILENT ION PUMP TECHNICAL NOTES

In the Diode configuration, the neutralization and back scattering probability is very small, thus the pumping speed for noble gases is only a small percentage of the N₂ pumping speed. Moreover, when operating at a relatively high argon partial pressure (i.e., higher than 10⁻⁸ mbar), sudden bursts of pressure due to the re-emission of temporarily implanted argon in the cathode is observed. After this occurs, a Diode pump is not able to pump more argon until its source is stopped. This phenomenon is known as “argon instability”.

Figure below shows that the StarCell pump is superior in comparison to diode pumps with differential cathodes. The test was performed at 10⁻⁵ mbar. The differential cathode diode showed instability after pumping about 3 mbar l of argon while the Starcell remained stable after pumping about 70 mbar l of argon, at which point the test was stopped.



In the Noble Diode element, one titanium cathode is replaced with one tantalum cathode. The high nuclear mass of tantalum increases the back-scattering probability and consequently the pumping speed for noble gases.

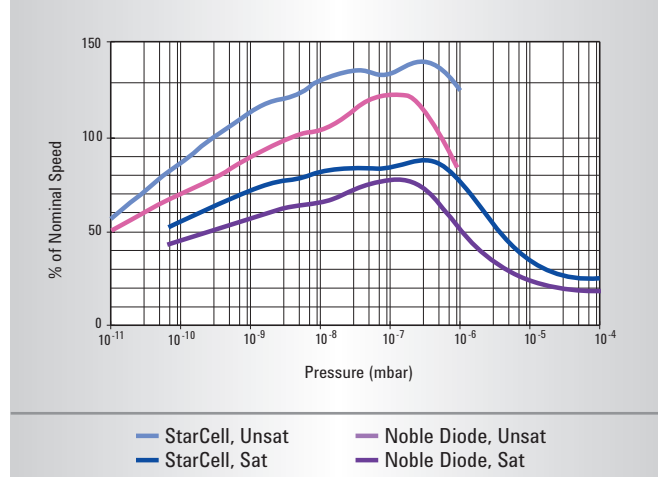
The best results in terms of pumping speed of noble gases are obtained using the open cathode structure typical of StarCell elements. In these configurations, the flat cathode structure has been replaced with a structure that allows glancing collisions with ions.

These are neutralized and then forward scattered toward the pump wall or the anode with a much higher probability than in the flat cathode case. The result is a pumping speed for noble gases of up to 60% of N₂. Furthermore, due to the unique design that allows optimal use of all the available titanium, the operating life of a StarCell pump is about 50% longer than all the other pumps.

Methane

Although methane is not a noble gas, it does not react with any getter material. It is always present to some degree in UHV systems as a reaction product of hydrogen and carbon present in the vacuum system walls. Methane is a particular problem in electron accelerators where it is the main cause of the beam decay.

Figure 16 - Methane pumping speed



Due to the Penning discharge in ion pumps, the methane molecule (as well as other hydrocarbon molecules) is cracked and transformed into smaller getterable compounds (C, CH₃, ... H).

The result is that the pumping speed for methane and light hydrocarbons is always higher than the speed for N₂.

Basic Performance Factors

- Pumping speed, as in the case of any high vacuum pump, is one of the factors determining the ultimate (base) pressure of a system. However, ion pumps pump various gases at different rates – from very fast for hydrogen to quite slow for argon. Thus, it is necessary to check specifications to match the pump properly to the application. The pump history in terms of gas load after a bakeout also influences pumping speed. Agilent pumps are rated by their equilibrium or “saturated” speed levels. Unsaturated pumps temporarily deliver higher speeds, especially at UHV. A typical pumping speed vs pressure curve is shown on page 46.
- Maximum throughput of an ion pump is located in the 10^{-4} to 10^{-5} mbar pressure range. Since ion pumps are generally operated at much lower pressures, throughput is generally not a major consideration.
- Starting pressure is the pressure to which the ion pump must first be rough-pumped before the glow discharge will be confined to the anode cell structure and the pumping effect begins. To prevent pump overheating and possible damage when the pump is saturated at higher pressure, the controllers automatically reduce the output voltage to maintain power below a safety level.
- Pump life is determined by various factors, including cathode life; this is limited by cathode erosion, which is proportional to the average operating pressure. At 10^{-6} mbar, cathode life ranges from 35,000 to 80,000 hours.
- Bakeability. In general, baking a UHV system and its ion pump to 200 to 250 °C is adequate for outgassing, attaining low pressures after atmospheric exposure. Some processes require higher bakeout temperatures. In general, ion pump bodies can be baked at 450 °C when the magnets are removed, or 350 °C when the magnets are on the pump. When bakeable cables are connected to the ion pumps, temperature should not exceed 220 °C.

AGILENT TITANIUM SUBLIMATION PUMP TECHNICAL NOTES

Titanium Sublimation Pumps

Thin films of reactive materials have been used for “gas cleanup” or “gettering” for over a century. The early electron tube makers were only able to mechanically pump to about 1×10^{-4} mbar, but through the use of “getters” flashed on the internal surfaces, pressures in the low 10^{-7} mbar scale were attained. These getters were typically metals like barium, titanium, zirconium, or thorium. Gettering materials are still used in tubes today even though pressures of 1×10^{-8} mbar are readily attained by the pumps in the manufacturing process.

Gettering was not employed extensively in vacuum systems until the 1960’s, when it was found to be highly compatible with ion pumping. Titanium was the metal commonly used because of its availability and its ability to sublime readily over a moderate temperature range.

Applications

Due to cleanliness, bakeability, low power consumption, vibration-free operation, long pumping life, and high pumping speed, Titanium Sublimation Pumping (TSP) is the ideal cost-effective companion to ion pumping in ultrahigh vacuum.

Applications for this pumping mode are found in many areas, such as:

- Auger electron spectrometry
- Electron spectroscopy for chemical analysis
- Electron tube manufacturing
- Mass spectrometers
- Materials science conductor R&D
- Nuclear physics
- Outer space simulation
- Particle accelerators
- Secondary ion mass spectroscopy
- Solid state semiconductors

Basic Performance Factors

• **Pumping Speed.** The pumping speed of a Ti film is proportional to the film area and to the sticking coefficient, that is the probability that an impinging gas molecule reacts with Ti forming a stable compound. The pumping speeds per unit area of a fresh evaporated Titanium film are reported in Table 1. Using these coefficients the intrinsic pumping speed (Si) of a Ti film can be evaluated using the following equation:

$$Si[l/s] = \text{Coefficient} \times \text{Surface.}$$

Table 1

Typical pumping speeds per square inch (per square centimeter) of titanium sublimation surface for various gases (liters per second)

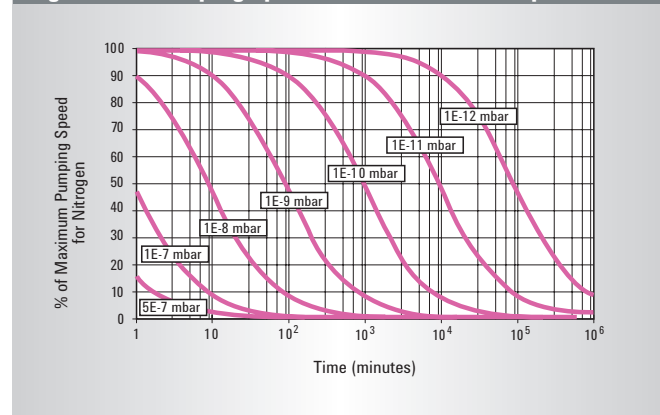
	Gas	H ₂	N ₂	O ₂	CO	CO ₂	H ₂ O	CH ₄	Ar	He
Surface Temperature	20 °C	20 (3.1)	30 (4.7)	60 (9.3)	60 (9.3)	50 (7.8)	20 (3.1)	0	0	0
	-195 °C	65 (10.1)	65 (10.1)	70 (10.9)	70 (10.9)	60 (9.3)	90 (13.9)	0	0	0

As the gas molecules react with the surface Ti atoms, the number of active sites decreases and, as a consequence, the pumping speed decreases. A plot of the specific pumping speed vs time at different pressures is reported in Figure 17. Using this plot it is possible to estimate how frequently the Ti film has to be renewed.

It must be noted that the actual pumping speed S of a TSP depends on the conductance C between the active surface and the vacuum vessel according to the following equation:

$$1/S = 1/C + 1/S_i$$

Figure 17 - Pumping speed vs time at different pressures



• **Throughput.** When the impingement rate of the gas molecules on the active film becomes higher than the Ti sublimation rate (excess of gas molecules respect the available Ti atoms), the pumping speed does not depend any more on the sticking coefficient. It is simply controlled by the quantity of the available Ti atoms according to stoichiometric reaction.

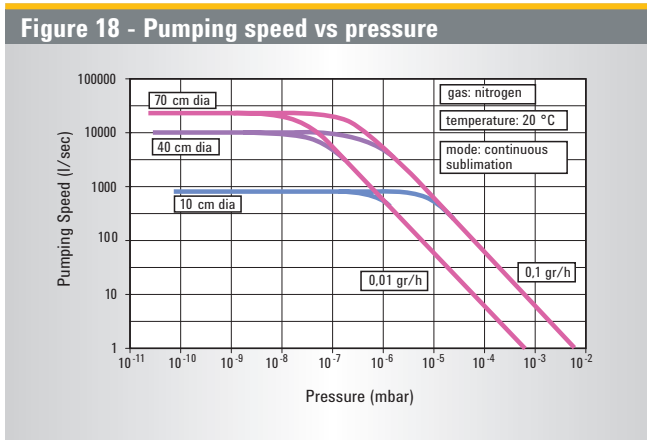
If n Ti atoms need to pump a gas molecule (example: $2Ti + N_2 \rightleftharpoons 2TiN$, $n = 2$), the gas throughput Q is given by:

$$Q [mbar \cdot l/s] = \frac{0.13}{n} R \left[\frac{gr}{h} \right]$$

Plus where R is the Ti sublimation rate. In this condition the pumping speed is not constant but it depends on the pressure and is directly proportional to the sublimation rate (Figure 18).

ION PUMPS

Figure 18 - Pumping speed vs pressure



After this time the filament cartridge should be replaced.

Design Features

- All sources are mounted on 2 3/4" Agilent ConFlat Flanges and fit through 1 1/2" ports.
- The three-filament source contains 3.3 grams of useful titanium.
- The Agilent Mini Ti-Ball source contains 15.2 grams of useful titanium.

- Other factors. The overall performance of a titanium sublimation pump is a function of several variables, including gas species, pressure, gas temperature, getter film temperature, getter film area, the geometry of the area, sublimation rate, sticking coefficient, and the conductance from the film to the area being evacuated. For further information, write for "Predicting and Evaluating Titanium Sublimation Pump Performance" by D.J. Harra, 1974 (Vacuum Report VR-88).

Operation

Titanium Sublimation Pumping is accomplished by coating the inner surfaces of a vacuum system with sublimed titanium films. Since it involves a chemical reaction, this kind of pumping is useful where mainly active gases are present.

The pumping speed of a unit area varies with various reactive gas species as shown in the following table. It can also be seen that cooling the substrate to liquid nitrogen temperature markedly increases the speed for hydrogen and water.

The gases thus "gettered" form stable compounds with titanium and are stored in the system as such until they are removed by cleaning. Since there is generally un-reacted pyrophoric titanium buried in the deposits, caution should be used in cleaning. If the desired gas throughput is known ($Q = \text{pumping speed} \times \text{pressure}$) the maximum theoretical operating time is given by:

$$\text{Operating time [h]} = \frac{0.13}{n} \frac{T \text{ [gr]}}{Q \text{ [mbar l/s]}}$$

where T is the usable Titanium

For example, using our cryopanel at 1×10^{-8} mbar with a three filaments cartridge Ti source, the theoretical operating time is given by:

$$\frac{0.13}{2} \frac{3.6 \text{ [gr]}}{500 \text{ [l/s]} \times 10^{-8} \text{ [mbar]}} = 46,800 \text{ hrs} = \text{about 5 years}$$

AGILENT ION PUMP SERVICE AND SUPPORT PLAN

Agilent Vacuum Technologies Products offers one of the most comprehensive service and support plans in the industry.

As a worldwide, first class company we strive to offer added value to our Customers wherever they may be located.

Excellence in Service and Support is a key factor in added value.

Support can be accomplished with qualified Engineers and an appropriate logistic infrastructure.

Technical skills and infrastructure are two areas where we are continuously making medium and long-term investments.

Our daily customer support philosophy is focused on two important factors: quick response and no hassle.

Agilent Vacuum Products is committed to providing our Customers with the most comprehensive service plans possible.

The following pages detail the standard sections of our Ion Pump Service and Support Plan. For more information, or if you have a need for customized solutions, please contact your Agilent representative.

Often, excellent products are not enough: Agilent's constant presence with Customer Service as a responsive partner is what really makes a difference.

Worldwide Parts Sourcing Plan

• Exchange and Repair Programs

Agilent's Ion Pumps and Controllers offer unmatched reliability, performance and cleanliness.

To maximize uptime, and for those occasions where time is essential, Agilent offers Ion pump controller exchange units for advance shipment.

Exchange units are fully remanufactured to the same strict standards as new products.

If requested, your Exchange unit can be shipped for overnight delivery. This efficiency is due to our logistic infrastructure and is the result of excellent teamwork among our Service and Customer Service Teams!

The Repair Program is available for those situations where the control of assets is important and when the requested turn around time is less critical.

The Exchange and Repair Programs allow global OEMs and End-Users consistent delivery time, pricing, part numbers, and order processing procedures.

• End User Extended Warranty

The End User Extended Warranty is a Service Agreement that provides coverage extension beyond the standard 12 months warranty of a product. It extends for additional 12 months the coverage from failures due to defects in material and workmanship.

By extending the warranty of purchased products, post-sales satisfaction is guaranteed. This is the result of the relevant cost decrease while cost predictability is increased.

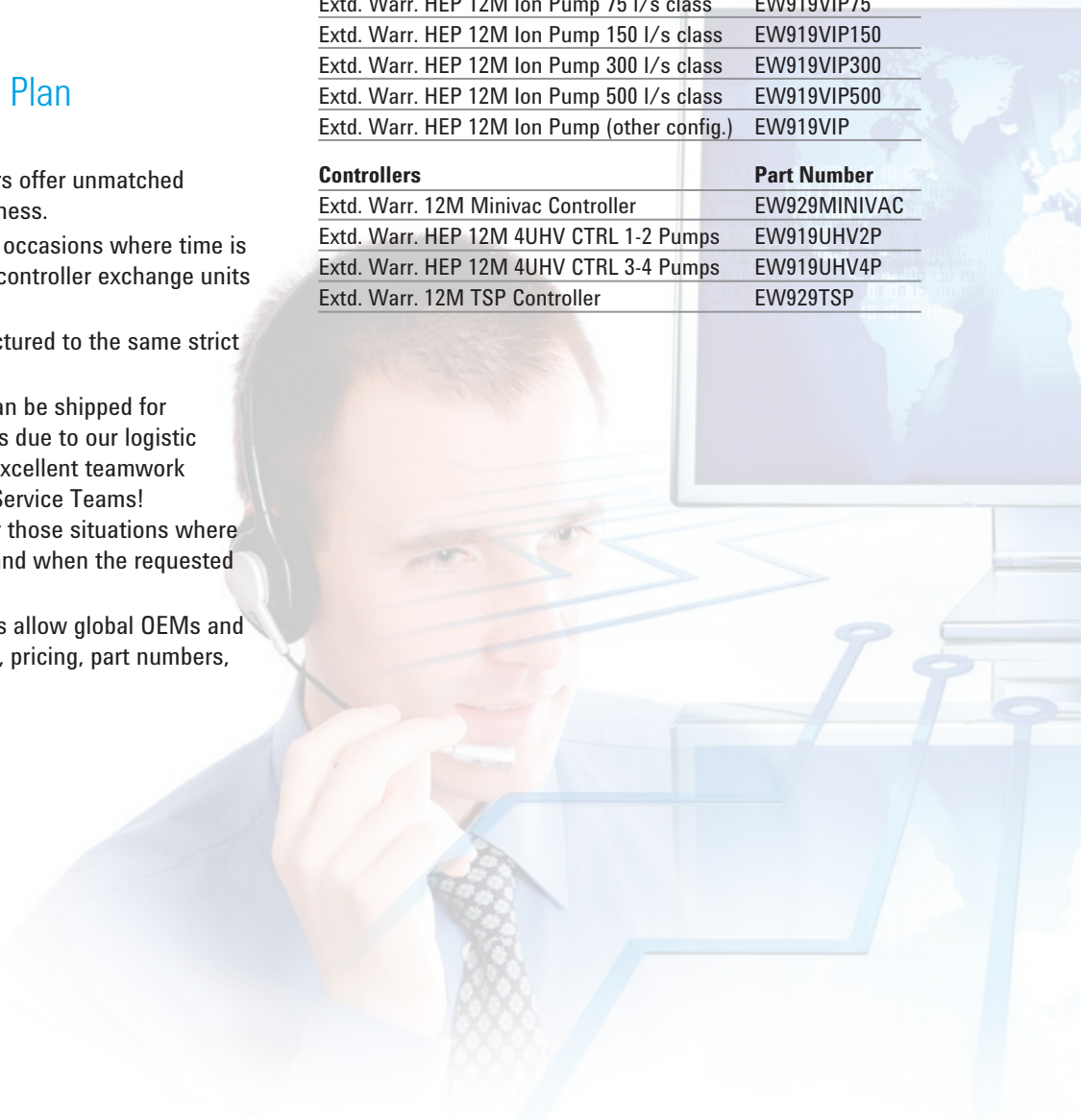
The End User Extended Warranty has been designed to cover the needs of the High Energy Physics Ultra High Vacuum applications.

• Ordering Information for End User Extended Warranty

High Energy Physics UHV Applications

Pumps	Part Number
Extd. Warr. HEP 12M Ion Pump 20 l/s class	EW919VIP20
Extd. Warr. HEP 12M Ion Pump 40 l/s class	EW919VIP40
Extd. Warr. HEP 12M Ion Pump 55 l/s class	EW919VIP55
Extd. Warr. HEP 12M Ion Pump 75 l/s class	EW919VIP75
Extd. Warr. HEP 12M Ion Pump 150 l/s class	EW919VIP150
Extd. Warr. HEP 12M Ion Pump 300 l/s class	EW919VIP300
Extd. Warr. HEP 12M Ion Pump 500 l/s class	EW919VIP500
Extd. Warr. HEP 12M Ion Pump (other config.)	EW919VIP

Controllers	Part Number
Extd. Warr. 12M Minivac Controller	EW929MINIVAC
Extd. Warr. HEP 12M 4UHV CTRL 1-2 Pumps	EW919UHV2P
Extd. Warr. HEP 12M 4UHV CTRL 3-4 Pumps	EW919UHV4P
Extd. Warr. 12M TSP Controller	EW929TSP





Technology Innovation
from the Leader in Ultra-High Vacuum

AGILENT ION PUMP 200

**The first ion pump with maximum pumping speed
at low pressure**



Agilent Technologies

The new Agilent Ion Pump 200

Technology Innovation from the Leader in UHV

NEW VIP 200: Features & Benefits

VIP 200 is the right pump for XHV (eXtreme High Vacuum) and UHV (Ultra High Vacuum) applications

- Research Centers
- Universities and Laboratories
- Particle Accelerators
- Beamlines

eXtreme High Vacuum Performance

- Maximum pumping speed at low pressure (10^{-8} mbar range)
- Best in class pumping speed for Nitrogen and Argon
- Reduced outgassing through Vacuum Firing thermal treatment
- New Diode and Noble Diode element design (more cells vs Volume)
- StarCell element: superior performance and stability for Noble gases.
- Optimized magnetic field distribution gives higher pumping speed

Versatile & Compact Design

- The smallest size in its category
- Wide range of configurations available, including side port and different HV feed throughs
- New heater design allows for high thermal efficiency and easy mounting operation
- Pumping elements fully replaceable

Agilent Quality

- Recognized Technology & Market leadership from the Ion Pump inventor: «All innovations introduced by Agilent in Ion Pump technology have become the standard in the industry»
- High standards of Manufacturing Excellence
- High reliability and performance guaranteed by severe test methodology



Image courtesy of CERN

Ion Pump Evolution Made UHV Possible

The Early History

With its acquisition of Varian, Inc. in 2010, Agilent Technologies inherited an unequalled wealth of experience in the field of high- and ultra-high vacuum technology. Varian developed and commercialized this critical enabling foundation technology and has provided clean high- and ultra-high vacuum for many developments in science and technology, from particle accelerators and analytical instruments to semiconductors and coatings.

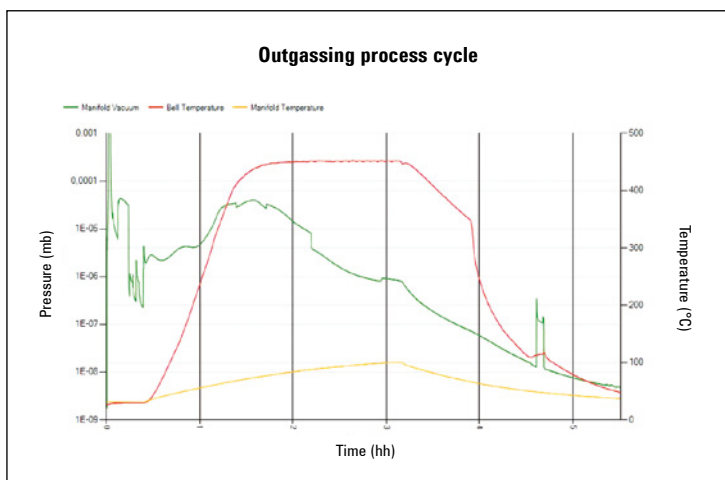
The original activity of Varian Inc., co-founded in 1948 by Sigurd and Russell Varian, the inventor of the Klystron, was in the field of microwave electron tubes. Robert Jepsen joined the company in 1951 and, as director of the Klystron research group, led investigation into electronic vacuum pumping to achieve the low pressures required by electron tubes. This led to the realization in 1957 of the first sputter ion pump (SIP), later named the Vaclon pump, of which Jepsen was co-inventor.





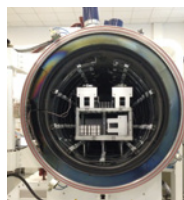
The New Agilent Ion Pump 200

Innovative Vacuum Thermal Treatment



UNIQUE VACUUM FIRING PROCESS

- Vacuum firing process applied to all surfaces exposed to vacuum, it effectively reduces Hydrogen outgassing rate and allows faster pumpdown to ultimate pressure.



STANDARD OUTGASSING PROCESS AT HIGH TEMPERATURE (450°) IN UHV OVEN

- Shortened time to reach base pressure compared to standard Ion pumps (up to 40% faster)



VACUUM FIRING

In the design of a large vacuum system, stainless steel is the most common material selected for the vacuum chambers because it can routinely achieve an outgassing rate of 10^{-12} mbar-l/(s-cm²) for hydrogen after a 24-h bakeout at 300 °C ⁽¹⁾. Much lower outgassing rates have been measured for vacuum fired stainless steel, down in the range of 10^{-15} mbar-l/(s-cm²) ⁽²⁾

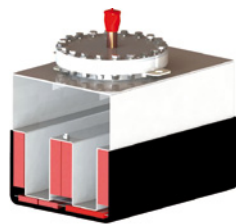
(1) R. Calder and G. Levin, Brit. J. Appl. Phys. 18, 1459 (1967).

(2) J-P. Bojon, N. Hilleret and B. Versolatto, CERN AT-VAC internal note.

Best Pumping Speed at 10⁻⁸ mbar range

NEW VIP200: OPTIMIZED MAGNETIC FIELD

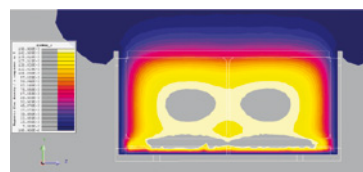
- Thanks to the optimized magnetic field distribution and element design, the VIP 200 is the most compact pump in its category.
- VIP 200 achieves peak pumping speed in the 10⁻⁸ mbar range, the normal operating range for ion pumps, while conventional ion pumps are at peak at higher pressure (10⁻⁶ mbar).



Isovalue curves showing the values of the magnetic field in the direction of the cell axis in the element housing.

Increased magnetic field (16 magnets for Diode/N. Diode, 20 magnets for starCell):

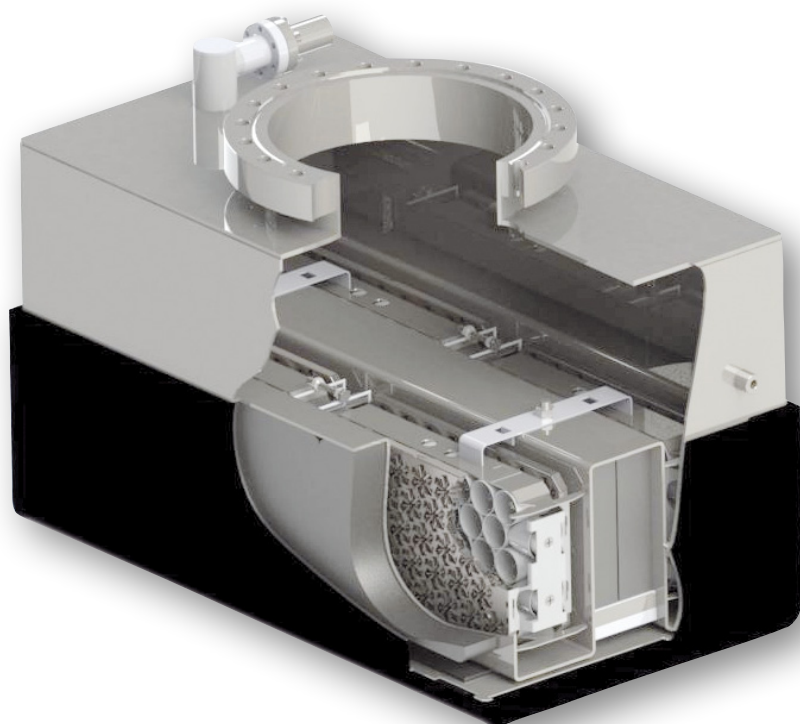
- No significant change outside the pole piece.
- Uniformity of the field inside the pump pocket is greatly enhanced
- Increased pumping speed



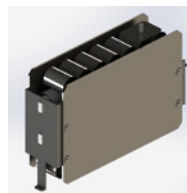
- **Dark blue:** low magnetic field values
- **Yellow:** high magnetic field values.
- **Gray in the center and bottom of the pocket:** above 1500 Gauss.
- **Gray area outside:** below the minimum of the scale



The first ion pump with maximum pumping speed at low pressure



Ion Pump Elements



DIODE & NOBLE DIODE

New element design

- New anode design
- New ceramic isolator
- #4 elements/pump
- Elements fully replaceable

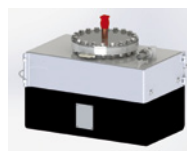


STARCELL

Incomparable performance for noble gases

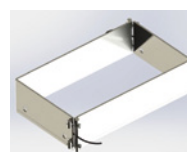
- #4 elements/pump
- Simplified assembly
- Elements fully replaceable

New Heater Design



EASY MOUNTING OPERATION

- No need to disassemble the pole piece



THERMAL EFFICIENCY

- Uniform heat distribution

4UHV Ion Pump Controller

The VIP 200 can be operated with the state-of-the-art Agilent 4UHV controller, which adjusts in every pressure range to provide the high voltage at which pumping speed is maximal for that range.

4UHV - FOR ULTRA HIGH VACUUM



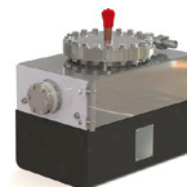
The new state-of-the-art Agilent 4UHV Ion Pump Controller can operate up to four VIP 200 simultaneously and independently (4x80W configuration) or two VIP 200 (2x200W). The 4UHV starts and controls ion pumps of any type (Diode, Noble Diode, StarCell). The variable voltage feature ensures optimum pumping speed and pressure reading throughout the operating pressure range.

Versatility



WIDE RANGE OF FEED THROUGH SELECTION:

- FISCHER
- SHV 10kV (Safeconn compatible)
- DESY (optional)

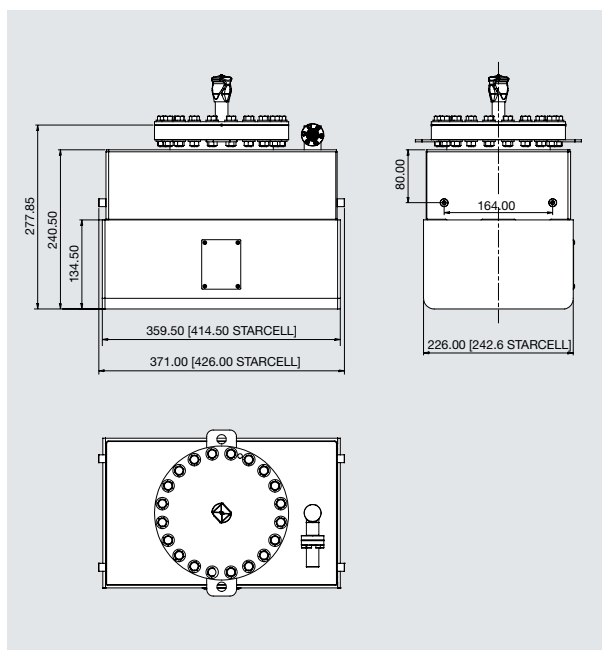
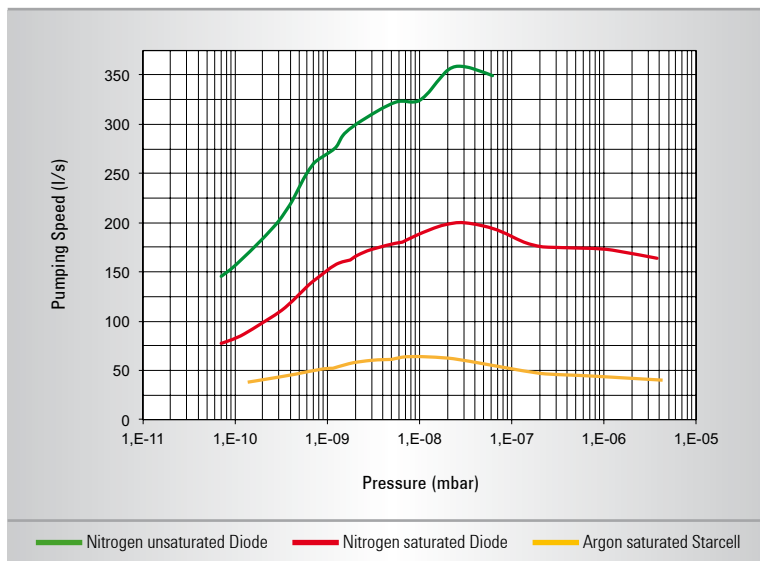


ADDITIONAL PORT (2³/₄ ConFlat)

The New Agilent Ion Pump 200



Pumping Speed vs Pressure



Technical Specifications

Specification	Model		
	Noble Diode	Diode	StarCell
Saturated pumping speed for Nitrogen (*) (l/s)	185	200	180
Saturated pumping speed for Argon (*) (l/s)	60	-	63
Operating life at 1×10^{-6} mbar of Nitrogen (hours)	50000	50000	80000
Protect current	50 mA	50 mA	50 mA
Operating voltage (max)	+7000 Vdc +/- 10 %	+7000 Vdc +/- 10 %	-7000 Vdc +/- 10 %
Suggested starting pressure (mbar)	$\leq 1 \times 10^{-5}$	$\leq 1 \times 10^{-5}$	$\leq 1 \times 10^{-4}$
Ultimate pressure (mbar)	10^{-11}	10^{-11}	10^{-11}
Inlet flange	8" CFF (NW 160) AISI 304 ESR	8" CFF (NW 160) AISI 304 ESR	8" CFF (NW 160) AISI 304 ESR
Internal volume (litres)	12.2	12.2	14
Temperature limits (°C):			
Pump with magnets	350	350	350
HV cable	220	220	220
Material:			
Body	AISI 304L	AISI 304L	AISI 304L
Cathodes	Titanium/ Tantalum	Titanium	Titanium
Anodes	AISI 304L	AISI 304L	AISI 304L
Magnets	Ferrite (Ceramic 8)	Ferrite (Ceramic 8)	Ferrite (Ceramic 8)
Pole piece	Iron	Iron	Iron
Ceramics	Alumina	Alumina	Alumina
Weight, lbs (kg)	99 (45)	99 (45)	112 (51)

* Tested according to ISO/DIS 3556-1-1992

The new Agilent Ion Pump 200

Technology Innovation from the Leader in UHV

Ordering Information

	Part number		
	Diode	Noble Diode	StarCell
Fischer feedthrough			
VIP 200 Ion Pump	X3601-64000	X3601-64018	X3601-64040
VIP 200 Ion Pump with heaters 120V	X3601-64002	X3601-64020	X3601-64042
VIP 200 Ion Pump with heaters 220V	X3601-64004	X3601-64022	X3601-64044
VIP 200 Ion Pump with with side port (2¾ in.)	X3601-64001	X3601-64019	X3601-64041
VIP 200 Ion Pump with with side port (2¾ in.) and heaters 120V	X3601-64003	X3601-64021	X3601-64043
VIP 200 Ion Pump with with side port (2¾ in.) and heaters 220V	X3601-64005	X3601-64023	X3601-64045
SHV feedthrough			
VIP 200 Ion Pump	X3601-64012	X3601-64030	X3601-64052
VIP 200 Ion Pump with heaters 120V	X3601-64014	X3601-64032	X3601-64054
VIP 200 Ion Pump with heaters 220V	X3601-64016	X3601-64034	X3601-64056
VIP 200 Ion Pump with with side port (2¾ in.)	X3601-64013	X3601-64031	X3601-64053
VIP 200 Ion Pump with with side port (2¾ in.) and heaters 120V	X3601-64015	X3601-64033	X3601-64055
VIP 200 Ion Pump with with side port (2¾ in.) and heaters 220V	X3601-64017	X3601-64035	X3601-64057
For part numbers with other feedthrough versions, please refer to your local Agilent representative.			
Cables and heaters			
HV radiation resistant cable, 4 m (13 ft), with interlock, for Fischer F/T	9290705	9290705	9290705
HV radiation resistant cable, 10 mt (33ft), with Interlock, for Fischer F/T	9290708	9290708	9290708
HV radiation resistant cable, 4 m (13 ft), for SHV F/T	9297010M023	9297010M023	9297010M023
HV radiation resistant cable, 10 mt (33ft), for SHV F/T	9297010M025	9297010M025	9297010M025
Heaters 120V (two items)	X3601-68003	X3601-68003	X3601-68005
Heaters 220V (two items)	X3601-68004	X3601-68004	X3601-68006
Heaters 120V for side port version (two items)	X3601-68007	X3601-68007	X3601-68009
Heaters 220V for side port version (two items)	X3601-68008	X3601-68008	X3601-68010

Vaclon *Plus* 800 Pump



Agilent expands its Vaclon *Plus* product family portfolio with the introduction of the Vaclon *Plus* 800 L/s ion pump.

The VIP800, with a 8 inch or 10 inch ConFlat inlet flange, can be used for those applications that require the pumping of large volume chambers where stable and ultrahigh vacuum is needed.

To ensure cleanliness, the VIP800 undergoes a complete factory process, including outgassing of the body and internal components in a high-temperature (450°C) vacuum oven. A full automated leak check is executed at the beginning and at the end of the process. To guarantee the pump's specifications, a final electrical check is performed. These processes ensure that the Agilent pump is shipped under ultrahigh vacuum with the highest level of cleanliness available in the ion pump market.

The VIP800 is available in StarCell configuration, and with or without heater to satisfy most common application requests.

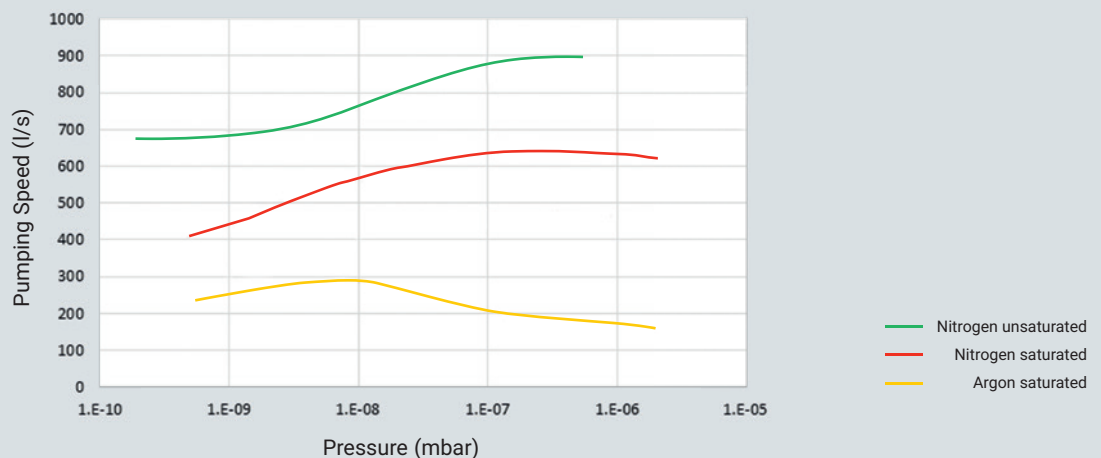
Vaclon Plus 800 Pump

Technical Specifications

Technical Specifications		
	Flange 10"	Flange 8"
Saturated Pumping Speed* for Nitrogen	650 L/s	530 L/s
Unsaturated Pumping Speed* for Nitrogen	910 L/s	685 L/s
Saturated Pumping Speed* for Argon	295 L/s	260 L/s
Pumping Speed* for Hydrogen	1900 L/s	1600 L/s
Operating life @1e-6 mbar	80000 h	
Protect current	150 mA	
Maximum Operating Voltage	-7000 Vdc (+/-10%)	
Maximum Starting Pressure	≤5 x 10 ⁻² mbar	
Ultimate Pressure	<1x10 ⁻¹¹ mbar	
Inlet flange	8 in CFF (NW 150) AISI 304 ESR 10 in CFF (NW 200) AISI 304 ESR	
Element type	StarCell	
Feedthrough style	Fischer	
Max Temperature limit with magnet	350°C	
Max Temperature limit without magnet	450°C	
Recommended maximum baking temperature with Ion pump ON	220°C (HV cable maximum temperature)	
Materials	Body	AISI304 L
	Cathodes	Titanium
	Anodes	AISI 304L
	Magnets PolePiece	Ferrite (Ceramic 8) Iron
Weight without heaters	lbs (kg)	437 (198)
Special versions available	On request	

*Tested according to ISO/DIS 3556-1-1992

Pumping Speed vs Pressure (Flange CFF 10" version)



Ordering Information

Pumps	Part Numbers
VIP800 pump with StarCell element, inlet flange 10"	X3607-64200
VIP800 pump with StarCell element, inlet flange 10", with 230 V heater installed	X3607-64201
VIP800 pump with StarCell element, inlet flange 10", with 115 V heater installed	X3607-64202
VIP800 pump with StarCell element, inlet flange 8"	X3607-64203
VIP800 pump with StarCell element, inlet flange 8", with 230 V heater installed	X3607-64204
VIP800 pump with StarCell element, inlet flange 8", with 115 V heater installed	X3607-64205

Double ended and side port versions available on request.

Controller Unit: 4UHV	Part Numbers
200W NEG	9299010
2 x 80W NEG	9299200
2 x 200W NEG	9299020
4 x 80W NEG	9299400
2 x 80W NEG and 1 x 200W NEG	9299210
Cables selection	Part Numbers
Pumps are equipped with standard Fischer high voltage feedthroughs.	
Cable lengths available:	
4 m Fischer cable with interlock (for Fischer feedthrough)	9290705
7 m Fischer cable with interlock (for Fischer feedthrough)	9290707
10 m Fischer cable with interlock (for Fischer feedthrough)	9290708
20 m Fischer cable with interlock (for Fischer feedthrough)	9290709
Replacement Parts	Part Numbers
HV feedthrough	9595125
Pumping element* StarCell	9199030
Heaters**, 115 V, (Input Power 800 W)	X3607-68001
Heaters**, 230 V, (Input Power 800 W)	X3607-68000

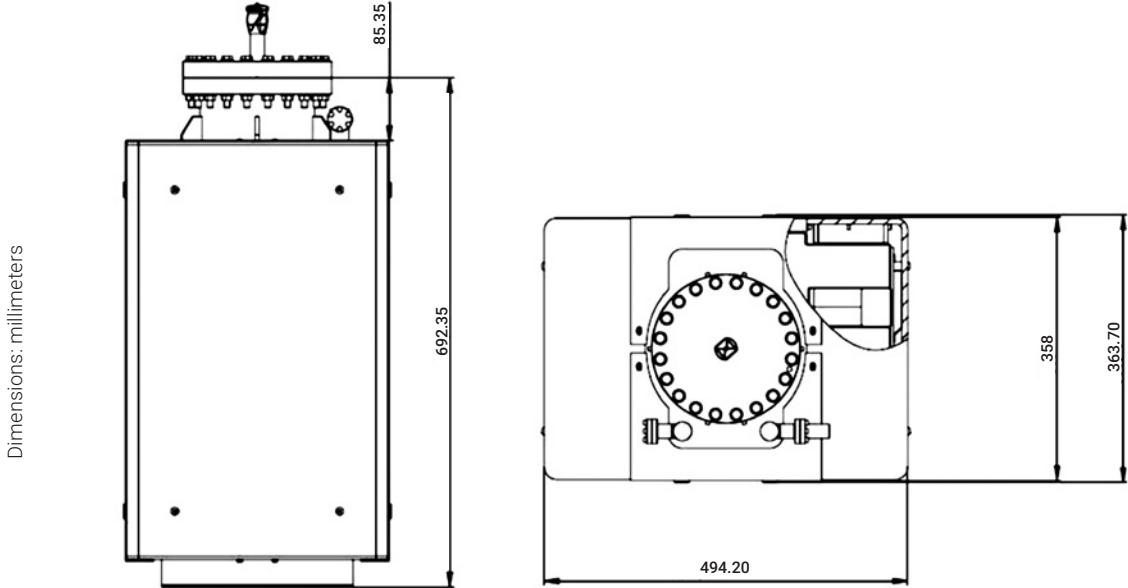
*Quantity required: 12.

**To order heaters for replacement or upgrading of existing pumps, please contact your local Agilent Vacuum Products representative.

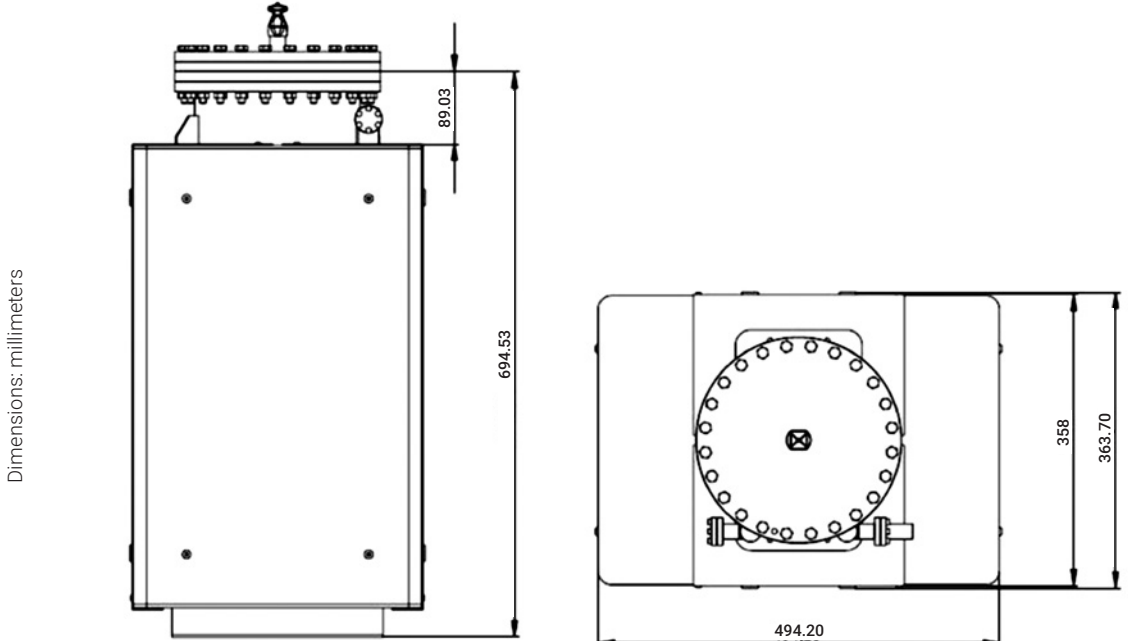
Vaclon Plus 800 Pump

Outline Drawings

Version with 8" flange



Version with 10" flange



Agilent Vaclon *Plus* 1000



The UHV Solution for Gravitational Waves Detectors

Agilent is now expanding its Vaclon *Plus* product family portfolio with the introduction of the Vaclon *Plus* 1000 L/s ion pump.

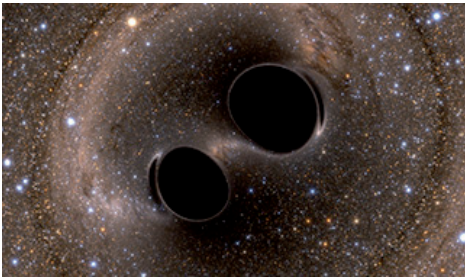
The VIP1000, with a 12 inch ConFlat inlet flange, can be used for those applications that require the evacuation of large volume chambers where stable and ultrahigh vacuum is needed.

An example of a suitable application for the new VIP1000 is undoubtedly the study and detection of gravitational waves. In this field, large pumping volumes and speeds are required along with the complete absence of vibration during system operation.

To ensure cleanliness, the VIP1000 undergoes a complete factory process, including outgassing of the body and internal components in a high-temperature (450°C) vacuum oven. A full automated leak check is executed at the beginning and at the end of the process. To guarantee the pump's specifications, a final electrical check is performed. These processes ensure that the Agilent pump is shipped under ultrahigh vacuum with the highest level of cleanliness available in the ion pump market.

The VIP1000 can be purchased in Diode and StarCell configuration, and with or without heater to satisfy most common application requests.

Agilent Vaclon *Plus* 1000



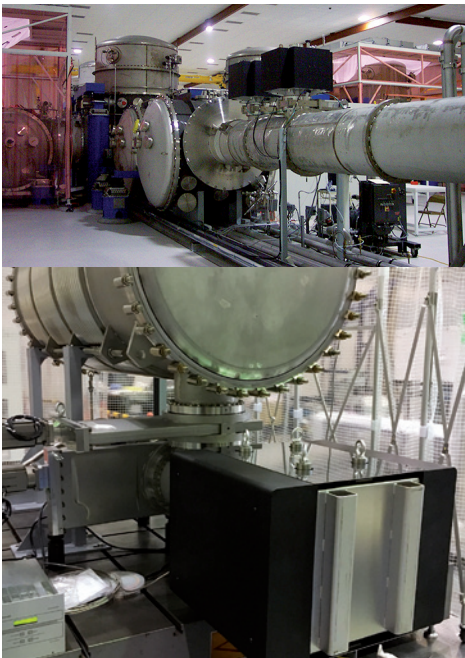
Features

- Proven Agilent quality
- Noncontaminating technology
- Long operational life
- Vibration-free
- Radiation resistance
- Low cost of ownership



Target Applications

- Detectors of gravitational waves
- Large vacuum chambers
- Space simulation
- Research centers
- Laboratories



Gravitational Waves Detected 100 Years After Einstein's Prediction

Agilent has contributed to the detection of gravitational waves 100 years after Einstein predicted them.

The Laser Interferometer Gravitational-Wave Observatory (LIGO) is designed to open the field of gravitational-wave astrophysics through the direct detection of gravitational waves predicted by Einstein's General Theory of Relativity. LIGO's multikilometer-scale gravitational wave detectors use laser interferometry to measure the minute ripples in space-time caused by passing gravitational waves from cataclysmic cosmic sources. These cosmic sources can include the mergers of pairs of neutron stars or black holes, or supernovae. LIGO consists of two widely separated interferometers within the United States, one in Hanford, Washington and the other in Livingston, Louisiana. These interferometers are operated in unison to detect gravitational waves.

KAGRA is a Gravitational Wave detector under construction in Japan, where Agilent VIP1000 Ion Pumps will be part of the vacuum system (assembled and tested at MIRAPRO).

Creating ultraclean and stable high vacuum in these multikilometer detectors is instrumental to the operation of the entire system and was one of the key technological challenges. Furthermore uptime, reliability, and vibrationless operation are an absolute requirement for such detectors.

Agilent designed and built customized ion pumps to fulfil all these stringent criteria, providing the ideal vacuum conditions for the success of this experiment.

Agilent Ion Pumps mounted on LIGO Gravitational Waves Detector and at MIRAPRO for KAGRA Gravitational Wave Interferometer.

* The images are courtesy of
Caltech/MIT/LIGO Laboratory (USA)
and of MIRAPRO CO.LTD (Japan)

Agilent Vaclon Plus 1000

Technical Specification

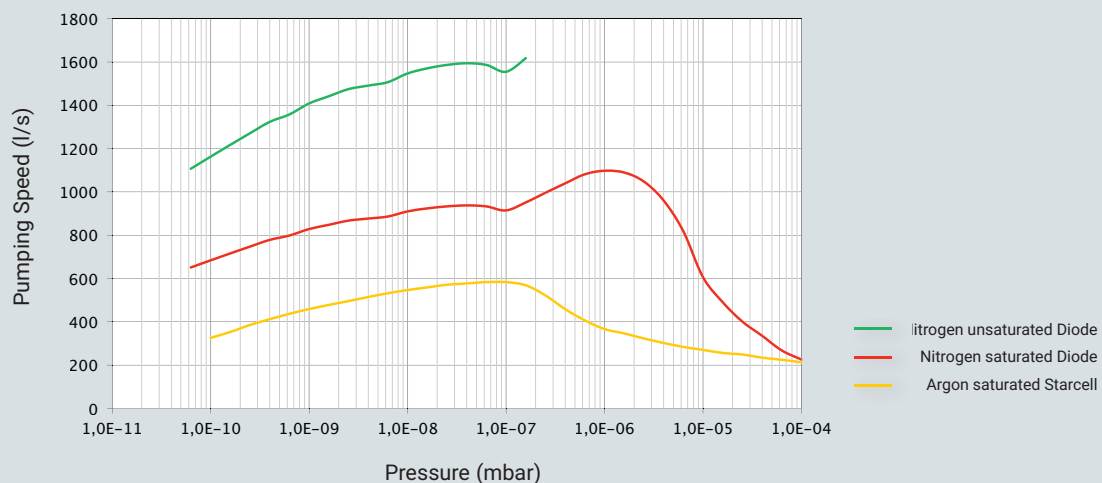
Technical Specification		
	Diode	StarCell
Saturated pumping speed for Nitrogen*	1100 L/s	900 L/s
Saturated pumping speed for Argon*		585 L/s
Operating life at 1E ⁻⁶ mbar for Nitrogen	50000 hours	80000 hours
Recommended maximum baking pressure with ion pump on	5 x 10 ⁻⁶ mbar	
Protect current	200 mA	
Maximum operating voltage	+7000 Vdc +/- 10%	-7000 Vdc +/- 10%
Recommended starting pressure	≤1 x 10 ⁻⁶ mbar	≤1 x 10 ⁻⁴ mbar
Ultimate pressure	10 ⁻¹¹ mbar	
Inlet flange	12" CFF (NW250) AISI 304 ESR or 316LN ESR	
Internal volume	136 litres	
Temperature limits:		
Pump without magnets	450 C°	
Pump with magnets	350 C°	
HV cable	220 C°	
Material	Body	AISI 304L
	Cathodes	Titanium
	Anodes	AISI 304L
	Magnets	Ferrite (Ceramic 8)
	Pole piece	Iron
Weight without heaters	lbs (kg)	585 (265)

* Tested according to ISO/DIS 3556-1-1992

Ordering Information

Configurations	Part Numbers
VIP1000 Diode without heater	X3604-64000
VIP1000 Diode with 115 V heater	X3604-64101
VIP1000 Diode with 230 V heater	X3604-64102
VIP1000 StarCell without heater	X3604-64120
VIP1000 StarCell with 115 V heater	X3604-64121
VIP1000 StarCell with 230 V heater	X3604-64122
The VIP1000 can be driven by the 4UHV controller with the configuration with 200 Watts.	
Controller Unit: 4UHV	Part Numbers
200W NEG	9299010
200W POS	9299011
The selection of the controller is strictly dependent on the starting pressure. If starting pressure is in the 10 ⁻⁶ mbar range, a single channel with 200 Watts is sufficient to start and maintain the operational function of the pump. If starting pressure is above 10 ⁻⁶ mbar range, please contact your Agilent representative.	
Cables selection	Part Numbers
Pumps are equipped with standard Fischer high voltage feedthroughs.	
Cable lengths available:	
4 m Fischer cable	9290705
7 m Fischer cable	9290707
10 m Fischer cable	9290708
20 m Fischer cable	9290709

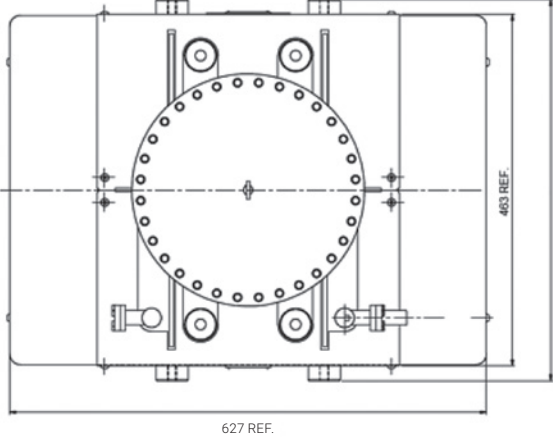
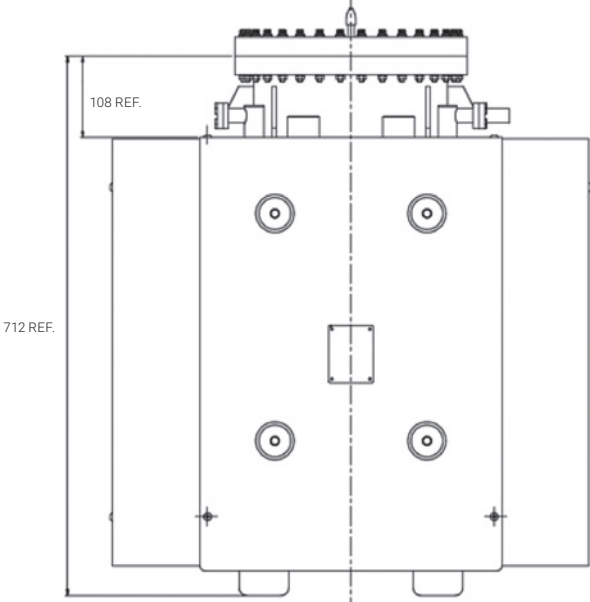
Pumping Speed vs Pressure



Agilent Vaclon Plus 1000

Outline Drawing

Dimensions: millimeters [inches]



3D Drawings available for download

New Agilent Ion CombiNEG 40-400



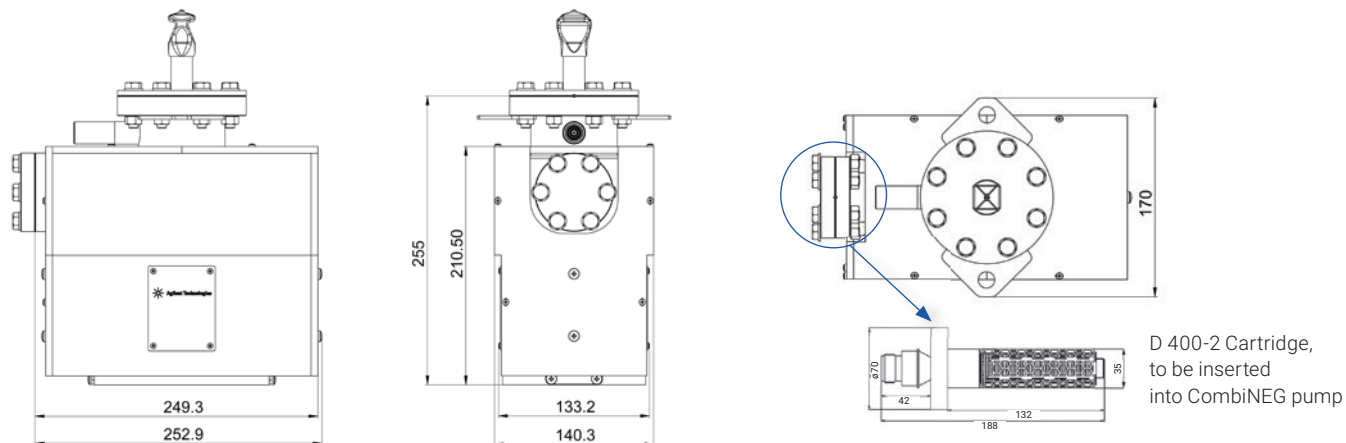
The Perfect Partnership Between UHV Leaders

The Agilent Ion CombiNEG pumps are the result of the more than 100 years' combined vacuum experience of Agilent Technologies and SAES GETTERS. Agilent (formerly Varian Vacuum) is the inventor of the ion pump, and SAES the originator of the NEG pump concept.

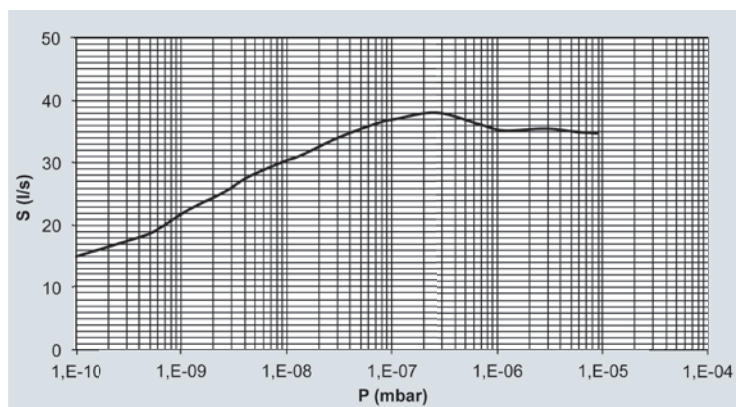
The Ion CombiNEG pumps combine the state-of-the-art Agilent Ion StarCell pump with the SAES NEG cartridge. These new pumps provide optimum pumping speed for getterable gases, methane, and noble gases and reach pressure values as low as 10^{-12} mbar.

The easy insertion of the NEG cartridge into the ion pump makes the Ion CombiNEG pump a smart solution, combining ion pump and NEG cartridge technologies in the same pump volume.

Outline Drawings

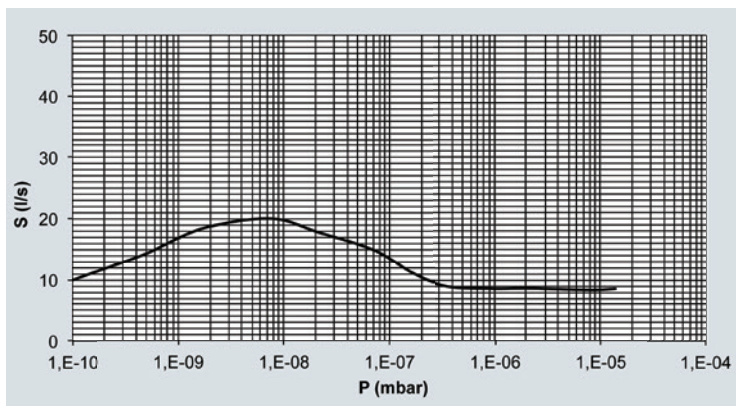


Pumping Speed - Ion CombiNEG 40-400 - StarCell, Nitrogen



Typical pumping speed vs pressure diagram for Nitrogen (Ion Pump only, StarCell, saturated, equipped with shield)

Pumping Speed - Ion CombiNEG 40-400 - StarCell, Argon



Typical pumping speed vs pressure diagram for Argon (Ion Pump only, StarCell, saturated, equipped with shield)

Technical Specifications

Specification	Model	
	Diode (*)	StarCell
Nominal saturated pumping speed for Nitrogen (L/s) with shield (without shield)	35 (39)	38 (43)
Nominal saturated pumping speed for Argon (L/s) with shield (without shield)	-	20 (22)
Operating life at 1E-6 mbar of Nitrogen (hours)	50000	80000
Suggested maximum baking pressure with ion pump on (mbar)	5E-6	
Protect current	30 mA	
Operating voltage (max)	+7000 Vdc +/- 10 %	-7000 Vdc +/- 10 %
Suggested starting pressure (mbar)	≤ 1E-5	≤ 1E-4
Ultimate pressure (mbar)	below 1E-11	
Inlet flange	4"1/2 CFF (DN63CF) AISI 304L ESR	
Side port	2"3/4 CFF (DN40CF)	
Internal volume (litres)	3.0	
Temperature limits (°C):		
Pump without magnets	450	
Pump with magnets	350	
HV cable	220	
Getter pump	(**)	
Material:	Body	AISI 304L
	Cathodes	Titanium Titanium
	Anodes	AISI 304L
	Magnets	Ferrite (Ceramic 8)
	Pole piece	Iron
Weight, lbs (kg)	49.6 (22.5)	

(*) Pumping element optimized to reduce leakage current

(**) Refer to the Operating Instructions Manual provided with the getter pump.

NEG Cartridge

The Ion CombiNEG 40-400 has a side port CFF 2”3/4 that is suitable to accommodate a SAES CapaciTorr D 400-2 getter pump.

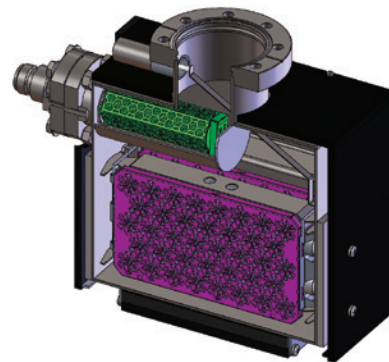
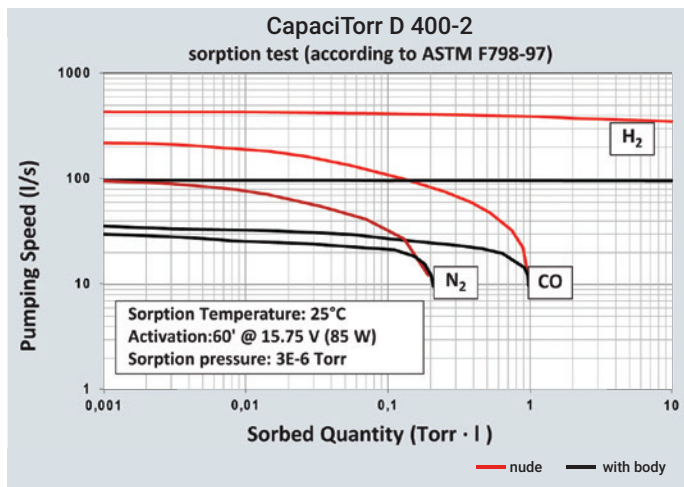
The CapaciTorr D 400-2 pump uses the high performing SINTERED St 172 (Zr-V-Fe) material in the form of disks to achieve high pumping performances in a very compact configuration.

A dedicated power supply is needed for the D 400-2 pump.



D 400-2 Cartridge

D 400-2 Pumping Speed



Cut-away showing the main pump assembly of the Ion CombiNEG 40-400 pump (StarCell version), with the D 400-2 getter pump mounted.

Technical Specifications

Typical Pump Characteristics		CapaciTorr D 400-2
Alloy Type		St 172
Alloy Composition		ZrVFe
Getter Mass (g)		45
Getter Surface (cm ²)		380
Pumping Speed (l/s)	H ₂	400
	CO	180
Sorption Capacity (Torr · l)	H ₂	450
	CO at 25 °C	0.9
	CO total	400

Cartridge Controller Characteristics	
Input	110-240 VAC +/-10%
Frequency	50-60 Hz +/-10%
Mains cord connector	IEC Type 6A 250V
Over-voltage class	Cat II
Output voltage	0-35 VDC
Output current	6.0 A
Output power	175 W + 18 W (overload)
NEG Temperature Monitoring	✓
Tuning of output voltage	✓
Tuning of ramp time	✓
Tuning of power off time	✓
NEG Activation	Adjustable Voltage
NEG Conditioning	Adjustable Voltage
Operation Mode	Keyboard; Remote (Modbus protocol over Ethernet or RS232 interface)
Interlock	✓
USB port (for data logging)	✓

Ordering Information - Ion CombiNEG 40-400 Pump

Pumps	Part number
Ion CombiNeg 40-400 pump, Diode, with heater, 115V	X3606-64000
Ion CombiNeg 40-400 pump, Diode, with heater, 230V	X3606-64001
Ion CombiNeg 40-400 pump, StarCell, with heater, 115V	X3606-64040
Ion CombiNeg 40-400 pump, StarCell, with heater, 230V	X3606-64041
Cables and heaters	
HV radiation resistant cable, 4 m (13 ft), with interlock (for Fischer feedthrough)	9290705
HV radiation resistant cable, 7 m (23 ft), with interlock (for Fischer feedthrough)	9290707
HV radiation resistant cable, 10 m (33 ft), with interlock (for Fischer feedthrough)	9290708
HV radiation resistant cable, 20 m (66 ft), with interlock (for Fischer feedthrough)	9290709
Heater, Ion CombiNEG 40-400 pump, 230V, 160W	9192837M005
Heater, Ion CombiNEG 40-400 pump, 120V, 160W	9192837M006

For cable part numbers with other feedthroughs, please refer to your local Agilent representative.

Controllers for Ion CombiNEG Pump	Part Number
4UHV Controller*	
200 W neg	9299010
200 W pos	9299011
IPCMini Controller*	
IPCMini, 110/220 V Fischer HV, neg	X3602-64000
IPCMini, 110/220 V Fischer HV, pos	X3602-64001

*Ion pump controllers - 4UHV and IPCMini are available in multiple configurations.

Ordering Information - D 400-2 Cartridge

Getter Pump	
D 400-2 NEG Cartridge, with heater	X3605-68010
CF35 base flange with connector	X3605-68020
Controller* for NEG Cartridge D 400-2	X3605-68030
Cable (controller to cartridge) for NEG Cartridge D 400-2, 3 m	X3605-68050
Cable (controller to cartridge) for NEG Cartridge D 400-2, 20 m	X3605-68054

(*) Power cord not included

New Agilent Ion CombiNEG 150-1000 and 150-2000

The Perfect Partnership Between UHV Leaders

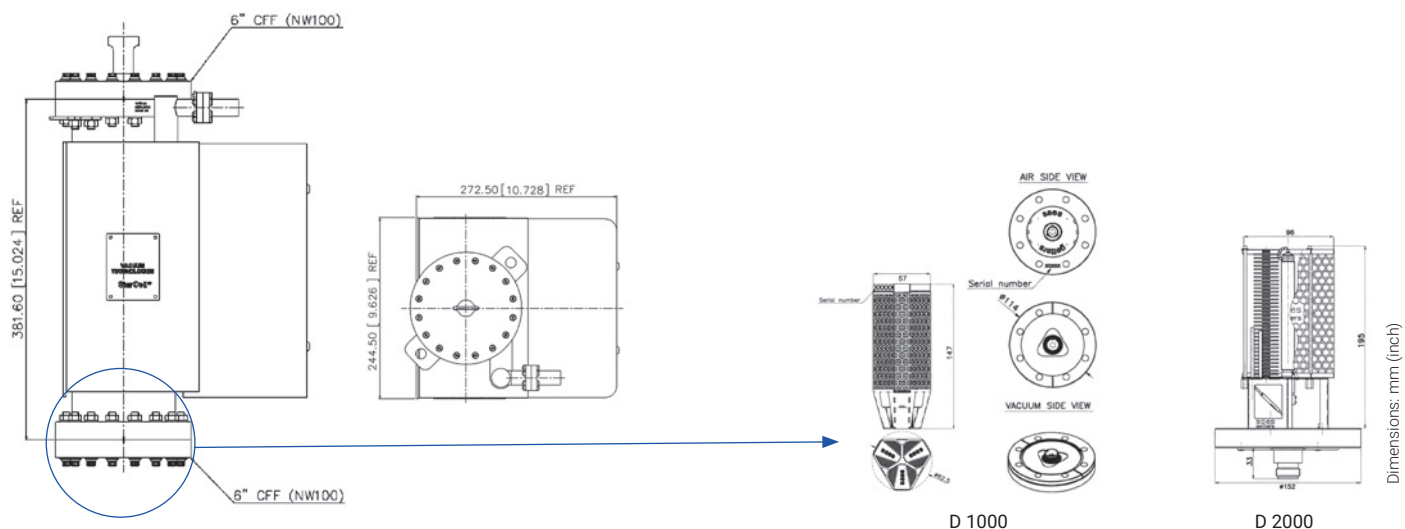
The Agilent Ion CombiNEG pumps are the result of the more than 100 years' combined vacuum experience of Agilent Technologies and SAES GETTERS. Agilent (formerly Varian Vacuum) is the inventor of the ion pump, and SAES the originator of the NEG pump concept.

The Ion CombiNEG pumps combine the state-of-the-art Agilent Ion StarCell pump with the SAES NEG cartridge. These new pumps provide optimum pumping speed for getterable gases, methane, and noble gases and reach pressure values as low as 10^{-12} mbar.

The easy insertion of the NEG cartridge into the ion pump makes the Ion CombiNEG pump a smart solution, combining ion pump and NEG cartridge technologies in the same pump volume.

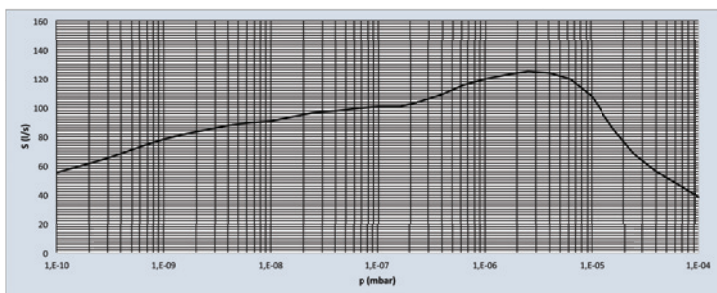


Outline Drawings



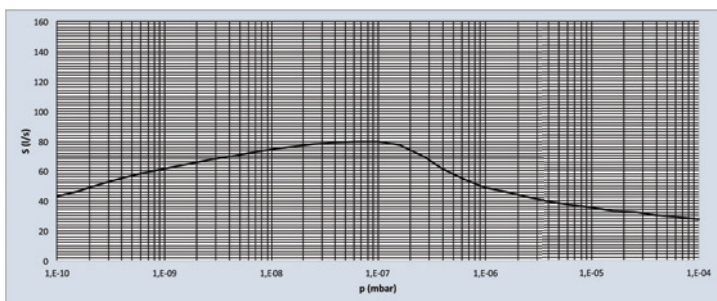
D 1000 Cartridge, and D 2000 Cartridge to be inserted into CombiNEG pump

Pumping Speed - Ion CombiNEG 150-1000 and 150-2000 - StarCell, Nitrogen



Typical pumping speed vs pressure diagram for Nitrogen (Ion Pump only, StarCell, saturated, equipped with shield)

Pumping Speed - Ion CombiNEG 150-1000 and 150-2000 - StarCell, Argon



Typical pumping speed vs pressure diagram for Argon (Ion Pump only, StarCell, saturated, equipped with shield)

Technical Specifications

Specifications		
Nominal saturated pumping speed for Nitrogen (L/s) with shield	125	
Nominal saturated pumping speed for Argon (L/s) with shield	80	
Operating life at 1E-6 mbar (hours)	80,000	
Max starting current	300 mA	
Max baking current	25 mA	
Protect current	50 mA	
Operating voltage (max)	-7000 Vdc +/- 10 %	
Maximum starting pressure (mbar)	$\leq 1 \times 10^{-3}$	
Ultimate pressure (mbar)	Below 10^{-11}	
Inlet flange	6" CFF (NW 100) AISI 304 ESR	
Side port	6" CFF (NW 100)	
Internal volume (litres)	12.1	
Maximum baking temperature (°C)	350	
Temperature limits (°C):		
Pump without magnets	400	
Pump with magnets	350	
Flange	500	
Getter Pump	(*)	
Material:	Body	AISI 304 SST
	Cathodes	Titanium
	Anodes	AISI 304 SST
	Magnets	Ferrite
Weight, lbs (kg)	94 (43)	

(*) Refer to the Operating Instructions Manual provided with the getter pump

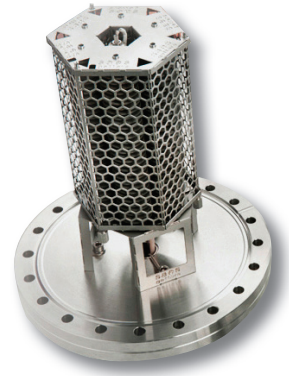
NEG Cartridges

The Ion CombiNEG 150-1000 and 150-2000 have a side port CFF 6" that is suitable to accommodate a SAES CapaciTorr D 1000 or D 2000 getter pumps.

The CapaciTorr D 1000 and D 2000 pumps use the high performing SINTERED St 172 (Zr-V-Fe) material in the form of disks to achieve high pumping performances in a very compact configuration. A dedicated power supply is needed for the D 1000 or D 2000 pumps.

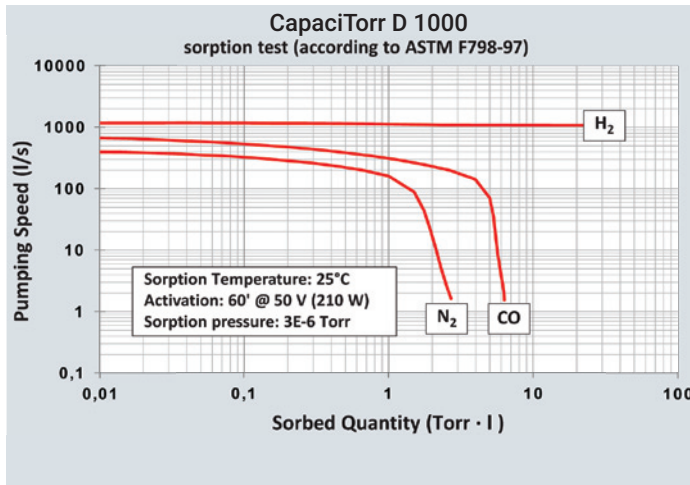


D 1000 Cartridge

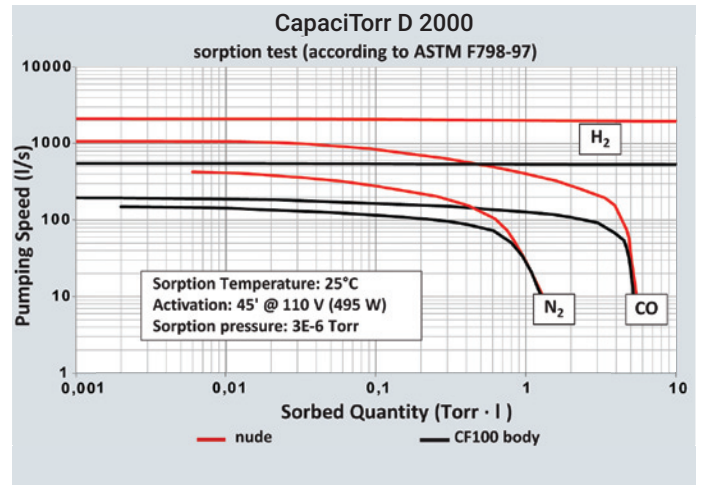


D 2000 Cartridge

D 1000 Pumping speed

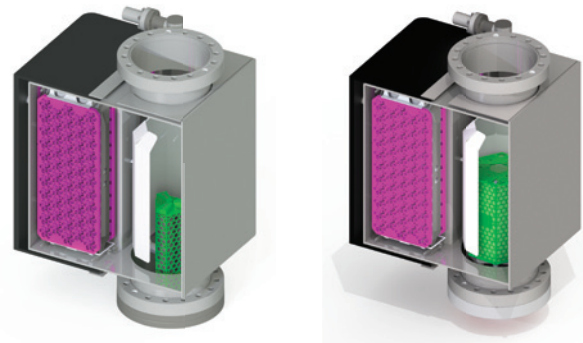


D 2000 Pumping speed



Technical Specifications

Typical Pump Characteristics		D 1000	D 2000
Alloy Type		St 172	St 172
Alloy Composition		ZrVFe	ZrVFe
Getter Mass (g)		136	225
Getter Surface (cm ²)		1140	1900
Pumping Speed (L/s)	H ₂	1000	2000
	CO	600	1000
Sorption Capacity (Torr · l)	H ₂	1360	2250
	CO at 25 °C	4	5
	CO total	1224	2000
Cartridge Controller Characteristics			
Input			
Maximum power		3.5 kW	
Supply voltage		110-220 V _{AC}	
Frequency		50-60 Hz	
Input current		20 A / 110 Vac - 14 A / 230 Vac	
Noise at 1 mt		< 40 dBA	
Mains cord connector		IEC Type 16A 250V	
Output 1-4 at 110 V			
Output power		700 W+overload	
Output voltage		0-110 V _{DC}	
Overload		110% for one minute	
Supply current		10 A	



Cut-aways showing the main pump assembly of the Ion CombiNEG 150-1000 and 150-2000 pumps (StarCell version), with the D 1000 and D 2000 getter pumps mounted.

Ordering Information Ion CombiNEG 150-1000 and 150-2000 Pumps

Pumps	Part number
Ion CombiNeg 150-1000/2000 pump, StarCell, with heater, 120 V	X3606-64060
Ion CombiNeg 150-1000/2000 pump, StarCell, with heater, 230 V	X3606-64061

Note: Diode versions available on request

Cables and heaters	
HV radiation resistant cable, 4 m (13 ft), with interlock (for Fischer feedthrough)	9290705
HV radiation resistant cable, 7 m (23 ft), with interlock (for Fischer feedthrough)	9290707
HV radiation resistant cable, 10 m (33 ft), with interlock (for Fischer feedthrough)	9290708
HV radiation resistant cable, 20 m (66 ft), with interlock (for Fischer feedthrough)	9290709
Heater, Ion CombiNEG 150-1000 or 2000 pump, 120V, 160W	9190072
Heater, Ion CombiNEG 150-1000 or 2000 pump, 220V, 160W	9190073

For part numbers of cables with other feedthrough types, please refer to your local Agilent representative.

Controllers for Ion CombiNEG Pump	Part Number
4UHV Controller*	
200 W neg	9299010
200 W pos	9299011
IPCMini Controller*	
IPCMini, 110/220 V Fischer HV, neg	X3602-64000
IPCMini, 110/220 V Fischer HV, pos	X3602-64001

* Ion pump controllers 4UHV and IPCMini are available in multiple configurations.

Ordering Information D 1000 and D 2000 Cartridges

Getter Pump	
D 1000 NEG Cartridge, with Heater	X3605-68012
CF100 base flange with connector (for D 1000)	X3605-68022
Cable (controller to cartridge) for NEG Cartridge D 1000, 3m	X3605-68051
D 2000 NEG Cartridge	X3605-68013
CF100 base flange with connector and heater (for D 2000)	X3605-68023
Cable (controller to cartridge) for NEG Cartridge D 2000, 3m	X3605-68052
Controller* for NEG Cartridge D-1000 and D-2000	X3605-68031

(* Power cord with Type F (Schuko) plug included

Agilent 4UHV Ion Pump Controller

For Ultra High Vacuum



For Ultra High Vacuum

Agilent 4UHV Ion Pump Controller

The state-of-the-art Agilent 4UHV ion pump controller operates up to four pumps simultaneously and independently. The 4UHV starts and controls ion pumps of any type (Diode, Noble Diode, StarCell) and size (from 10 to 1000 L/s). A large four-line LCD display allows simultaneous reading of individual pump voltage, current, and pressure. The variable voltage feature ensures optimum pumping speed and pressure reading throughout the operating pressure range. Built-in setpoints, remote operation and RS-232/485 computer interface; Profibus and Ethernet are standard. A Fast Response version of the 4UHV controller is also available.

Optimized pumping speed

The 4UHV will select the right operating voltage to optimize the pumping speed of your ion pumps. By applying high voltage in accordance with operating pressure, pumping speed performance is improved.

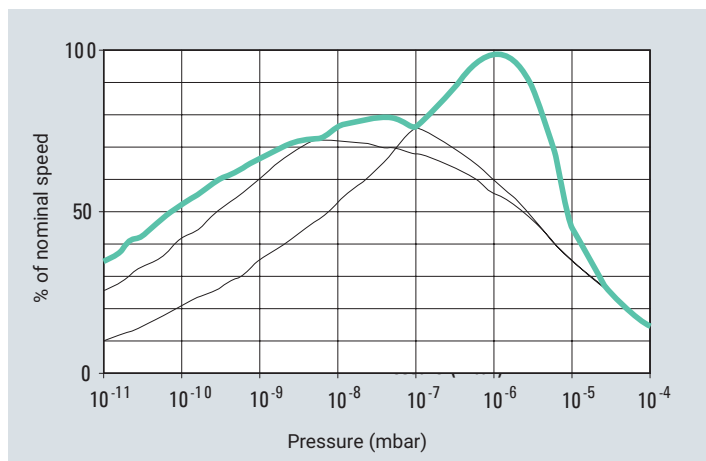
This is because the energy with which the ion bombards the cathode is the nominal applied HV, reduced by the space charge effect due to the electron cloud present in the ion pump cell. Since the space charge effect is pressure related, a variable HV is applied to maintain optimum bombardment energy, resulting in the best possible pumping performance at any pressure (see graph below).



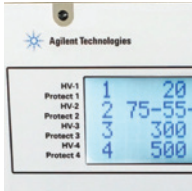
Ion Pump Leadership

Since the invention of the Vaclon Pump in 1957, all of the major innovations in UHV have come from Agilent Technologies (formerly Varian Vacuum)

Pumping Speed vs Pressure at different voltages



Agilent 4UHV Features



Versatility

The 4UHV is available in different configurations, in order to independently power, control, and monitor any combination of multiple pumps of different sizes, from one to four pumps, from 10 to 1000 L/s. For each number of pumps to be operated, several options are available:

- 200 W for a single pump
- 2 x 80 W or 2 x 200 W for two pumps
- 2 x 80 + 200 W for three pumps
- 4 x 80 W for four pumps



Intelligence

To access the unit, you can use analog or RS-232/485 ports.

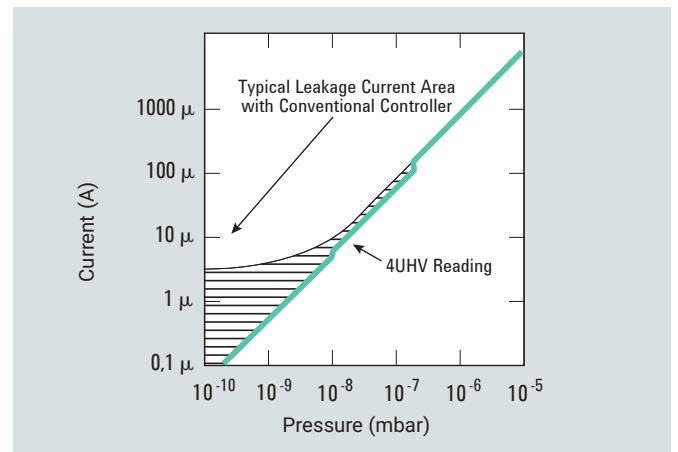
The controller uses the same protocol as our other intelligent vacuum devices (TwisTorr turbo pump controller and inverter driven scroll and rotary vane pumps), giving you fast, convenient access to all elements of the vacuum system. Profibus and Ethernet communications, and Fast Response version are available as standard.



Pressure reading

The 4UHV is preprogrammed to automatically convert current reading of any Vaclon Plus pump into pressure. Thanks to its ability to detect ion current as low as 10 nA, it allows pressure measurement in the 10⁻¹⁰-10 mbar range. To ensure reliable pressure reading down to the UHV region, the 4UHV optimizes the applied high voltage as a function of pressure. As a result, the leakage current of the ion pump is eliminated, thereby providing more accurate pressure readings (see the curve on the right).

Typical Current vs Pressure Curve



Safety

To protect you against high voltage, the cable is equipped with an interlock system, which immediately shuts down the high voltage when the plug is removed from the pump. The protect mode limits the current to protect the pump and the controller.



Low noise

For Scanning Electron Microscopes (SEM) applications especially, the remaining AC component of the HV output is reduced to a minimum. It is much lower than in any other existing unit, eliminating the need for extra filters in many cases.

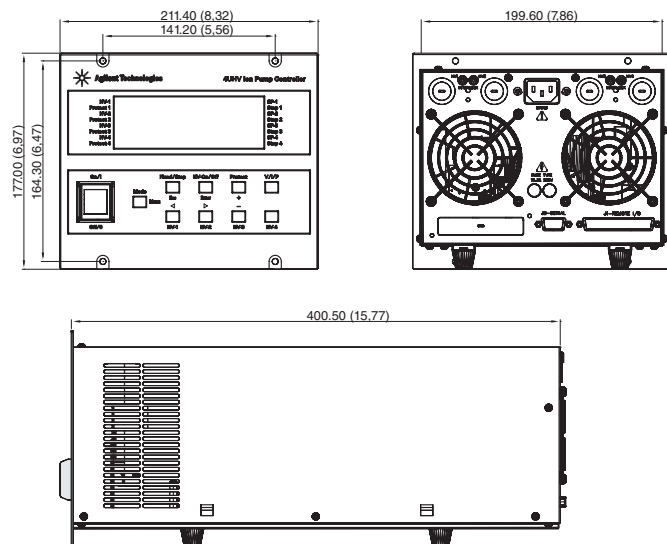
Technical Specifications

	4UHV standard	4UHV Fast Response
Input voltage	100-240 Vac (±10%)	100-240 Vac (±10%)
Input frequency	50-60 Hz	50-60 Hz
Dimensions	400.5 x 211.4 x 177.0 mm (l x w x h)	400.5 x 211.4 x 177.0 mm (l x w x h)
Display	4 rows with 20 characters	4 rows with 20 characters
Available configurations	1 x 200W, 2 x 200W, 2 x 80W, 4 x 80W, 1 x 200W + 2 x 80W	1 x 200W, 2 x 200W, 2 x 80W, 4 x 80W, 1 x 200W + 2 x 80W
Minimum configuration	One HV card with 200 W or 2x80 W	One HV card with 200 W or 2x80 W
Output voltage (open circuit)	3.5 and 7 kV	3.5 and 7 kV
Output current (short circuit)	40 mA for 80 W channel 100 mA for 200 W channel	40 mA for 80 W channel 100 mA for 200 W channel
Modes of operation	Local / Serial / Remote	Local / Serial / Remote
Front panel readings	Voltage, Pressure, Current, Status	Voltage, Pressure, Current, Status
Safety marks	CE, C_CSA_US	CE, C_CSA_US
Current measurement range	10 nA to 100 mA	10 nA to 100 mA
Input signals	On/Off; Protect; Step Mode	On/Off; Protect; Step Mode
Output signals	Analog Out; NC setpoint; NO Set-point	Analog Out; NC setpoint; NO Set-point
HV connector	Fischer Type 105	Fischer Type 105
Output power maximum	400 W	400 W
Communications	RS232/485 standard, Profibus, Ethernet	RS232/485 standard, Profibus, Ethernet
Relay and analog output response time	1 s typical (*)	20 ms typical (*) (**)
Relay	4 relays configurable	Only one for each channel
Analog Output	4 relays configurable	Only one for each channel

(*) test performed with a step load from 100nA to 1mA and setpoint set to 1µA

(**) Warning: Electrical discharges may occur inside the ion pump. To achieve 20ms response time filtering on the relay and on the analog output has been reduced. If, by chance, those discharges last more than 20ms, the controller could activate the relay and generate false positive (due to discharges and not to real pressure increase).

Outline Drawing



Dimensions: millimeters [inches]

Ordering Information

Description	Part Number 4UHV	Part Number 4UHV Fast Response
4UHV Controller 1x200W Negative	9299010	9299010M1000
4UHV Controller 1x200W Positive	9299011	9299011M1000
4UHV Controller 2X80W Negative	9299200	9299200M1000
4UHV Controller 2X80W Positive	9299201	9299201M1000
4UHV Controller 2x200W Negative	9299020	9299020M1000
4UHV Controller 2x200W Positive	9299021	9299021M1000
4UHV Controller 1x200W Positive & 1x200W Negative	9299022	9299022M1000
4UHV Controller 4X80W Negative	9299400	9299400M1000
4UHV Controller 4X80W Positive	9299401	9299401M1000
4UHV Controller 2x80W Positive & 2x80W Negative	9299402	9299402M1000
4UHV Controller 2x80W Negative & 1X200W Negative	9299210	9299210M1000
4UHV Controller 2x80W Positive & 1x200W Positive	9299211	9299211M1000
4UHV Controller 2x80W Positive & 1x200W Negative	9299212	9299212M1000
4UHV Controller 2x80W Negative & 1X200W Positive	9299213	9299213M1000
4UHV Controller 1x200W Negative, Ethernet	7299010	7299010M1000
4UHV Controller 1x200W Positive, Ethernet	7299011	7299011M1000
4UHV Controller 2X80W Negative, Ethernet	7299200	7299200M1000
4UHV Controller 2X80W Positive, Ethernet	7299201	7299201M1000
4UHV Controller 2x200W Negative, Ethernet	7299020	7299020M1000
4UHV Controller 2x200W Positive, Ethernet	7299021	7299021M1000
4UHV Controller 1x200W Positive & 1x200W Negative, Ethernet	7299022	7299022M1000
4UHV Controller 4X80W Negative, Ethernet	7299400	7299400M1000
4UHV Controller 4X80W Positive, Ethernet	7299401	7299401M1000
4UHV Controller 2x80W Positive & 2x80W Negative, Ethernet	7299402	7299402M1000
4UHV Controller 2x80W Negative & 1X200W Negative, Ethernet	7299210	7299210M1000
4UHV Controller 2x80W Positive & 1x200W Positive, Ethernet	7299211	7299211M1000
4UHV Controller 2x80W Positive & 1x200W Negative, Ethernet	7299212	7299212M1000
4UHV Controller 2x80W Negative & 1X200W Positive, Ethernet	7299213	7299213M1000
4UHV Controller 1x200W Negative, Profibus	8299010	8299010M1000
4UHV Controller 1x200W Positive, Profibus	8299011	8299011M1000
4UHV Controller 2X80W Negative, Profibus	8299200	8299200M1000
4UHV Controller 2X80W Positive, Profibus	8299201	8299201M1000
4UHV Controller 2x200W Negative, Profibus	8299020	8299020M1000
4UHV Controller 2x200W Positive, Profibus	8299021	8299021M1000
4UHV Controller 1x200W Positive & 1x200W Negative, Profibus	8299022	8299022M1000
4UHV Controller 4X80W Negative, Profibus	8299400	8299400M1000
4UHV Controller 4X80W Positive, Profibus	8299401	8299401M1000
4UHV Controller 2x80W Positive & 2x80W Negative, Profibus	8299402	8299402M1000
4UHV Controller 2x80W Negative & 1X200W Negative, Profibus	8299210	8299210M1000
4UHV Controller 2x80W Positive & 1x200W Positive, Profibus	8299211	8299211M1000
4UHV Controller 2x80W Positive & 1x200W Negative, Profibus	8299212	8299212M1000
4UHV Controller 2x80W Negative & 1X200W Positive, Profibus	8299213	8299213M1000

Accessories and Cables *

HV bakeable cable, radiation resistant, 4 m (13 ft.), with Interlock	9290705
HV bakeable cable, radiation resistant, 7 m (23 ft.), with Interlock	9290707
HV bakeable cable, radiation resistant, 10 m (33 ft.), with Interlock	9290708
HV bakeable cable, radiation resistant, 20 m (66 ft.), with Interlock	9290709
Rack adapter 19"	9290064
Mains cable NEMA Plug, 3 m (10 ft.)	9699958
Mains cable European Plug, 3 m (10 ft.)	9699957

(*) The unit does not include the power cable, please order the cable separately.



How much power do I need for my ion pumps?

Power requirements depend on the pump size and starting pressure; the larger the pump and higher the starting pressure, the higher the power consumption. The large size Ion Pump 500 L/s, for example, can be easily started with 200 W up to 10^{-5} mbar, while a medium size pump (75 L/s) needs less than 80 W to be started at the same pressure, and 80 W are sufficient to operate a 500 L/s in the typical ion pump operating range (below 2×10^{-6} mbar).



Why was the higher power rating necessary in the past?

In the past, ion pumps were started with the aid of sorption pumps, able to reach 10^{-4} mbar only. As a consequence, much larger and more powerful ion pumps controller were needed. Starting at such high pressures shortened the life of the ion pumps (1 minute of operation at 10^{-4} mbar is equivalent to two months at 10^{-9} mbar). Today's oil-free turbo pumps, backed by oil-free primary pumps, achieve lower pressures, reducing the starting pressure of the ion pump. This reduces the maximum power requirement of the ion pump controller and extends the lifetime of the ion pump.



Negative or positive?

The requirement of negative or positive potential depends on the pumping element installed in the ion pump. Diode style elements (Diode and Noble Diode) need positive voltages, while Triode style elements (old style Triode and StarCell) need negative voltages for operation.



Is a fast response version available?

In addition to the standard 4UHV version, the new 4UHV Ion Pump Controller Fast Response can be used whenever the output signal is crucial to trigger a fast response in the acquisition process and/or to trigger an action (i.e. close a valve when a sudden pressure increase is detected).

IPCMini Single Channel Ion Pump Controller



Innovation at your touch

The IPCMini ion pump controller, with an intuitive 3.5-inch touch panel, enables powering, control, and monitoring of ion pumps ranging from 0.2 to 500 L/s, and ensures a completely new user experience.

- Touch screen
- High current resolution (1nA) for accurate reading in the low pressure range
- New iSTEP voltage function improves start up in the low pressure range
- I/O response time <10 ms
- Front panel USB port for data acquisition
- ¼-inch rack
- RS-232/485 computer interface

Technical Specifications

Specification		Specification	
Input voltage	100 - 240 Vac (+/-10 %)	Voltage measurement	Resolution 100 V (+/- 5 %)
Input frequency	50/60 Hz	Current resolution	1 nA
Input power	160 VA	Ripple noise	20 V
Output high voltage	+/- 7000 Vdc +/- 5 %	Weight	1.9 kg (4.2 lb)
Output high voltage short circuit current	20 mA	Installation category	II
Output high voltage power max	40 W	Max altitude	2000 m
Operating temperature	0 °C to 45 °C	Pollution degree	2
Storage temperature	-40 °C to +70 °C	Communications	RS-232/485 standard Ethernet optional
Compliance with:			
EN 61010-1 2010: Safety requirements for electrical equipment for measurement, control, and laboratory use			
EN 61326-1 2013: Electrical equipment for measurement, control, and laboratory use - EMC requirements (Cl. A)			

Ordering Information

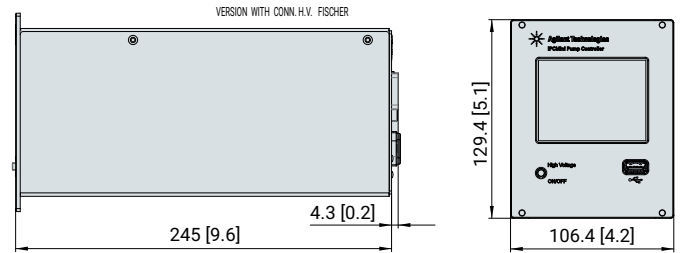
Controller Selection	Part Numbers
IPCMini standard unit	
IPCMini, 110/220 V Fischer high voltage, neg.	X3602-64000
IPCMini, 110/220 V Fischer high voltage, pos.	X3602-64001
IPCMini, 24 VDC, Fischer high voltage, neg.	X3602-64002
IPCMini, 24 VDC, Fischer high voltage, pos.	X3602-64003
IPCMini, 110/220 V King high voltage, neg.	X3602-64020
IPCMini, 110/220 V King high voltage, pos.	X3602-64021
IPCMini, 24 VDC, King high voltage, neg.	X3602-64022
IPCMini, 24 VDC, King high voltage, pos.	X3602-64023

IPCMini with Ethernet	
IPCMini, 110/220 V Fischer high voltage, neg., Ethernet	X3602-64010
IPCMini, 110/220 V Fischer high voltage, pos., Ethernet	X3602-64011
IPCMini, 24 VDC, Fischer high voltage, neg., Ethernet	X3602-64012
IPCMini, 24 VDC, Fischer high voltage, pos., Ethernet	X3602-64013
IPCMini, 110/220 V King high voltage, neg., Ethernet	X3602-64030
IPCMini, 110/220 V King high voltage, pos., Ethernet	X3602-64031
IPCMini, 24 VDC, King high voltage, neg., Ethernet	X3602-64032
IPCMini, 24 VDC, King high voltage, pos., Ethernet	X3602-64033

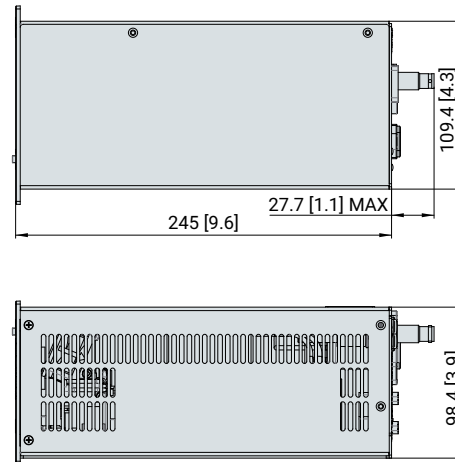
Accessories	
I/O adapter MiniVac/MicroVac to IPCMini	X3602-68001
Interlock adapter, IPCMini to Safeconn	X3602-68002
RS-232 cable	X3602-68003

Power cord selection	
Mains cable, NEMA plug, 3 m (10 ft)	9699958
Mains cable, European plug, 3 m (10 ft)	9699957
Power cord, China plug, 10A	8121-0723

Version with Fischer Connector



Version with King Connector



Dimensions: mm [inches]

High Voltage Cables	Part Numbers
High voltage cable for miniature pumps, 2.5 m (8 ft)	9240122
High voltage radiation resistant cable, 4 m (13 ft) Fischer - King	9290706
High voltage radiation resistant cable, 4 m (13 ft) Fischer - Fischer	9290705
High voltage radiation resistant cable, 7 m (23 ft) Fischer - Fischer	9290707
High voltage radiation resistant cable, 10 m (33 ft) Fischer - Fischer	9290708
High voltage radiation resistant cable, 20 m (66 ft) Fischer - Fischer	9290709
High voltage cable bakeable, 4 m (13 ft) StarCell - Fischer	9290710
High voltage cable bakeable, 4 m (13 ft) Old Varian - Fischer	9290712
High voltage cable w/o interlock, SHV, 4 m (13 ft) SHV - Fischer	9290710M023
High voltage cable w/o interlock, SHV, 7 m (23 ft) SHV - Fischer	9290710M024
High voltage cable w/o interlock, SHV, 10 m (33 ft) SHV - Fischer	9290710M025
High voltage cable w/o interlock, SHV, 20 m (66 ft) SHV - Fischer	9290710M024

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